(#2)

Access DB# 179212

SEARCH REQUEST FORM

Scientific and Technical Information Center

Requester's Full Name: Sin J. Lee Examiner #: 76060 Date: 2-8-06
Art Unit: 1752 Phone Number ~~30~~ 2-1333 Serial Number: 10/224,980
Mail Box and Bldg/Room Location: 9D60 (Rem.) Results Format Preferred (circle): PAPER DISK E-MAIL

If more than one search is submitted, please prioritize searches in order of need.

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Please provide a detailed statement of the search topic, and describe as specifically as possible the subject matter to be searched. Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers, and combine with the concept or utility of the invention. Define any terms that may have a special meaning. Give examples or relevant citations, authors, etc, if known. Please attach a copy of the cover sheet, pertinent claims, and abstract.

Title of Invention: Plz. see Bib.

Inventors (please provide full names):

Earliest Priority Filing Date:

**For Sequence Searches Only* Please include all pertinent information (parent, child, divisional, or issued patent numbers) along with the appropriate serial number.*

— Please search for a composition of Cl. #13 (attached here) which contains those highlighted components (Please use those formulas of Cl. #14 for the "vinyl ether methacrylates" or "vinylether acrylates".) ✓

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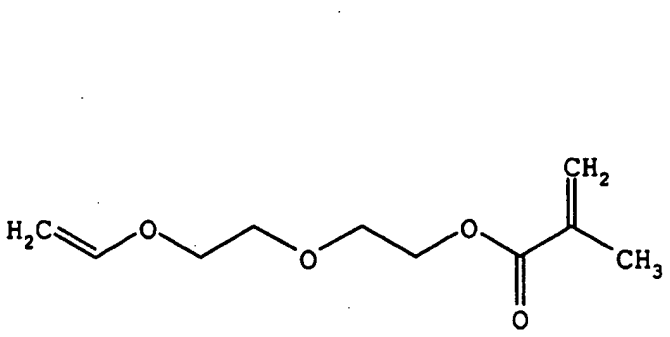
STAFF USE ONLY	Type of Search	Vendors and cost where applicable
Searcher: EJ	NA Sequence (#)	STN
Searcher Phone #:	AA Sequence (#)	Dialog
Searcher Location:	Structure (#)	Questel/Orbit
Date Searcher Picked Up:	Bibliographic	Dr.Link
Date Completed: 2-10-06	Litigation	Lexis/Nexis
Searcher Prep & Review Time:	Fulltext	Sequence Systems
Clerical Prep Time:	Patent Family	WWW/Internet
Online Time:	Other	Other (specify)

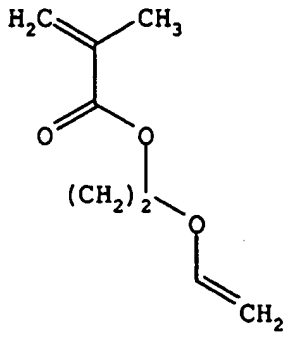
PTO-1590 (8-01)

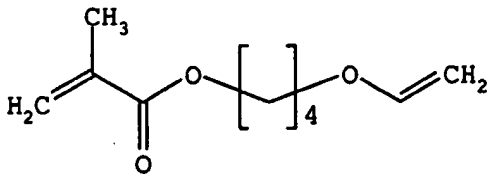
139, 154, 151, 180, 185, Pigment Red 122, 22, 23, 17, 210, 170, 188, 185, 146, 144, 176, 57:1, 184, 202, 206, 207; Pigment Blue 15:3, Pigment Blue 15:2, Pigment Blue 15:1, Pigment Blue 15:4, Pigment Blue 15:6, Pigment Blue 16, and carbon black.

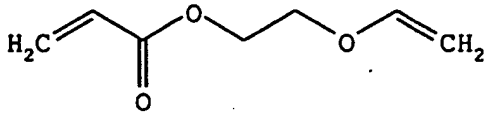
13. (currently amended) A radiation curable ink composition comprising at least one initiator and at least one polyhedral oligomeric silsesquioxane (POSS) represented by the following empirical formula $[R(SiO_{1.5})]_n$ wherein n=4,6,8,10,12,14,16 and larger and each R is independently hydrogen, an inorganic group, an alkyl group, an alkylene group, an aryl group, an arylene group, or non-heterocyclic group-containing organo-functional derivatives of alkyl, alkylene, aryl or arylene groups wherein said radiation curable ink composition contains at least one colorant in a concentration between 0.5 and 20 percent by weight based on the total weight of said radiation curable ink composition ~~Radiation curable ink composition according to claim 1~~, wherein said composition further comprises at least one photopolymerizable compound selected from the group consisting of vinylether methacrylates and vinylether acrylates.

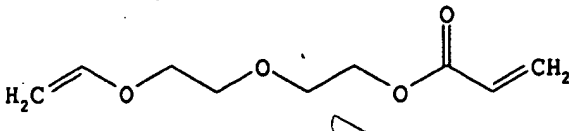
14.(original) Radiation curable ink composition according to claim 13, wherein said vinylether methacrylate or vinylether acrylate is selected from group consisting of:











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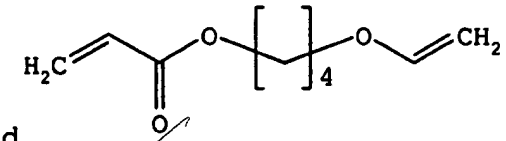

15.(original) Radiation curable ink composition according to claim 1, wherein said ink composition further contains a second photopolymerizable monomer, oligomer or prepolymer.

16.(original) Radiation curable ink composition according to claim 15, wherein said second monomer is selected from the

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BIBDATASHEET

Bib Data Sheet

CONFIRMATION NO. 9601

SERIAL NUMBER	FILING DATE	CLASS	GROUP ART UNIT	ATTORNEY DOCKET NO.
10/774,980	02/09/2004 RULE	430	1752	27500-GN03027

APPLICANTS

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Johan Loccufier, Zwijaarde, BELGIUM;
Roland Claes, Dendermonde, BELGIUM;

** CONTINUING DATA **********

This appln claims benefit of 60/455,606 03/17/2003 SJL

** FOREIGN APPLICATIONS **********

EUROPEAN PATENT OFFICE (EPO) 03100462.5 02/26/2003 SJL

IF REQUIRED, FOREIGN FILING LICENSE GRANTED
** 05/05/2004

Foreign Priority claimed ☑ yes ☐ no 35 USC 119 (a-d) conditions met ☑ yes ☐ no ☐ Met after Allowance Verified and Acknowledged Examiner's Signature SJL Initials	STATE OR COUNTRY BELGIUM	SHEETS DRAWING 0	TOTAL CLAIMS 30	INDEPENDENT CLAIMS 2

ADDRESS
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Nexsen Pruet Jacobs & Pollard LLP
201 W. McBee Avenue
Greenville , SC
29603

TITLE
Radiation curable ink compositions suitable for ink-jet printing

FILING FEE	FEES: Authority has been given in Paper No. _____ to charge/credit DEPOSIT ACCOUNT No. _____ for following:	☐ All Fees ☐ 1.16 Fees (Filing) ☐ 1.17 Fees (Processing Ext. of time)

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L2              5 S L1
L3            602 S L1 FUL
                  SAV L3 LEE980/A

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L6                STR L4
L7              0 S L6 SSS SAM SUB=L3
L8              0 S L6 SSS FUL SUB=L3

     FILE 'HCA'
L9            375 S L3
L10          9883 S ?SILSESQUIOXAN?
L11             7 S L9 AND L10

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L12           563 S L3 NOT SI/ELS
L13            15 S L6
L14               SCR 1735 OR 1549
L15            16 S L6 AND L14
L16          7494 S L6 AND L14 FUL
                  SAV L16 LEE980A/A

     FILE 'HCA'
L17         15783 S L16
L18             7 S (L17 OR L10) AND L9

     FILE 'HCAPLUS'
L19           157 S VANMAELE ?/AU OR VAN MAELE ?/AU OR MAELE ?/AU
L20            99 S LOCCUFIER ?/AU
L21           894 S CLAES ?/AU
L22             2 S L19 AND L20 AND L21
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                SEL L23 6,7,8,9,11 RN
L24            5 S E14-E18

     FILE 'HCA'
L25           18 S L24
L26            0 S L25 AND L9

     FILE 'REGISTRY'
L27       199542 S (C(L)H(L)O(L)SI)/ELS (L) 4/ELC.SUB AND RSD/FA

     FILE 'HCA'
L28        91457 S L27
L29          364 S L12
L30           17 S L28 AND L29
L31            3 S L30 AND (L17 OR L10)
L32            7 S L11 OR L18 OR L31
L33           14 S L30 NOT L32

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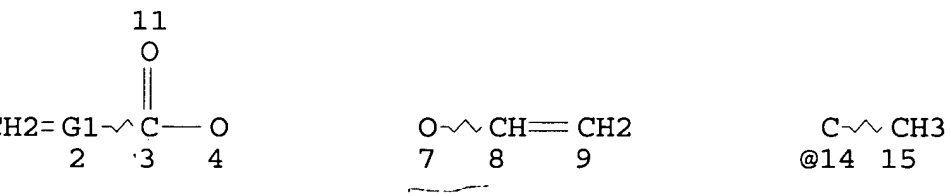


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STEREO ATTRIBUTES: NONE
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VAR G1=X/OH
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L32  ANSWER 1 OF 7  HCA  COPYRIGHT 2006 ACS on STN
144:14223  Antireflecting polarizing plates with good moisture and
     weather resistance, uniform in-plane color, durability, and
     neutralization for image display devices.  Kato, Eiichi; Yoneyama,
     Hiroyuki; Nakamura, Kazuhiro (Fuji Photo Film Co., Ltd., Japan).
```

PCT Int. Appl. WO 2005114271 A1 20051201, 184 pp. DESIGNATED STATES: W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KM, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SM, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW; RW: AT, BE, BF, BJ, CF, CG, CH, CI, CM, CY, DE, DK, ES, FI, FR, GA, GB, GR, IE, IS, IT, LU, MC, ML, MR, NE, NL, PT, SE, SN, TD, TG, TR. (Japanese). CODEN: PIXXD2. APPLICATION: WO 2005-JP9266 20050520. PRIORITY: JP 2004-150223 20040520; JP 2004-227204 20040803.

AB Title big polarizing plates free from external light reception comprise a polarizing film of polyvinyl alc. and, superimposed on both major surface sides thereof, cellulose acylate films as a protective film whose one-side cellulose acylate film is coated with an antireflection film of multilayer structure, wherein the surface of the polarizing film side of cellulose acylate films are alkali sapond. so that after the alkali sapon. treatment, the uneveness of the surface of the polarizing film side has an specific configuration. This 474 parts cellulose acrylate soln. comprising cellulose triacetate 100, triphenylphosphate 1.0, plasticizers 10.0, UV-absorbers 1.3, methylene chloride 300, methanol 54, and 1-butanol 11 parts and 15.3 parts fine particle dispersion comprising Aerosil R 812 2.00, cellulose triacetate 2.00, a phosphate-based dispersant 0.25, methylene chloride 78.70, methanol 14.20, and 1-butanol 2.86 parts were mixed, cast onto a metal substrate (av. roughness 0.006 .mu.m, max. height 0.06 .mu.m), dried at 50.degree., and stretched to give a protective film with curl -0.3/m, haze 0.2%, av. roughness 0.003 .mu.m, moisture permeability 1050 g/m2.cntdot.24 h, and tear strength 12.4 g. A hardcoat compn. comprising TMPTA (trimethylolpropane triacrylate), polyglycidyl methacrylate, Irgacure 184, di(tert-butylphenyl)iodonium hexafluorophosphate was applied on a the resulting protective film, irradiated with an UV-ray, coated with an intermediate refractive coating comprising cobalt titanium oxide particles, DPHA (acrylic monomer mixt.), Irgacure 907, and Kayacure DETX, irradiated with an UV-ray, coated with a high refractive coating comprising DPHA, cobalt titanium oxide particles, Kayacure DETX, and Irgacure 907, irradiated with an UV-ray, coated with a low refractive coating comprising DPHA, an acrylate-contg. fluoropolymer, KBM 5103 sol, RMS 033 (polysiloxane acrylate), and hollow silica, and irradiated with an UV-ray to give an antireflective film with dynamic frictional const. 0.12, good adhesion, pencil hardness, uniform in-plane color, weather and abrasion resistance, surface energy 25 mN/m, and mirror plane reflectance 0.35%.

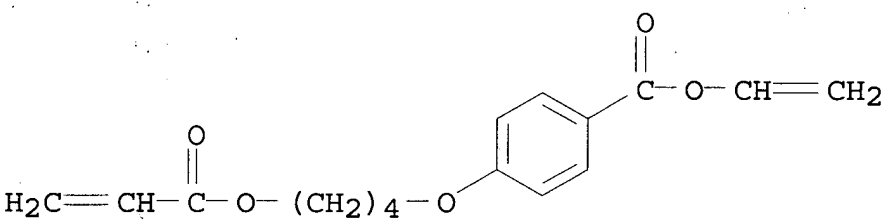
IT **211913-71-2P**

(antireflecting polarizing plates with good moisture and weather resistance, uniform in-plane color, durability, and

neutralization for image display devices)
RN 211913-71-2 HCA
CN Benzoic acid, 4-[4-[(1-oxo-2-propenyl)oxy]butoxy]-, ethenyl ester, polymer with ethenol, ethenyl acetate and pentanedial (9CI) (CA INDEX NAME)

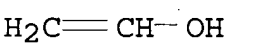
CM 1

CRN 182154-44-5
CMF C16 H18 O5



CM 2

CRN 557-75-5
CMF C2 H4 O



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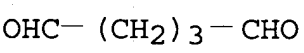
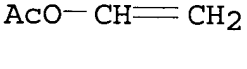
CRN 111-30-8
CMF C5 H8 O2



CM 4

CRN 108-05-4
CMF C4 H6 O2



IT **646508-62-5DP**, polymers with polysiloxane acrylates, **silsesquioxane** acrylates, and acrylic monomers

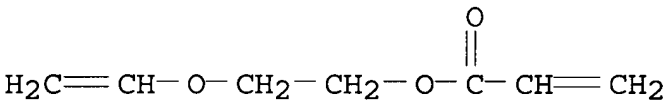
(assumed monomers, low refractive layer; antireflecting polarizing plates with good moisture and weather resistance, uniform in-plane color, durability, and neutralization for image display devices)

RN 646508-62-5 HCA

CN 2-Propenoic acid, 2-(ethenyloxy)ethyl ester, polymer with 1,1,2,3,3,3-hexafluoro-1-propene (9CI) (CA INDEX NAME)

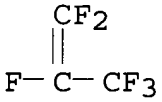
CM 1

CRN 41440-38-4
CMF C7 H10 O3



CM 2

CRN 116-15-4
CMF C3 F6



IC ICM G02B005-30
ICS B29C055-02; B32B007-02; B32B023-00; G02B001-11; G02F001-1335; B29K029-00; B29L011-00

CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38, 42, 73

ST antireflecting polarizing plate moisture weather resistance uniform inplane color; durability neutralization image display device; Aerosil cellulose triacetate protective film; cobalt titanium oxide acrylic polymer low particle refractive layer; acrylic fluoropolymer polysiloxane **silsesquioxane** hollow silica low refractive layer

IT **Silsesquioxanes**
(acrylic-polysiloxane-, fluoropolymer-, low refractive layer; antireflecting polarizing plates with good moisture and weather resistance, uniform in-plane color, durability, and neutralization for image display devices)

IT Polysiloxanes, properties
(acrylic-**silsesquioxane**-, fluoropolymer-, low

refractive layer; antireflecting polarizing plates with good moisture and weather resistance, uniform in-plane color, durability, and neutralization for image display devices)

IT Polysiloxanes, preparation
(methacrylate-, X 22-164C, polymers with acrylic monomers and acrylate-contg. **silsesquioxane** for low refractive layer; antireflecting polarizing plates with good moisture and weather resistance, uniform in-plane color, and durability)

IT Acrylic polymers, properties
(polysiloxane-**silsesquioxane**-, fluoropolymer-, low refractive layer; antireflecting polarizing plates with good moisture and weather resistance, uniform in-plane color, durability, and neutralization for image display devices)

IT **Silsesquioxanes**
(silicate-, fluorine-contg., low refractive layer; antireflecting polarizing plates with good moisture and weather resistance, uniform in-plane color, durability, and neutralization for image display devices)

IT Fluoropolymers, preparation
(silicate-**silsesquioxane**-, low refractive layer; antireflecting polarizing plates with good moisture and weather resistance, uniform in-plane color, durability, and neutralization for image display devices)

IT **211913-71-2P**
(antireflecting polarizing plates with good moisture and weather resistance, uniform in-plane color, durability, and neutralization for image display devices)

IT **646508-62-5DP**, polymers with polysiloxane acrylates, **silsesquioxane** acrylates, and acrylic monomers
(assumed monomers, low refractive layer; antireflecting polarizing plates with good moisture and weather resistance, uniform in-plane color, durability, and neutralization for image display devices)

IT 29570-58-9DP, DPHA, polymers with polysiloxane acrylates, **silsesquioxane** acrylates, and acrylate-contg. fluoropolymers 160716-45-0DP, KBM 5103 homopolymer, polymers with polysiloxane acrylate, acrylate-contg. fluoropolymers, and acrylic monomers
(low refractive layer; antireflecting polarizing plates with good moisture and weather resistance, uniform in-plane color, durability, and neutralization for image display devices)

L32 ANSWER 2 OF 7 HCA COPYRIGHT 2006 ACS on STN
143:376626 Highly crosslinkable and storage-stable resin compositions, their antireflection films, manufacture of the films, and polarizers and electrooptical displays using the films. Omatsu, Tadashi (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2005283849 A2 20051013, 76 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2004-95945 20040329.

AB The compns., which are for forming a low-refractive index layer on the outer surface of an antireflection film having multiple layers on a transparent substrate, contain polymers having radically polymerizable groups, wherein the ratio of the polymerizable group content after coating before curing to that before coating is .gtoreq.0.8. The reaction ratio of the polymerizable groups after curing is preferable .gtoreq.60 mol%. The compns. are cured by irradiating with UV or electron beams at O concn. on the surface .ltoreq.1 vol.%. The polarizers are useful for liq. crystal displays (LCD).

IT **623962-01-6P 848665-38-3P 866413-66-3P**
866413-67-4P 866413-69-6P 866413-70-9P
866413-72-1P 866413-73-2P 866413-74-3P
866413-78-7P 866413-80-1P 866413-82-3P
(highly crosslinkable and storage-stable resin compns. for antireflection films of liq. crystal displays)

RN 623962-01-6 HCA

CN 2-Propenoic acid, 2-(ethenyloxy)ethyl ester, polymer with 2-(ethenyloxy)ethanol and 1,1,2,3,3,3-hexafluoro-1-propene (9CI) (CA INDEX NAME)

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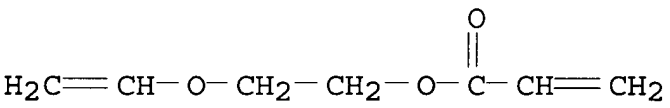
CRN 41440-38-4
CMF C7 H10 O3



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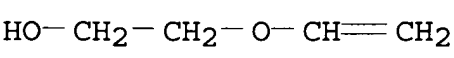

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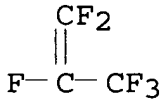
CRN 116-15-4
CMF C3 F6



RN 848665-38-3 HCA
CN 2-Propenoic acid, 2-methyl-, 2-(ethenyloxy)ethyl ester, polymer with 2-(ethenyloxy)ethanol and 1,1,2,3,3,3-hexafluoro-1-propene (9CI) (CA INDEX NAME)

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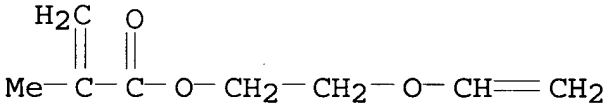

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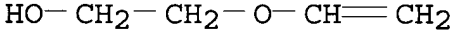

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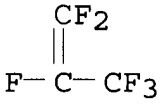
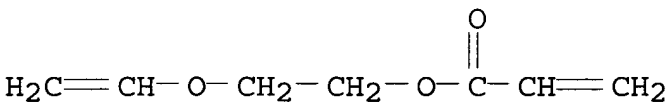
CRN 116-15-4
CMF C3 F6



RN 866413-66-3 HCA
CN 2-Propenoic acid, 2-methyl-, 2-(ethenyloxy)ethyl ester, polymer with 2-(ethenyloxy)ethanol, 2-(ethenyloxy)ethyl 2-propenoate and 1,1,2,3,3,3-hexafluoro-1-propene (9CI) (CA INDEX NAME)

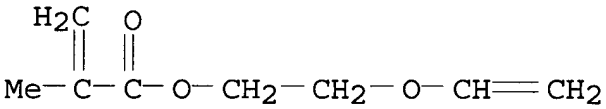
CM 1

CRN 41440-38-4
CMF C7 H10 O3



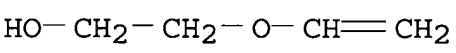
CM 2

CRN 1464-69-3
CMF C8 H12 O3



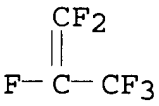
CM 3

CRN 764-48-7
CMF C4 H8 O2



CM 4

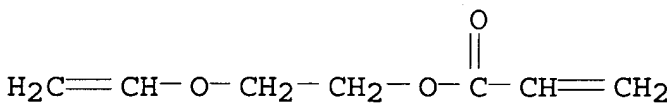
CRN 116-15-4
CMF C3 F6



RN 866413-67-4 HCA
CN 2-Propenoic acid, 2-methyl-, 2-(ethenyloxy)ethyl ester, polymer with 2-(ethenyloxy)ethanol, 2-(ethenyloxy)ethyl 2-propenoate, 1,1,2,3,3,3-hexafluoro-1-propene and 2-[[3-[(1-oxo-2-propenyl)oxy]-2,2-bis[[(1-oxo-2-propenyl)oxy]methyl]propoxy]methyl]-2-[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl di-2-propenoate (9CI) (CA INDEX NAME)

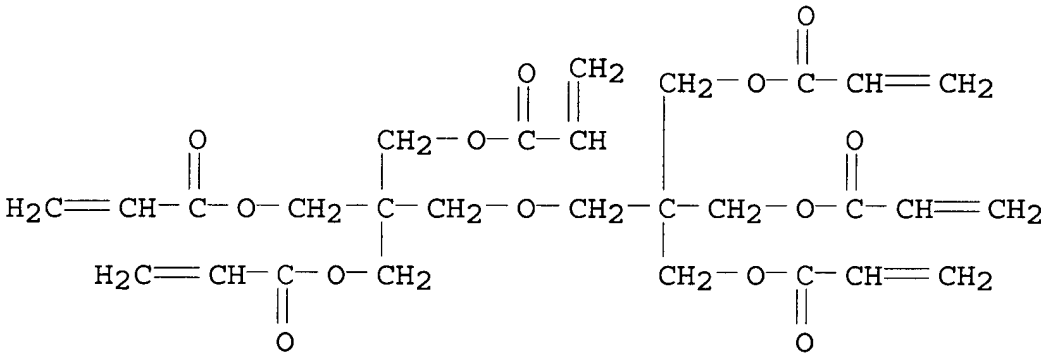
CM 1

CRN 41440-38-4
CMF C7 H10 O3



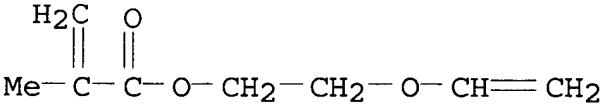
CM 2

CRN 29570-58-9
CMF C28 H34 O13



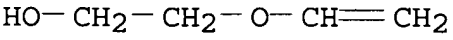
CM 3

CRN 1464-69-3
CMF C8 H12 O3



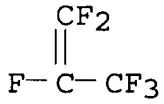
CM 4

CRN 764-48-7
CMF C4 H8 O2



CM 5

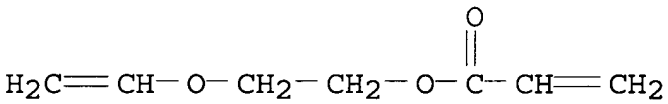
CRN 116-15-4
CMF C3 F6



RN 866413-69-6 HCA
CN 2-Propenoic acid, 2-methyl-, 2-(ethenyloxy)ethyl ester, polymer with 2-(ethenyloxy)ethyl 2-propenoate and 1,1,2,3,3,3-hexafluoro-1-propene (9CI) (CA INDEX NAME)

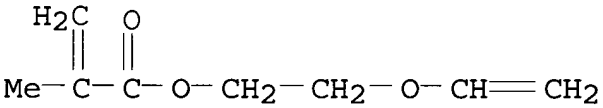
CM 1

CRN 41440-38-4
CMF C7 H10 O3



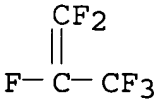
CM 2

CRN 1464-69-3
CMF C8 H12 O3



CM 3

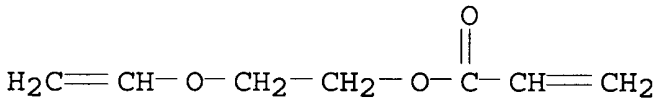
CRN 116-15-4
CMF C3 F6



RN 866413-70-9 HCA
CN 2-Propenoic acid, 2-methyl-, 2-(ethenyloxy)ethyl ester, polymer with 2-(ethenyloxy)ethyl 2-propenoate, 1,1,2,3,3,3-hexafluoro-1-propene and 2-[[3-[(1-oxo-2-propenyl)oxy]-2,2-bis[[(1-oxo-2-propenyl)oxy]methyl]propoxy]methyl]-2-[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl di-2-propenoate (9CI) (CA INDEX NAME)

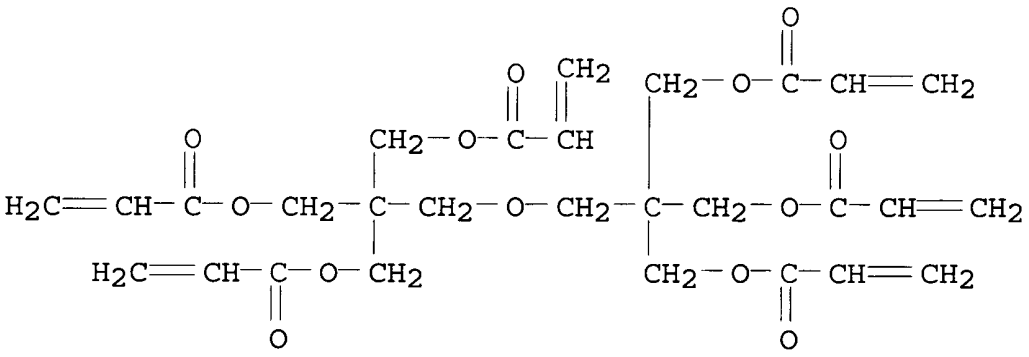
CM 1

CRN 41440-38-4
CMF C7 H10 O3



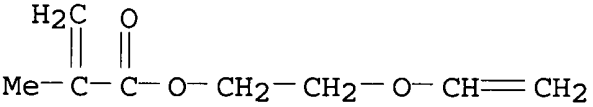
CM 2

CRN 29570-58-9
CMF C28 H34 O13



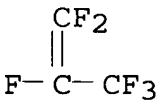
CM 3

CRN 1464-69-3
CMF C8 H12 O3



CM 4

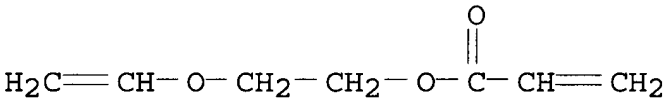
CRN 116-15-4
CMF C3 F6



RN 866413-72-1 HCA
CN 2-Propenoic acid, 2-[[3-[(1-oxo-2-propenyl)oxy]-2,2-bis[[(1-oxo-2-propenyl)oxy]methyl]propoxy]methyl]-2-[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl ester, polymer with 2-(ethenyloxy)ethanol, 2-(ethenyloxy)ethyl 2-propenoate and 1,1,2,3,3,3-hexafluoro-1-propene (9CI) (CA INDEX NAME)

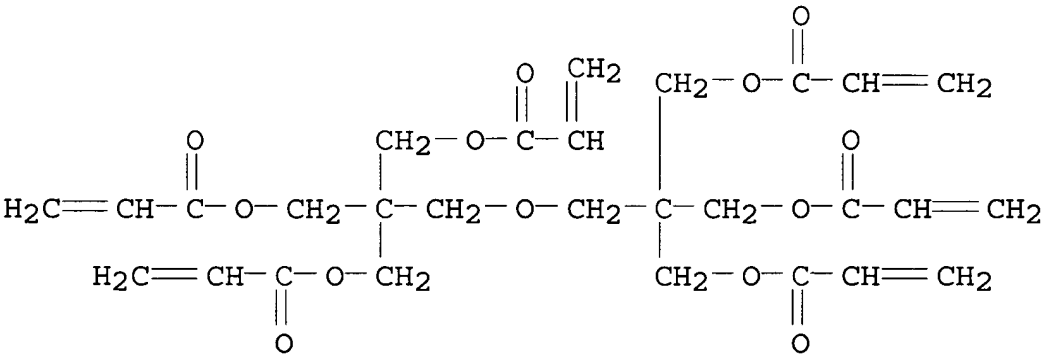
CM 1

CRN 41440-38-4
CMF C7 H10 O3



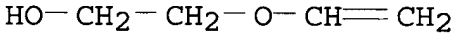
CM 2

CRN 29570-58-9
CMF C28 H34 O13



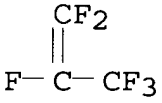
CM 3

CRN 764-48-7
CMF C4 H8 O2



CM 4

CRN 116-15-4
CMF C3 F6



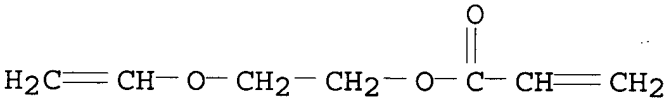
RN 866413-73-2 HCA
CN 2-Propenoic acid, 2-(ethenyloxy)ethyl ester, polymer with Ebecryl 1290K, 2-(ethenyloxy)ethanol and 1,1,2,3,3,3-hexafluoro-1-propene (9CI) (CA INDEX NAME)

CM 1

CRN 143549-97-7
CMF Unspecified
CCI PMS, MAN
*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

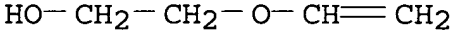
CM 2

CRN 41440-38-4
CMF C7 H10 O3



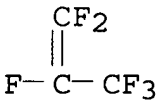
CM 3

CRN 764-48-7
CMF C4 H8 O2



CM 4

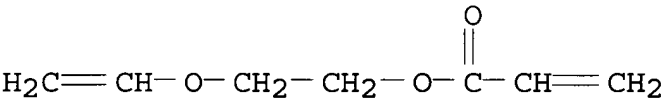
CRN 116-15-4
CMF C3 F6



RN 866413-74-3 HCA
CN 2-Propenoic acid, 2-ethyl-2-[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl ester, polymer with 2-(ethenyloxy)ethanol, 2-(ethenyloxy)ethyl 2-propenoate and 1,1,2,3,3,3-hexafluoro-1-propene (9CI) (CA INDEX NAME)

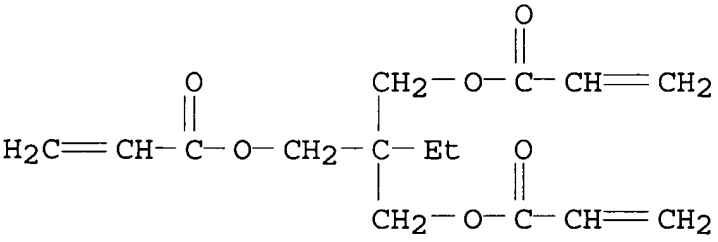
CM 1

CRN 41440-38-4
CMF C7 H10 O3



CM 2

CRN 15625-89-5
CMF C15 H20 O6

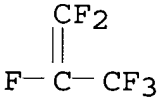


CM 3

CRN 764-48-7
CMF C4 H8 O2

CM 4

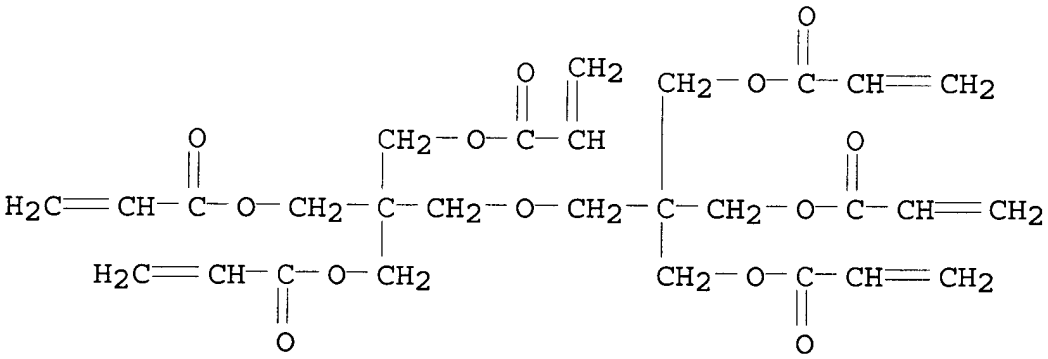
CRN 116-15-4
CMF C3 F6



RN 866413-78-7 HCA
CN 2-Propenoic acid, 2-methyl-, 2-(ethenyloxy)ethyl ester, polymer with 2-(ethenyloxy)ethanol, 1,1,2,3,3,3-hexafluoro-1-propene and 2-[[3-[(1-oxo-2-propenyl)oxy]-2,2-bis[[(1-oxo-2-propenyl)oxy]methyl]propoxy]methyl]-2-[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl di-2-propenoate (9CI) (CA INDEX NAME)

CM 1

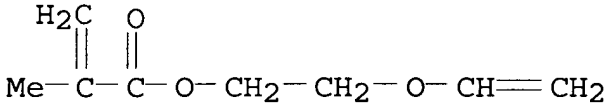
CRN 29570-58-9
CMF C28 H34 O13



CM 2

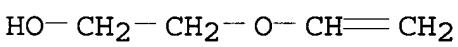
CRN 1464-69-3

CMF C8 H12 O3



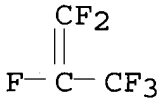
CM 3

CRN 764-48-7
CMF C4 H8 O2



CM 4

CRN 116-15-4
CMF C3 F6



RN 866413-80-1 HCA
CN 2-Propenoic acid, 2-methyl-, 2-(ethenyloxy)ethyl ester, polymer with Ebecryl 1290K, 2-(ethenyloxy)ethanol and 1,1,2,3,3,3-hexafluoro-1-propene (9CI) (CA INDEX NAME)

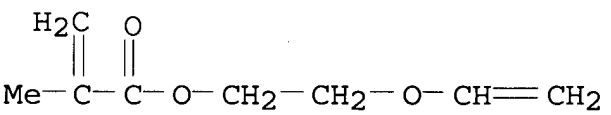
CM 1

CRN 143549-97-7
CMF Unspecified
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

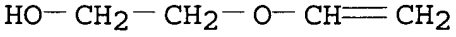
CM 2

CRN 1464-69-3
CMF C8 H12 O3



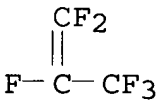
CM 3

CRN 764-48-7
CMF C4 H8 O2



CM 4

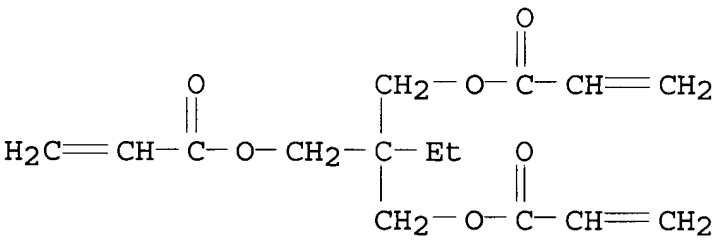
CRN 116-15-4
CMF C3 F6



RN 866413-82-3 HCA
CN 2-Propenoic acid, 2-methyl-, 2-(ethenyloxy)ethyl ester, polymer with 2-(ethenyloxy)ethanol, 2-ethyl-2-[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl di-2-propenoate and 1,1,2,3,3,3-hexafluoro-1-propene (9CI) (CA INDEX NAME)

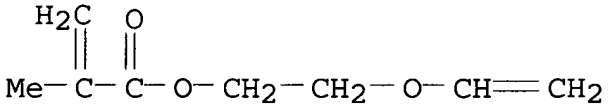
CM 1

CRN 15625-89-5
CMF C15 H20 O6



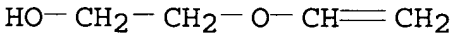
CM 2

CRN 1464-69-3
CMF C8 H12 O3



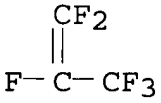
CM 3

CRN 764-48-7
CMF C4 H8 O2



CM 4

CRN 116-15-4
CMF C3 F6



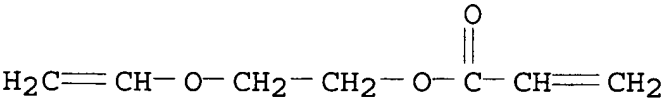
IT **866413-68-5P 866413-71-0P 866413-75-4P**
866413-84-5P
(highly crosslinkable and storage-stable resin compns. for antireflection films of liq. crystal displays)

RN 866413-68-5 HCA

CN 2-Propenoic acid, 2-methyl-, 2-(ethenyloxy)ethyl ester, polymer with 2-(ethenyloxy)ethanol, 2-(ethenyloxy)ethyl 2-propenoate, 1,1,2,3,3,3-hexafluoro-1-propene, 2-[[3-[(1-oxo-2-propenyl)oxy]-2,2-bis[[(1-oxo-2-propenyl)oxy]methyl]propoxy]methyl]-2-[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl di-2-propenoate and 3-(trimethoxysilyl)propyl 2-propenoate (9CI) (CA INDEX NAME)

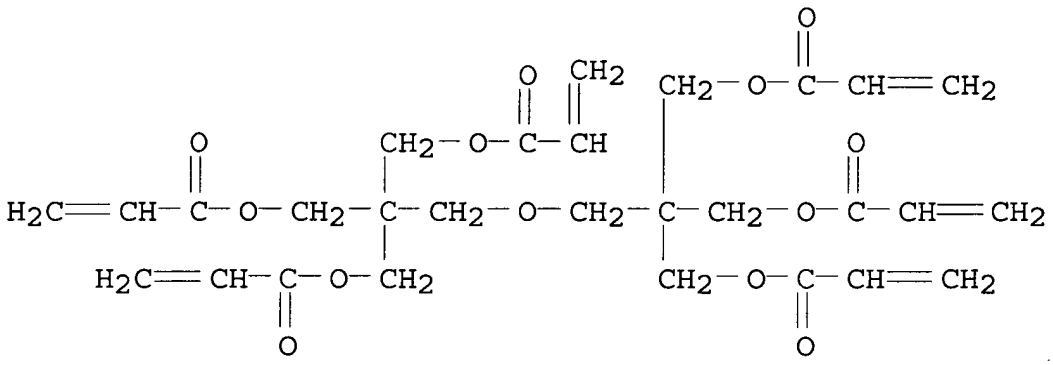
CM 1

CRN 41440-38-4
CMF C7 H10 O3



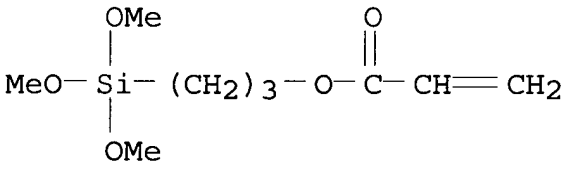
CM 2

CRN 29570-58-9
CMF C28 H34 O13



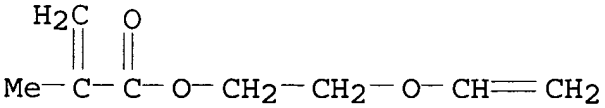
CM 3

CRN 4369-14-6
CMF C9 H18 O5 Si



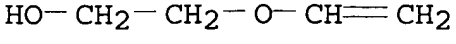
CM 4

CRN 1464-69-3
CMF C8 H12 O3



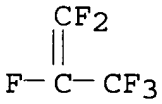
CM 5

CRN 764-48-7
CMF C4 H8 O2



CM 6

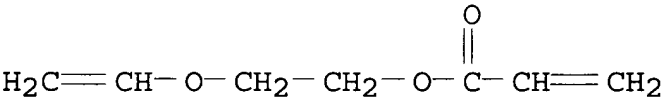
CRN 116-15-4
CMF C3 F6



RN 866413-71-0 HCA
CN 2-Propenoic acid, 2-methyl-, 2-(ethenyloxy)ethyl ester, polymer with 2-(ethenyloxy)ethyl 2-propenoate, 1,1,2,3,3,3-hexafluoro-1-propene, 2-[[3-[(1-oxo-2-propenyl)oxy]-2,2-bis[[(1-oxo-2-propenyl)oxy]methyl]propoxy]methyl]-2-[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl di-2-propenoate and 3-(trimethoxysilyl)propyl 2-propenoate (9CI) (CA INDEX NAME)

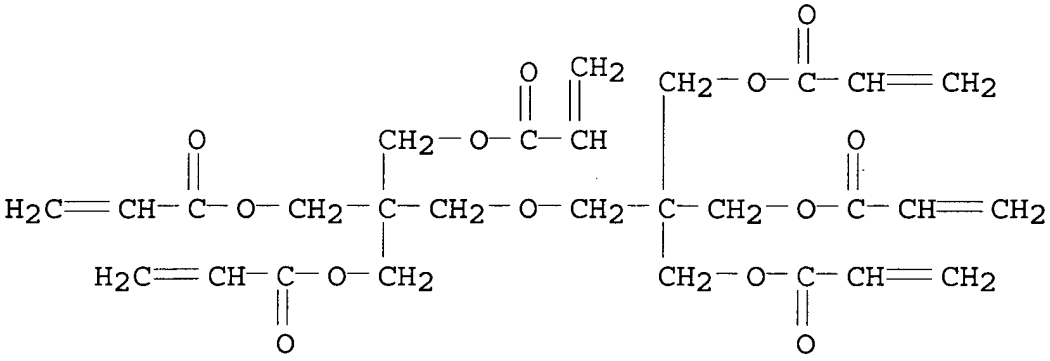
CM 1

CRN 41440-38-4
CMF C7 H10 O3



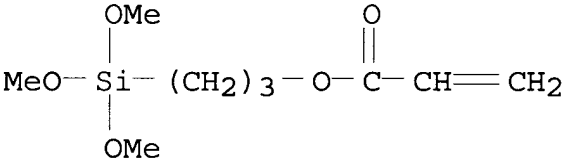
CM 2

CRN 29570-58-9
CMF C28 H34 O13



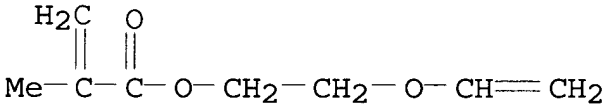
CM 3

CRN 4369-14-6
CMF C9 H18 O5 Si



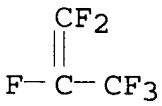
CM 4

CRN 1464-69-3
CMF C8 H12 O3



CM 5

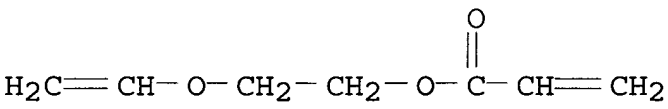
CRN 116-15-4
CMF C3 F6



RN 866413-75-4 HCA
CN 2-Propenoic acid, 2-[[3-[(1-oxo-2-propenyl)oxy]-2,2-bis[[(1-oxo-2-propenyl)oxy]methyl]propoxy]methyl]-2-[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl ester, polymer with 2-(ethenyloxy)ethanol, 2-(ethenyloxy)ethyl 2-propenoate, 1,1,2,3,3,3-hexafluoro-1-propene and 3-(trimethoxysilyl)propyl 2-propenoate (9CI) (CA INDEX NAME)

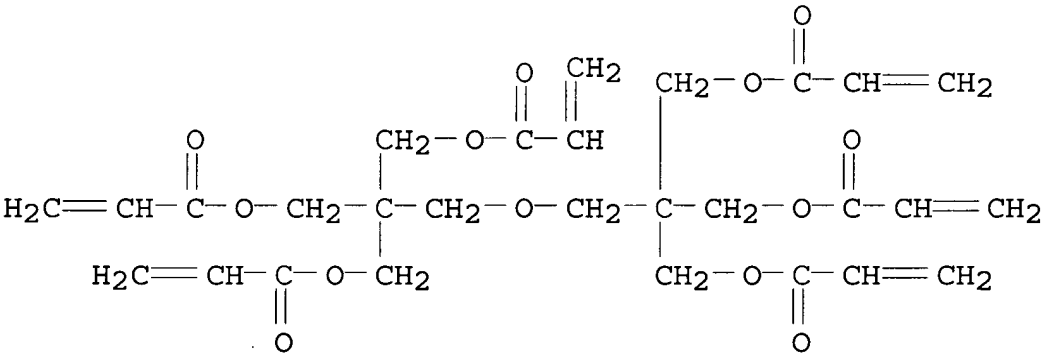
CM 1

CRN 41440-38-4
CMF C7 H10 O3



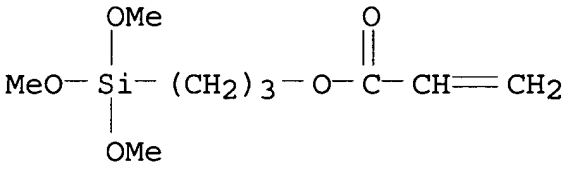
CM 2

CRN 29570-58-9
CMF C28 H34 O13



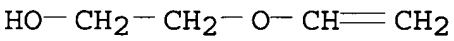
CM 3

CRN 4369-14-6
CMF C9 H18 O5 Si



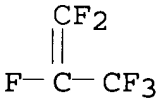
CM 4

CRN 764-48-7
CMF C4 H8 O2



CM 5

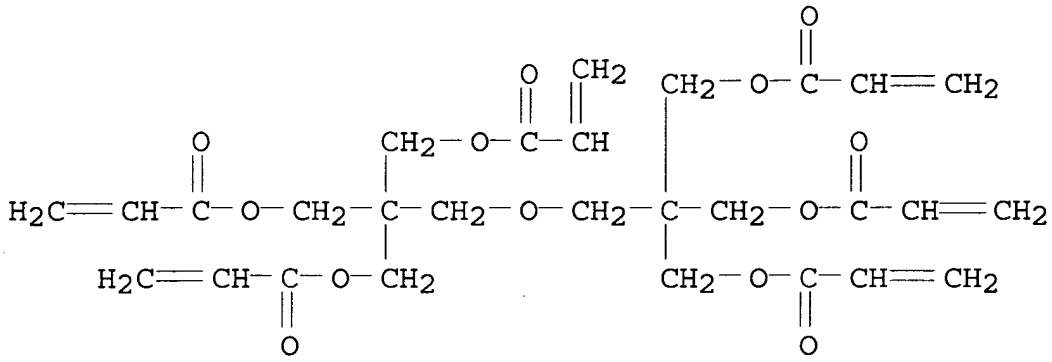
CRN 116-15-4
CMF C3 F6



RN 866413-84-5 HCA
CN 2-Propenoic acid, 2-methyl-, 2-(ethenyloxy)ethyl ester, polymer with 2-(ethenyloxy)ethanol, 1,1,2,3,3,3-hexafluoro-1-propene, 2-[[3-[(1-oxo-2-propenyl)oxy]-2,2-bis[[(1-oxo-2-propenyl)oxy]methyl]propoxy]methyl]-2-[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl di-2-propenoate and 3-(trimethoxysilyl)propyl 2-propenoate (9CI) (CA INDEX NAME)

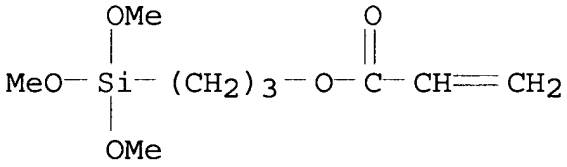
CM 1

CRN 29570-58-9
CMF C28 H34 O13



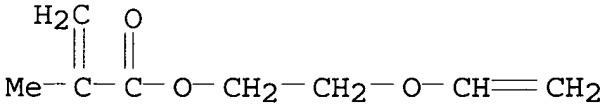
CM 2

CRN 4369-14-6
CMF C9 H18 O5 Si



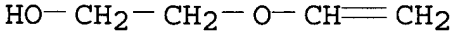
CM 3

CRN 1464-69-3
CMF C8 H12 O3



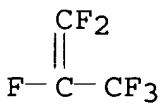
CM 4

CRN 764-48-7
CMF C4 H8 O2



CM 5

CRN 116-15-4
CMF C3 F6



IC ICM G02B001-10
ICS B05D001-28; B05D007-04; B05D007-24; B32B007-02; B32B027-30; C08F299-00; C08J007-18; G02B005-30; G02F001-1335; G02F001-1336; C08L101-00

CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38

IT **Silsesquioxanes**
(acrylic, fluorine-contg.; highly crosslinkable and storage-stable resin compns. for antireflection films of liq. crystal displays)

IT Fluoropolymers, preparation
(acrylic-**silsesquioxane**-; highly crosslinkable and storage-stable resin compns. for antireflection films of liq. crystal displays)

IT **623962-01-6P 848665-38-3P 866413-66-3P**
866413-67-4P 866413-69-6P 866413-70-9P
866413-72-1P 866413-73-2P 866413-74-3P
866413-78-7P 866413-80-1P 866413-82-3P
(highly crosslinkable and storage-stable resin compns. for antireflection films of liq. crystal displays)

IT **866413-68-5P 866413-71-0P 866413-75-4P**
866413-84-5P
(highly crosslinkable and storage-stable resin compns. for antireflection films of liq. crystal displays)

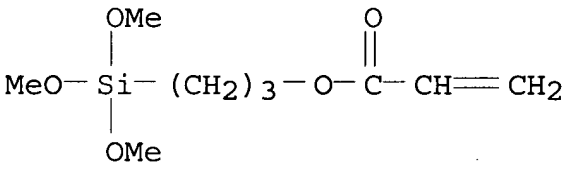
L32 ANSWER 3 OF 7 HCA COPYRIGHT 2006 ACS on STN
143:68368 Ink-jet printer heads showing excellent water repellency and wear resistance at jet ports and manufacture thereof. Ishizuka, Takahiro (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2005153390 A2 20050616, 51 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2003-397030 20031127.

AB The heads are, at around jet ports, coated with compns. of (hydrolyzed and/or partially condensed) polymerizable organosilanes and fluorine compds. followed by heating or actinic-ray exposure to form ink-repellent coatings. The compns. may contain inorg. microparticles. The coatings show long-lasting ink repellency against stress on wiping with rubber cloths.

IT **548774-43-2P**
(cured; ink-jet printer heads having repellent coatings contg. F compds. and polysiloxanes at around jet ports)
RN 548774-43-2 HCA
CN 2-Propenoic acid, 3-(trimethoxysilyl)propyl ester, polymer with trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

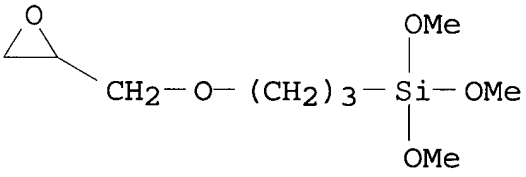
CM 1

CRN 4369-14-6
CMF C9 H18 O5 Si

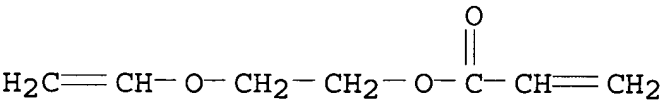


CM 2

CRN 2530-83-8
CMF C9 H20 O5 Si



IT **41440-38-4D**, polymers
(ink-jet printer heads having repellent coatings contg. F compds. and polysiloxanes at around jet ports)
RN 41440-38-4 HCA
CN 2-Propenoic acid, 2-(ethenyloxy)ethyl ester (9CI) (CA INDEX NAME)



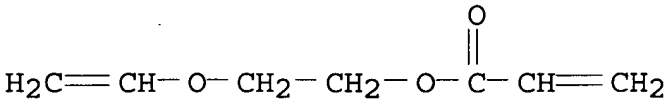
IC ICM B41J002-135
ICS B41J002-01; C08F299-08; C23C026-00
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 42

IT **Silsesquioxanes**
(acrylic; ink-jet printer heads having repellent coatings contg. F compds. and polysiloxanes at around jet ports)
IT 160716-45-0P, 3-Acryloyloxypropyltrimethoxysilane homopolymer **548774-43-2P**
(cured; ink-jet printer heads having repellent coatings contg. F compds. and polysiloxanes at around jet ports)
IT 100-42-5D, Styrene, polymers 106-90-1D, polymers 7631-86-9, MEK-ST, uses **41440-38-4D**, polymers 123109-42-2D, polymers 853915-96-5
(ink-jet printer heads having repellent coatings contg. F compds. and polysiloxanes at around jet ports)

L32 ANSWER 4 OF 7 HCA COPYRIGHT 2006 ACS on STN
143:50766 Antireflective films showing near-neutral tone of reflection light, polarizers, and displays therewith. Kato, Eiichi (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2005156642 A2 20050616, 88 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2003-391366 20031120.
AB The films 30-120-.mu.m-thick cellulose acylate support films forming antireflective films consisting of sequentially laminated layers of light-diffusing layers and low-n layers in succession, where the diffusing layers contain 3-30% (to solids) transparent particles with av. diam. 0.5-5 .mu.m and .DELTA. 0.02-0.2 to that of transparent matrix resins. The support films are long webs of length 100-5000 m, width .gtoreq.0.7 m, and thickness variation .ltoreq..+-.3%. The transparent particles may consist of .gtoreq.2 particles having .DELTA. 0.02-0.1 between them. The antireflective layers may satisfy surface energy 15-25.8 mN/m and kinetic friction coeff. 0.05-0.25. The antireflective films may have, between the support films and the light-diffusing layers, transparent antistatic layers satisfying surface resistivity .ltoreq.2 .times. 1012 .OMEGA./.box., haze .ltoreq.10%, and 550-nm transmittance .gtoreq.50%. Polarizers having the films as one or both of protective films, and imaging devices equipped with the same are further claimed.
IT **646508-62-5DP**, polymers with methacrylate-terminated polysiloxanes
(low-n layers; contrast-enhancing antireflective films forming particle-diffuser layers for polarizer protective films)
RN 646508-62-5 HCA
CN 2-Propenoic acid, 2-(ethenyloxy)ethyl ester, polymer with 1,1,2,3,3,3-hexafluoro-1-propene (9CI) (CA INDEX NAME)

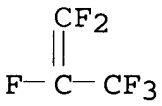
CM 1

CRN 41440-38-4
CMF C7 H10 O3



CM 2

CRN 116-15-4
CMF C3 F6



IC ICM G02B001-11
ICS B32B007-02; B32B023-20; G02B005-02; G02B005-30; G02F001-1335; G02F001-1336; H05B033-02; H05B033-14
CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38, 73
IT **Silsesquioxanes**
(acrylic-silicate-, antistatic layers; contrast-enhancing antireflective films forming particle-diffuser layers for polarizer protective films)
IT **646508-62-5DP**, polymers with methacrylate-terminated polysiloxanes
(low-n layers; contrast-enhancing antireflective films forming particle-diffuser layers for polarizer protective films)

L32 ANSWER 5 OF 7 HCA COPYRIGHT 2006 ACS on STN
142:326040 Antiglare and antireflective films resistant to photoinduced degradation, their manufacture, polarizers, and displays therewith. Kato, Eiichi (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2005070318 A2 20050317, 52 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2003-298962 20030822.
AB The films have antiglare hardcoat layers and low-n layers in this order on transparent supports, where the hardcoat layers contain translucent particles, high-n TiO2-based inorg. nanoparticles contg. Co, Al, and/or Zr and satisfying av. diam. .ltoreq.100 nm, and matrixes (e.g., org. binders, hydrolyzed organometallics, etc.). The manufg. process includes prepn. of the said nanoparticles by wet dispersion of them in the presence of dispersing agents with <0.8-mm-diam. (av.) media. Polarizers laminated with the films on one side (and with retarder films on the other side) are further claimed. The films exhibit good durability and suppress external

light reflection, resulting in improved visibility of displays.

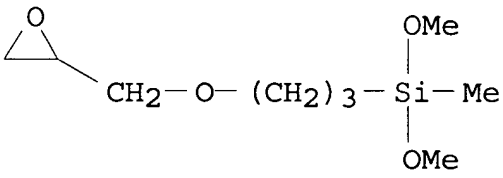
IT **847988-86-7P**
(hardcoat layers; antireflective films contg. antiglare hardcoat layers contg. doped titania nanoparticles)

RN 847988-86-7 HCA

CN Silicic acid (H4SiO4), tetraethyl ester, polymer with dimethoxymethyl[3-(oxiranylmethoxy)propyl]silane and triethoxymethylsilane (9CI) (CA INDEX NAME)

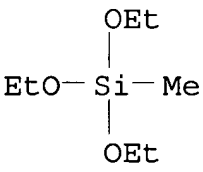
CM 1

CRN 65799-47-5
CMF C9 H20 O4 Si



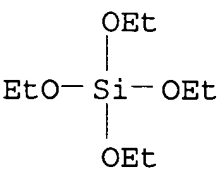
CM 2

CRN 2031-67-6
CMF C7 H18 O3 Si



CM 3

CRN 78-10-4
CMF C8 H20 O4 Si



IT **646508-62-5**

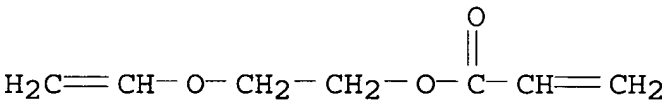
(low-n layers; antireflective films contg. antiglare hardcoat layers contg. doped titania nanoparticles)

RN 646508-62-5 HCA

CN 2-Propenoic acid, 2-(ethenyloxy)ethyl ester, polymer with 1,1,2,3,3,3-hexafluoro-1-propene (9CI) (CA INDEX NAME)

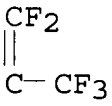
CM 1

CRN 41440-38-4
CMF C7 H10 O3



CM 2

CRN 116-15-4
CMF C3 F6



IC ICM G02B001-11
ICS G02B001-10; G02F001-1335; H04N005-72; H05B033-02; H05B033-14

CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38, 73

IT **Silsesquioxanes**
(silicate-, hardcoat layers; antireflective films contg. antiglare hardcoat layers contg. doped titania nanoparticles)

IT Silicates, preparation
(**silsesquioxane**-, hardcoat layers; antireflective films contg. antiglare hardcoat layers contg. doped titania nanoparticles)

IT 82277-45-0P, Dipentaerythritol hexaacrylate-dipentaerythritol pentaacrylate copolymer 88583-06-6P, Kayarad DPHA homopolymer 205382-11-2P 462109-01-9P, Chemisnow SX 500H **847988-86-7P** 847995-46-4P, SX 300H
(hardcoat layers; antireflective films contg. antiglare hardcoat layers contg. doped titania nanoparticles)

IT 7631-86-9D, MEK-ST, hydrolyzed 373358-08-8, Opstar TM 501A **646508-62-5**
(low-n layers; antireflective films contg. antiglare hardcoat

layers contg. doped titania nanoparticles)

L32 ANSWER 6 OF 7 HCA COPYRIGHT 2006 ACS on STN
142:102846 Radiation sensitive refractive index changing composition, pattern forming method, and optical material. Hanamura, Masaaki; Nishikawa, Michinori; Kumano, Atsushi (JSR Corporation, Japan). U.S. Pat. Appl. Publ. US 2004265737 A1 20041230, 18 pp. (English). CODEN: USXXCO. APPLICATION: US 2004-874391 20040624. PRIORITY: JP 2003-180855 20030625.

AB Radiation-sensitive compns. which change their refractive indexes on exposure to radiation (e.g., UV or visible radiation) are described which comprise inorg. oxide particles, a polymerizable compd., a material which decomps. on exposure to radiation, and a compd. which decomps., sublimes, or evaps. to escape through volatilization or the like when it is heated. Preferably, the material which decomps. upon exposure to radiation forms an acid, base, or radical that reacts to increase the mol. wt. of the polymerizable compd. Methods of forming a refractive index pattern are described which entail applying a film comprising the radiation-sensitive refractive index-changing compn., irradn. at least part of the coating film, and heating the film to polymerize the polymerizable compd. of the exposed portion so as to confine the escaping compd. by crosslinking in the exposed region which allowing it to escape from the unexposed portion. Refractive index patterns and patterned optical materials having refractive index patterns formed by the methods are also described.

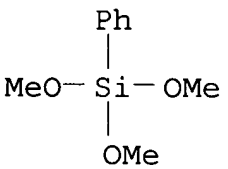
IT **162816-07-1P**, Methyltrimethoxysilane-phenyltrimethoxysilane copolymer **816417-96-6P**, Dicyclopentanyl methacrylate-methacrylic acid-styrene-2-(2-vinyloxyethoxy)ethyl methacrylate copolymer
(radiation-sensitive refractive index-changing compns. and pattern forming methods using them and patterned optical materials formed by the methods)

RN 162816-07-1 HCA

CN Silane, trimethoxymethyl-, polymer with trimethoxyphenylsilane (9CI) (CA INDEX NAME)

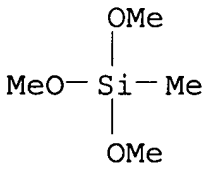
CM 1

CRN 2996-92-1
CMF C9 H14 O3 Si



CM 2

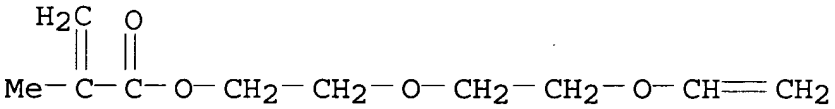
CRN 1185-55-3
CMF C4 H12 O3 Si



RN 816417-96-6 HCA
CN 2-Propenoic acid, 2-methyl-, polymer with ethenylbenzene, 2-[2-(ethenyloxy)ethoxy]ethyl 2-methyl-2-propenoate and octahydro-4,7-methano-1H-inden-5-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

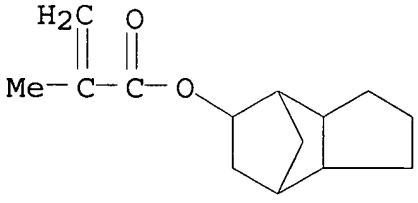
CM 1

CRN 76392-22-8
CMF C10 H16 O4



CM 2

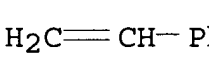
CRN 34759-34-7
CMF C14 H20 O2



CM 3

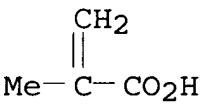
CRN 100-42-5

CMF C8 H8



CM 4

CRN 79-41-4
CMF C4 H6 O2



IC ICM B29D011-00
INCL 430270100; 264001210; 264001360
CC 73-11 (Optical, Electron, and Mass Spectroscopy and Other Related Properties)
Section cross-reference(s): 38, 74
IT Polysiloxanes, uses
Silsesquioxanes
(radiation-sensitive refractive index-changing compns. and pattern forming methods using them and patterned optical materials formed by the methods)
IT 25498-03-7P, Methyltrimethoxysilane homopolymer 30174-74-4P, 2-Isopropenyl-2-oxazoline-styrene copolymer 153315-80-1P **162816-07-1P**, Methyltrimethoxysilane-phenyltrimethoxysilane copolymer **816417-96-6P**, Dicyclopentanyl methacrylate-methacrylic acid-styrene-2-(2-vinyloxyethoxy)ethyl methacrylate copolymer
(radiation-sensitive refractive index-changing compns. and pattern forming methods using them and patterned optical materials formed by the methods)

L32 ANSWER 7 OF 7 HCA COPYRIGHT 2006 ACS on STN
141:131362 Antireflective coatings, their films, and antisoiling coatings for optical imaging devices. Kato, Eiichi (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2004198445 A2 20040715, 57 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2002-361112 20021212. PRIORITY: JP 2002-308753 20021023.
AB The antireflective coatings are manufd. by curing compns. comprising (I) AB or ABA block copolymers having (A) polymer blocks mainly contg. repeating units of CF2CFRf (Rf = F, C1-8 perfluoroalkyl, ORf'; Rf' = fluorine-contg. C1-30 aliph. group) and (B) polymer blocks contg. repeating units having OSiR11R12 and/or OSiR13R14R15 (R11-R15 = aliph. or arom. group), and repeating units having

crosslinkable groups, and (II) crosslinking agents and/or crosslinking accelerators. The antireflective films show good scratch and soiling resistance, and are useful for liq. crystal displays.

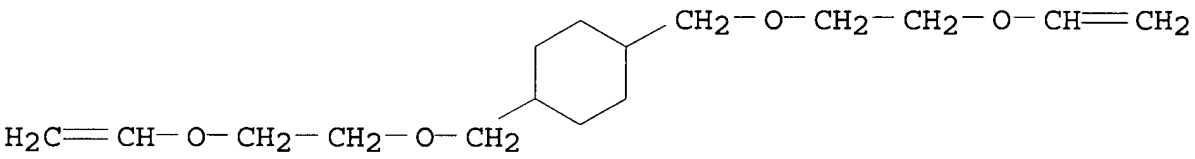
IT **722494-49-7P**
(antireflective and antisoiling coatings for optical imaging devices)

RN 722494-49-7 HCA

CN 2-Propenoic acid, 2-methyl-, 2-[2-(ethenyloxy)ethoxy]ethyl ester, polymer with 1,4-bis[[2-(ethenyloxy)ethoxy]methyl]cyclohexane, 1,1,2,3,3,4,4,4-octafluoro-1-butene, 3-(pentamethyldisiloxanyl)propyl 2-methyl-2-propenoate and tetrafluoroethene (9CI) (CA INDEX NAME)

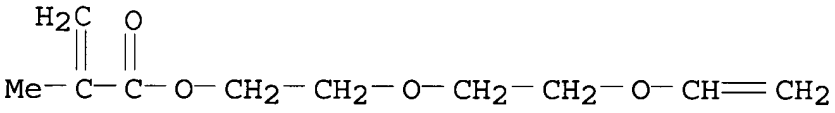
CM 1

CRN 658075-08-2
CMF C16 H28 O4



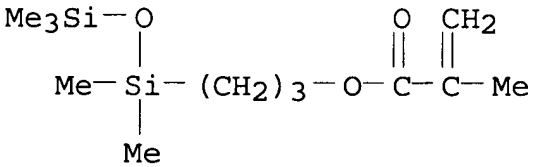
CM 2

CRN 76392-22-8
CMF C10 H16 O4



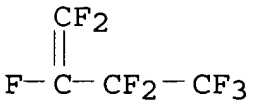
CM 3

CRN 18151-85-4
CMF C12 H26 O3 Si2



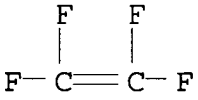
CM 4

CRN 357-26-6
CMF C4 F8



CM 5

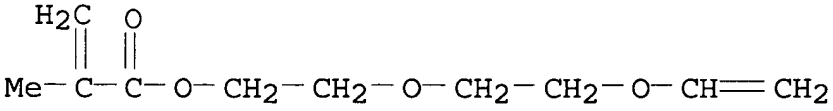
CRN 116-14-3
CMF C2 F4



IT **722494-46-4**
(antireflective and antisoiling coatings for optical imaging devices)
RN 722494-46-4 HCA
CN 2-Propenoic acid, 2-methyl-, 2-[2-(ethenyloxy)ethoxy]ethyl ester, polymer with 1,1,2,3,3,4,4,4-octafluoro-1-butene, 3-(pentamethyldisiloxanyl)propyl 2-methyl-2-propenoate and tetrafluoroethene, diblock (9CI) (CA INDEX NAME)

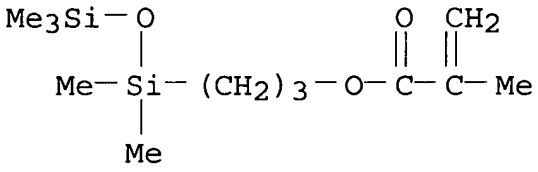
CM 1

CRN 76392-22-8
CMF C10 H16 O4



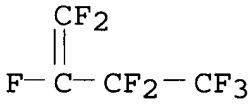
CM 2

CRN 18151-85-4
CMF C12 H26 O3 Si2



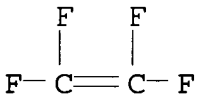
CM 3

CRN 357-26-6
CMF C4 F8



CM 4

CRN 116-14-3
CMF C2 F4



IC ICM G02B001-11
ICS B32B007-02; B32B027-00; C08F293-00; G02B001-10
CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38, 42, 73
IT Epoxy resins, preparation
Silsesquioxanes
(fluorine-contg.; antireflective and antisoiling coatings for optical imaging devices)
IT **Silsesquioxanes**
(polysiloxane-, fluorine-contg.; antireflective and antisoiling coatings for optical imaging devices)
IT Fluoropolymers, preparation
(polysiloxane-**silsesquioxane**-; antireflective and antisoiling coatings for optical imaging devices)
IT Polysiloxanes, preparation
(**silsesquioxane**-, fluorine-contg.; antireflective and antisoiling coatings for optical imaging devices)
IT Fluoropolymers, preparation

(**silsesquioxane**-; antireflective and antisoiling coatings for optical imaging devices)

IT 722494-41-9P 722494-42-0P 722494-43-1P 722494-44-2P
722494-48-6P **722494-49-7P** 722494-50-0P 722494-52-2P
722494-53-3P 722494-55-5P 722494-58-8P 722494-60-2P
722494-61-3P 722504-41-8P
(antireflective and antisoiling coatings for optical imaging devices)

IT 722494-45-3 **722494-46-4** 722494-47-5 722494-51-1
722494-54-4 722494-57-7 722494-59-9
(antireflective and antisoiling coatings for optical imaging devices)

(answer set is probably pretty junky)

=> d 133 1-14 cbib abs hitstr hitind

L33 ANSWER 1 OF 14 HCA COPYRIGHT 2006 ACS on STN
144:139028 Multilayered antireflection sheets, antiglare films, polarizing plates, display devices. Kato, Eiichi; Ikeda, Akira (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2006010829 A2 20060112, 99 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2004-184912 20040623.

AB The title antireflective sheet consists of multilayer laminates of .gtoreq.2 layers of light-transmitting layers having different refractive indexes. including layer(s) formed by curing a compn. contg. a curable mulitbranched polymer, comprising a multibranched polymer core terminated with photocurable and/or heat curable groups, and .gtoreq.1 of curing agents and curing accelerators. The mulitbranched polymers may be dendrimers, hyperbranched polymers, of starburst polymers. The sheets may comprise a high refractive index layer, e.g. TiO2-based material contg. Co, Al, and/or Zr, a low refractive index layer, and .gtoreq.2 layers having intermediate refractive index. An antiglare film obtained by lamination of the said sheet on a transparent support by placing the low refractive index layer on the face side, a polarizing plate including the antireflection sheet, and display devices including the antiglare film or the polarizing plate are also claimed. Noncracking and scratch-resistant films resistant to weathering are obtained.

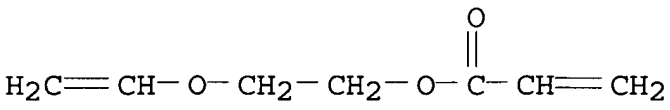
IT **866413-69-6DP**, polymers with acrylic dendritic compd. and acrylic siloxanes **873444-37-2P 873444-61-2P**
(multilayered antireflection sheets including cured dendritic polymer layer for antiglare films, polarizing plates, and display devices)

RN 866413-69-6 HCA

CN 2-Propenoic acid, 2-methyl-, 2-(ethenyloxy)ethyl ester, polymer with 2-(ethenyloxy)ethyl 2-propenoate and 1,1,2,3,3,3-hexafluoro-1-propene (9CI) (CA INDEX NAME)

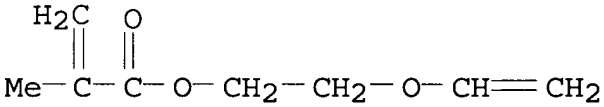
CM 1

CRN 41440-38-4
CMF C7 H10 O3



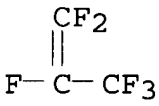
CM 2

CRN 1464-69-3
CMF C8 H12 O3



CM 3

CRN 116-15-4
CMF C3 F6

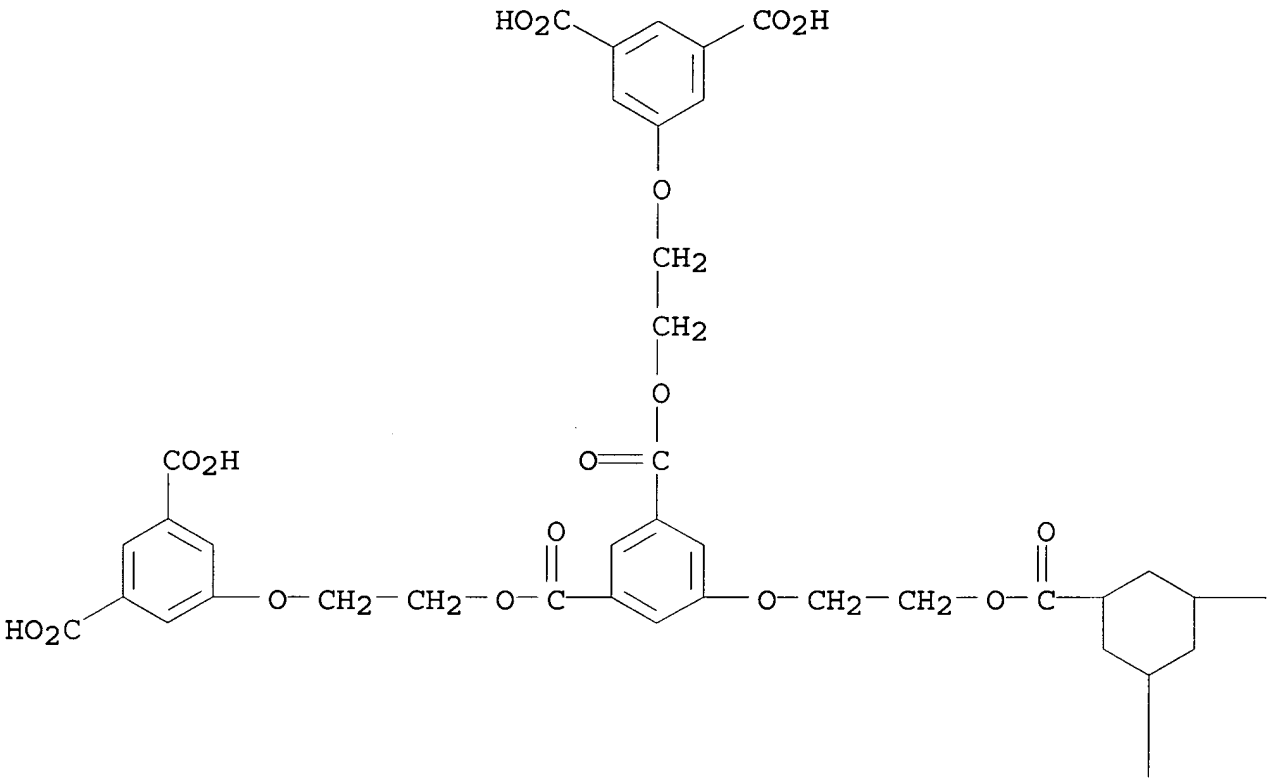


RN 873444-37-2 HCA
CN INDEX NAME NOT YET ASSIGNED

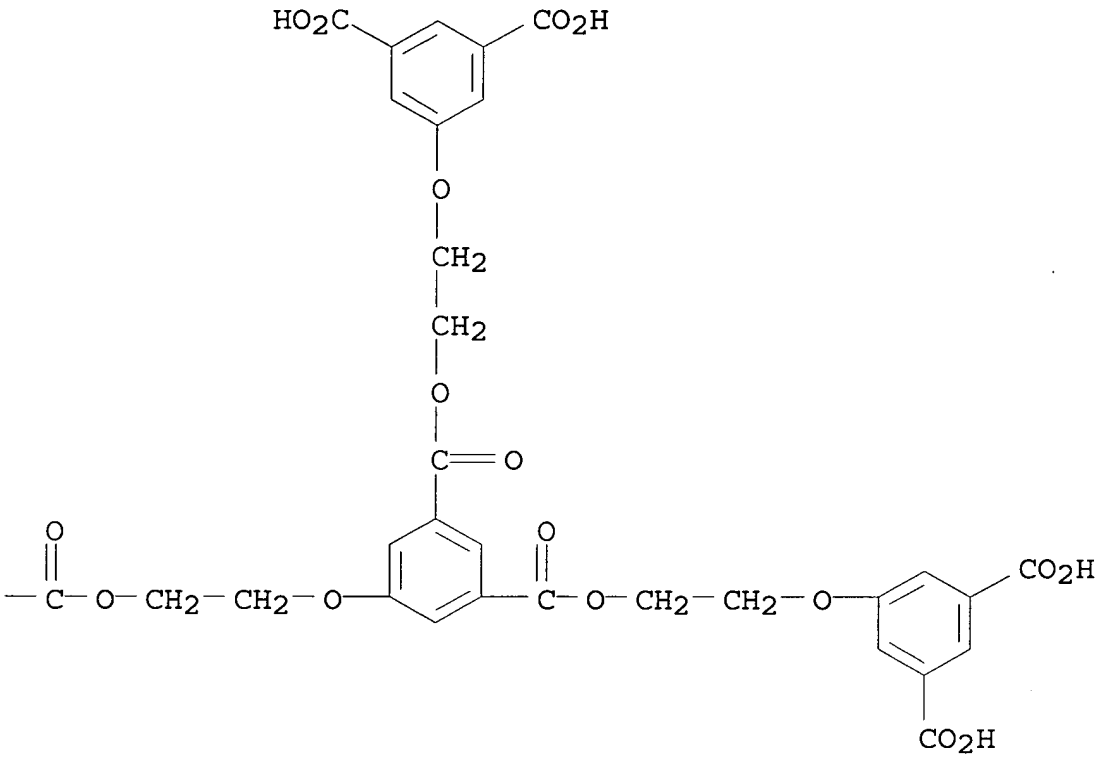
CM 1

CRN 873444-35-0
CMF C99 H84 O51

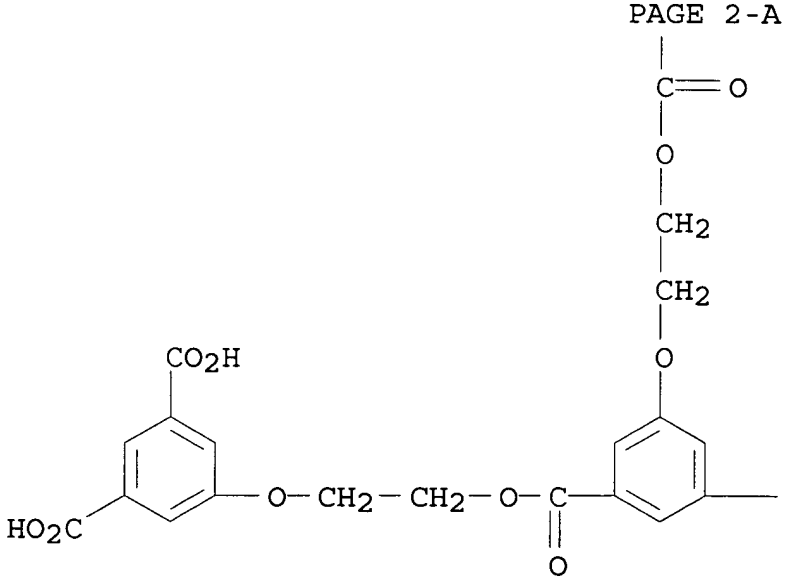
PAGE 1-A



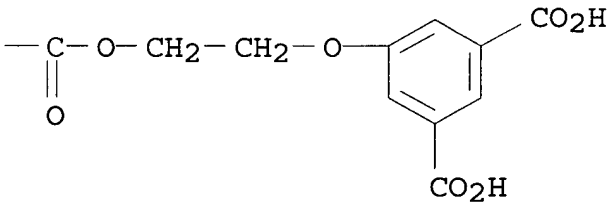
PAGE 1-B



PAGE 2-A

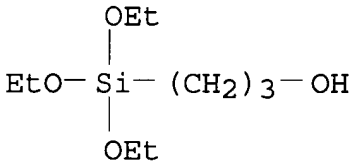


PAGE 2-B



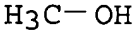
CM 2

CRN 53394-61-9
CMF C9 H22 O4 Si



CM 3

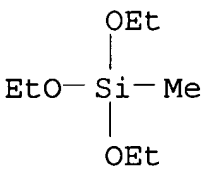
CRN 67-56-1
CMF C H4 O



RN 873444-61-2 HCA
CN INDEX NAME NOT YET ASSIGNED

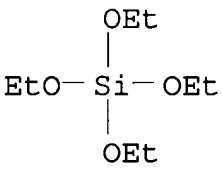
CM 1

CRN 2031-67-6
CMF C7 H18 O3 Si



CM 2

CRN 78-10-4
CMF C8 H20 O4 Si



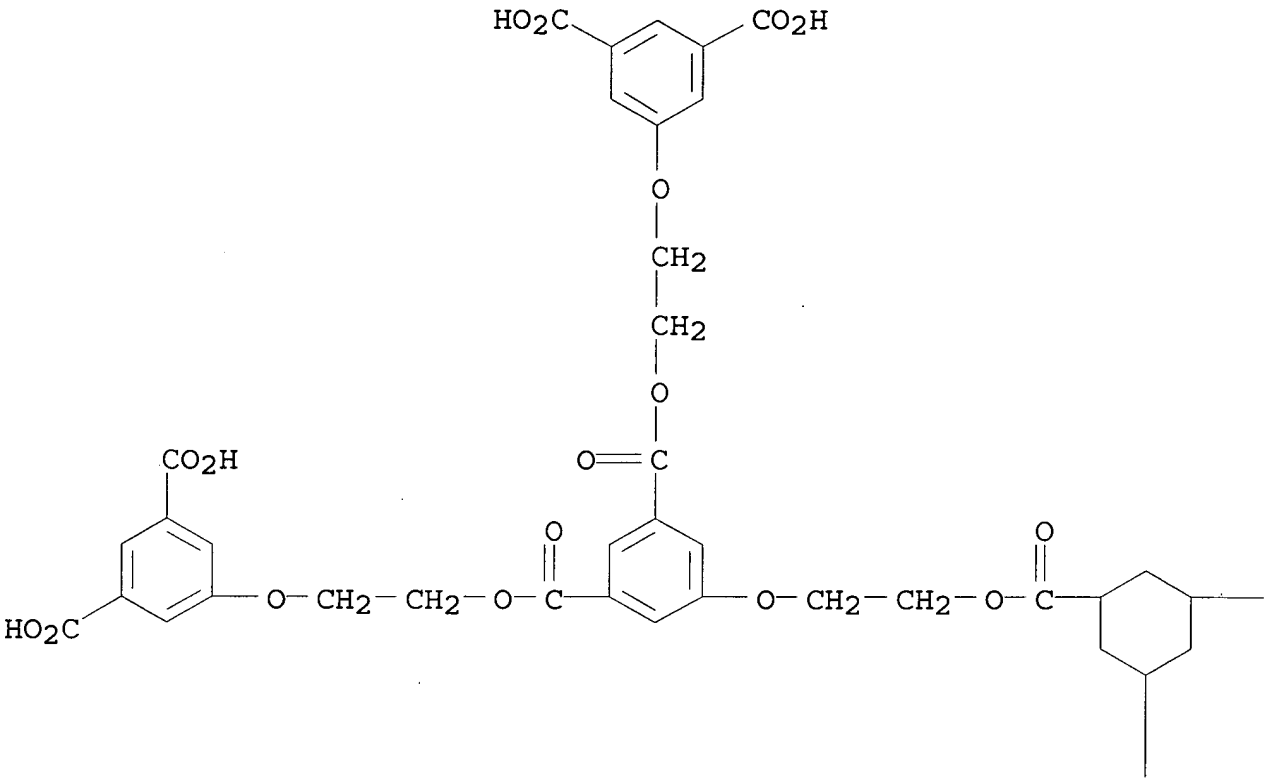
CM 3

CRN 873444-37-2
CMF C99 H84 O51 . x C9 H22 O4 Si . x C H4 O

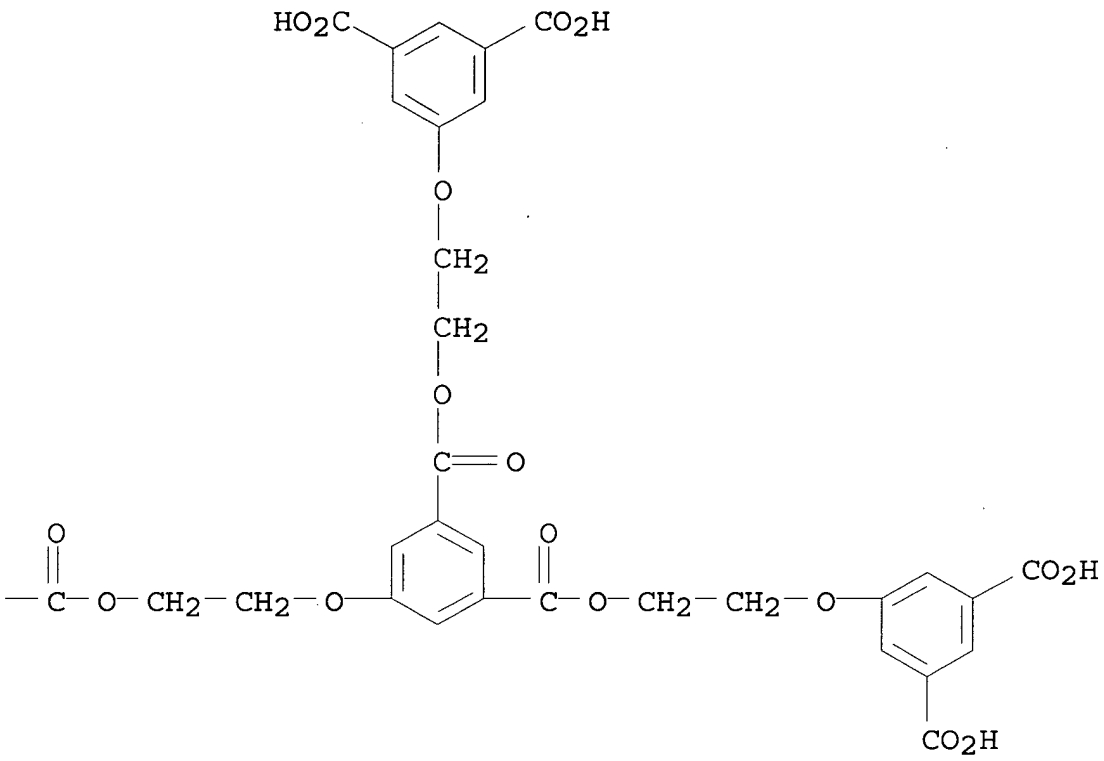
CM 4

CRN 873444-35-0
CMF C99 H84 O51

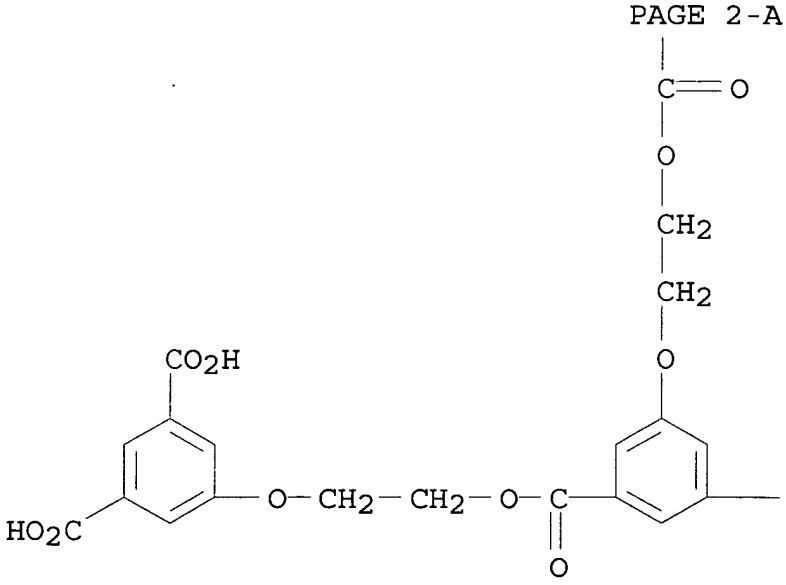
PAGE 1-A



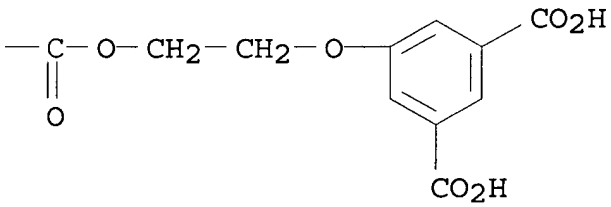
PAGE 1-B



PAGE 2-A

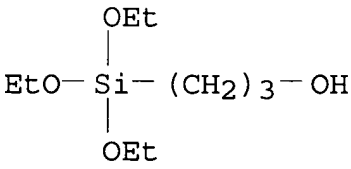


PAGE 2-B



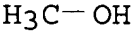
CM 5

CRN 53394-61-9
CMF C9 H22 O4 Si



CM 6

CRN 67-56-1
CMF C H4 O



CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 73

IT 4369-14-6DP, KBM 5103, polymers with acrylic dendritic compd.,acrylic fluoropolymer, acrylic siloxanes **866413-69-6DP**, polymers with acrylic dendritic compd. and acrylic siloxanes 867304-05-0P 867338-86-1DP, acrylic functional dendrimer, polymers with acrylic fluoropolymer and acrylic siloxanes 873442-85-4P 873442-86-5P 873442-87-6P 873442-99-0P 873443-02-8DP, methacryl-terminated, polymers with methacrylates 873444-34-9P 873444-36-1P **873444-37-2P** 873444-39-4P **873444-61-2P** 873444-87-2P
(multilayered antireflection sheets including cured dendritic polymer layer for antiglare films, polarizing plates, and display devices)

L33 ANSWER 2 OF 14 HCA COPYRIGHT 2006 ACS on STN
142:229105 Curable block copolyester compositions, articles and having cured layers therefrom, weather-resistant antireflective (AR) films, polarizers, and displays therewith. Kato, Eiichi (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2005042072 A2 20050217, 74 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2003-280476 20030725.

AB The curable compns. contain (1) AB, ABA, or comb-shaped block copolymers composed of block A comprising radically polymerizable monomers and block B of polyesters and (2) compds. which cure with light or heat. The AR film comprises a transparent support having thereon a multilayer composed of a high-refractive index (n.) layer formed by application and curing of the curable compns. and showing n. 1.55-2.50 and a low-n. layer, provided in this order. In another alternative, the AR film comprises a transparent support having thereon a multilayer composed of an antiglare layer formed by application and curing of the curable compns. which further contains mat particles with diam. 0.5-10 .mu.m and a low-n. layer, provided in this order. Preferably, a hard coat is disposed between the transparent support and the high-n. layer. The polarizer of the display employs the AR film as at least one of the protective films.

IT **843652-16-4DP**, reaction products with 3-mercaptopropyltrimethoxysilane
(assumed and actual monomers, comb; curable block copolyester compns. for weather-resistant antireflective or antiglare films for protection of display polarizers)

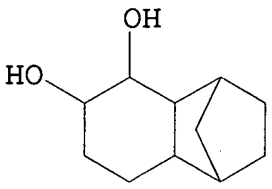
RN 843652-16-4 HCA

CN Heptanedioic acid, polymer with cyclohexyl 2-propenoate, decahydro-1,4-methanonaphthalene-5,6-diol and 3-(trimethoxysilyl)propyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

CM 1

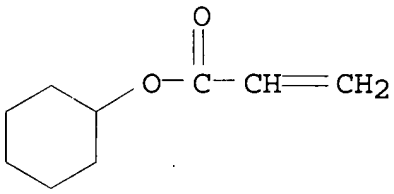
CRN 791853-78-6

CMF C11 H18 O2



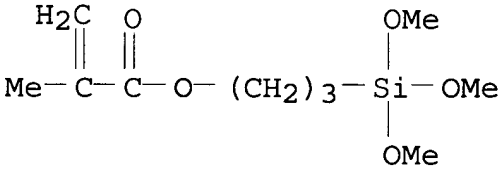
CM 2

CRN 3066-71-5
CMF C9 H14 O2



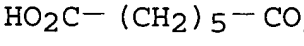
CM 3

CRN 2530-85-0
CMF C10 H20 O5 Si



CM 4

CRN 111-16-0
CMF C7 H12 O4



IT **843652-00-6P 843652-02-8DP**, reaction products with Et carbamate

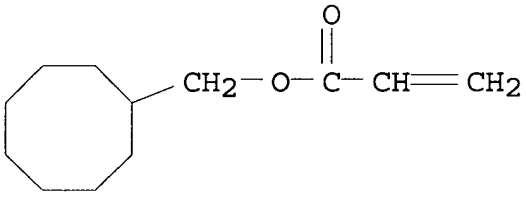
(assumed and actual monomers; curable block copolyester compns. for weather-resistant antireflective or antiglare films for protection of display polarizers)

RN 843652-00-6 HCA

CN Butanedioic acid, methyl-, polymer with bicyclo[2.2.1]heptane-2,3-dimethanol, cyclooctylmethyl 2-propenoate and 3-(trimethoxysilyl)propyl 2-propenoate, diblock (9CI) (CA INDEX NAME)

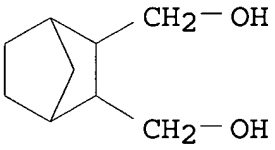
CM 1

CRN 654072-00-1
CMF C12 H20 O2



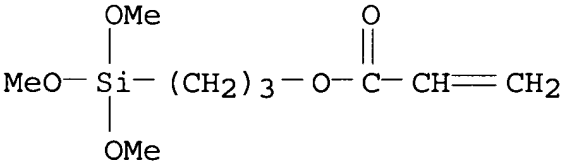
CM 2

CRN 45849-05-6
CMF C9 H16 O2



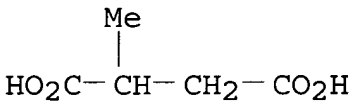
CM 3

CRN 4369-14-6
CMF C9 H18 O5 Si



CM 4

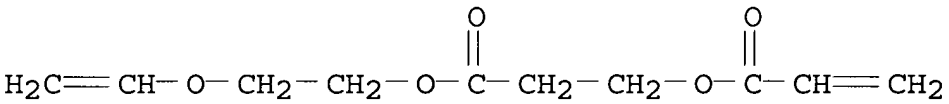
CRN 498-21-5
CMF C5 H8 O4



RN 843652-02-8 HCA
CN Heptanedioic acid, polymer with decahydro-1,5-naphthalenediol, 3-[2-(ethenyloxy)ethoxy]-3-oxopropyl 2-propenoate, hexylbutanedioic acid and methyl 2-methyl-2-propenoate, diblock (9CI) (CA INDEX NAME)

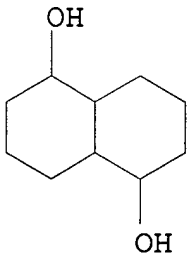
CM 1

CRN 843652-01-7
CMF C10 H14 O5



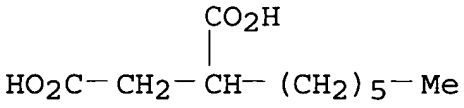
CM 2

CRN 66818-21-1
CMF C10 H18 O2



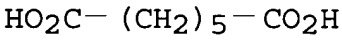
CM 3

CRN 5702-91-0
CMF C10 H18 O4



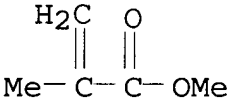
CM 4

CRN 111-16-0
CMF C7 H12 O4



CM 5

CRN 80-62-6
CMF C5 H8 O2



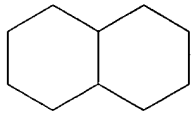
IT **844465-59-4DP**, reaction products with 3-mercaptopropyltrimethoxysilane **844465-61-8DP**, reaction products with 3-mercaptopropyltrimethoxysilane **844476-62-6DP**, reaction products with 3-mercaptopropyltrimethoxysilane (comb; curable block copolyester compns. for weather-resistant antireflective or antiglare films for protection of display polarizers)

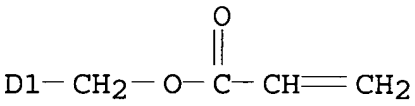
RN 844465-59-4 HCA

CN 2-Propenoic acid, 2-methyl-, 3-(trimethoxysilyl)propyl ester, polymer with 1,4-cyclohexanedimethanol, (decahydronaphthalenyl)methyl 2-propenoate and dihydro-2,5-furandione, graft (9CI) (CA INDEX NAME)

CM 1

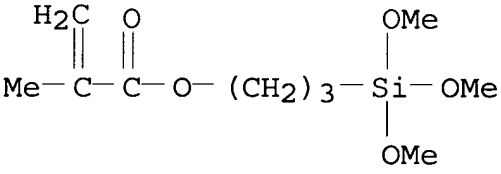
CRN 711027-40-6
CMF C14 H22 O2
CCI IDS





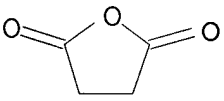
CM 2

CRN 2530-85-0
CMF C10 H20 O5 Si



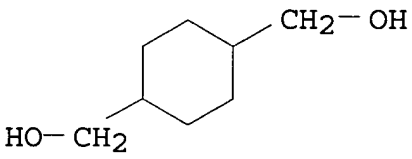
CM 3

CRN 108-30-5
CMF C4 H4 O3



CM 4

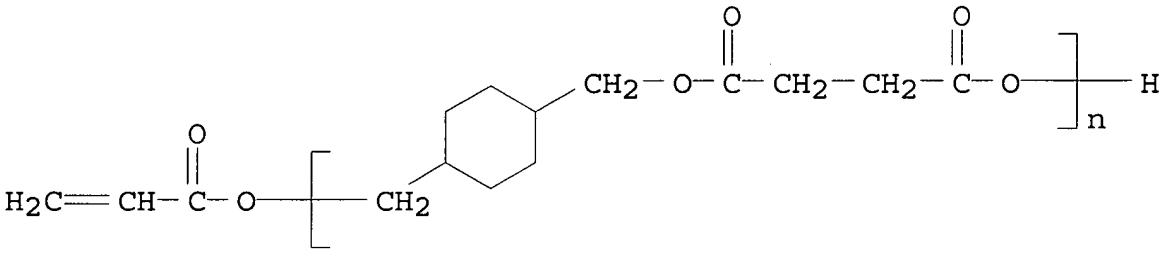
CRN 105-08-8
CMF C8 H16 O2



RN 844465-61-8 HCA
CN 2-Propenoic acid, 2-methyl-, 3-(trimethoxysilyl)propyl ester, polymer with (decahydronaphthalenyl)methyl 2-propenoate and .alpha.-hydro-.omega.-[(1-oxo-2-propenyl)oxy]poly[oxy(1,4-dioxo-1,4-butanediyl)oxymethylene-1,4-cyclohexanediylmethylene], graft (9CI) (CA INDEX NAME)

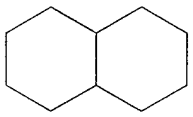
CM 1

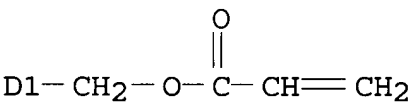
CRN 791853-66-2
CMF (C12 H18 O4)n C3 H4 O2
CCI PMS



CM 2

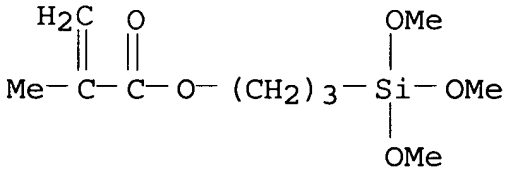
CRN 711027-40-6
CMF C14 H22 O2
CCI IDS





CM 3

CRN 2530-85-0
CMF C10 H20 O5 Si



RN 844476-62-6 HCA
CN 2-Propenoic acid, 2-methyl-, 3-(trimethoxysilyl)propyl ester, polymer with cyclohexyl 2-propenoate and .alpha.-hydro-.omega.-[2-hydroxy-3-[(2-methyl-1-oxo-2-propenyl)oxy]propoxy]poly[oxy(decahydro-1,4-methanonaphthalenediyl)oxy(1,7-dioxo-1,7-heptanediyl)], graft (9CI) (CA INDEX NAME)

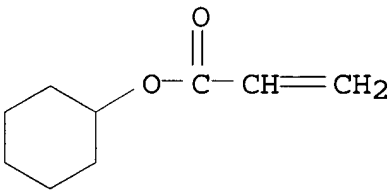
CM 1

CRN 791853-76-4
CMF (C18 H26 O4)n C7 H12 O4
CCI IDS, PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

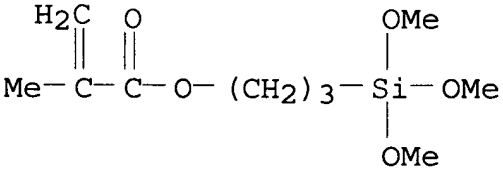
CM 2

CRN 3066-71-5
CMF C9 H14 O2



CM 3

CRN 2530-85-0
CMF C10 H20 O5 Si



IT **843652-20-0P**

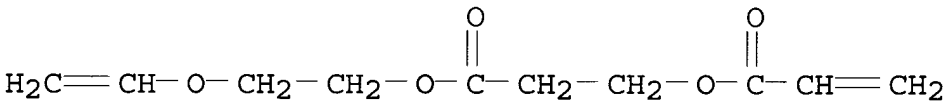
(curable block copolyester compns. for weather-resistant antireflective or antiglare films for protection of display polarizers)

RN 843652-20-0 HCA

CN Heptanedioic acid, polymer with 2,2',2''-[1,3,5-benzenetriyltris(oxymethylene)]tris[oxirane], decahydro-1,5-naphthalenediol, 3-[2-(ethenyloxy)ethoxy]-3-oxopropyl 2-propenoate, hexylbutanedioic acid and methyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

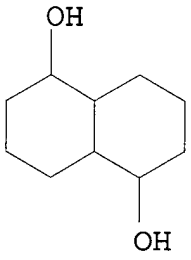
CM 1

CRN 843652-01-7
CMF C10 H14 O5



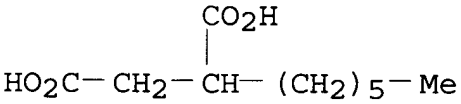
CM 2

CRN 66818-21-1
CMF C10 H18 O2



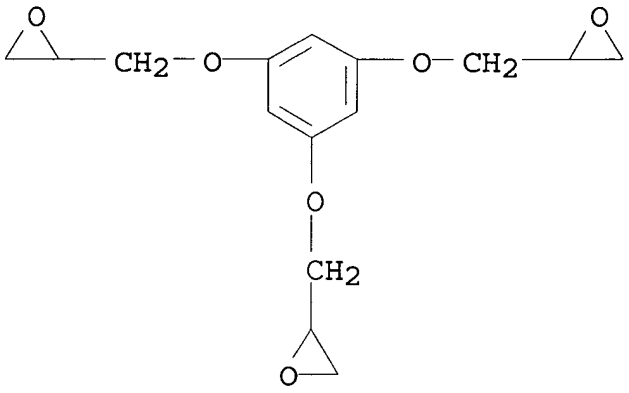
CM 3

CRN 5702-91-0
CMF C10 H18 O4



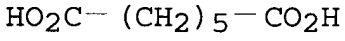
CM 4

CRN 4223-14-7
CMF C15 H18 O6



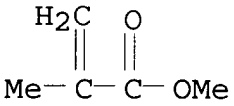
CM 5

CRN 111-16-0
CMF C7 H12 O4



CM 6

CRN 80-62-6
CMF C5 H8 O2



IC ICM C08L087-00
ICS B32B007-02; B32B027-36; C08L055-00; C08L101-02; G02B001-10; G02B001-11; G02B005-30

CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 37, 38

IT 843652-11-9DP, reaction products with glycidyl mercaptoethyl ether
843652-15-3P **843652-16-4DP**, reaction products with 3-mercaptopropyltrimethoxysilane 844465-65-2P

(assumed and actual monomers, comb; curable block copolyester compns. for weather-resistant antireflective or antiglare films for protection of display polarizers)

IT 791853-65-1P 843651-99-0P **843652-00-6P**
843652-02-8DP, reaction products with Et carbamate
843652-06-2P 843661-18-7P 843662-08-8P 844465-57-2P
(assumed and actual monomers; curable block copolyester compns. for weather-resistant antireflective or antiglare films for protection of display polarizers)

IT 4420-74-0DP, 3-Mercaptopropyltrimethoxysilane, reaction products with acrylic graft copolymer 843652-09-5P 843652-10-8DP, reaction products with glycidyl mercaptoethyl ether 843652-12-0DP, reaction products with acrylic polyester graft copolymers 843652-14-2P **844465-59-4DP**, reaction products with 3-mercaptopropyltrimethoxysilane **844465-61-8DP**, reaction products with 3-mercaptopropyltrimethoxysilane 844465-63-0P **844476-62-6DP**, reaction products with 3-mercaptopropyltrimethoxysilane
(comb; curable block copolyester compns. for weather-resistant antireflective or antiglare films for protection of display polarizers)

IT 51-79-6DP, Ethyl carbamate, reaction products with block copolymers 791853-61-7P 843651-96-7P 843651-97-8P 843652-03-9P 843652-05-1P **843652-20-0P**
(curable block copolyester compns. for weather-resistant antireflective or antiglare films for protection of display polarizers)

L33 ANSWER 3 OF 14 HCA COPYRIGHT 2006 ACS on STN
141:114160 Antireflection coating on antireflection film for optical imaging devices. Obayashi, Tatsuhiko (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2004191916 A2 20040708, 39 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2003-153413 20030529. PRIORITY: JP 2002-301022 20021015.

AB The title coating contains a F-contg. copolymer and other components, wherein the other components include a compd. having polyoxyalkylene chains and polysiloxane having repeating unit of -Si(R1)(R2)O- (R1-2 = alkyl, haloalkyl, aryl). The coating provides low reflection and shows high scratch-resistance, high soiling-resistance and antistatic.

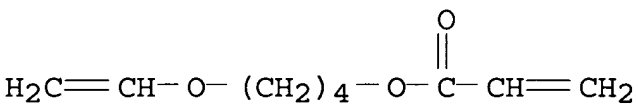
IT **646508-64-7P 718616-23-0P 718616-24-1P**
(f-contg. copolymer in antireflection coating)

RN 646508-64-7 HCA

CN 2-Propenoic acid, 4-(ethenyloxy)butyl ester, polymer with 1,1,2,3,3,3-hexafluoro-1-propene (9CI) (CA INDEX NAME)

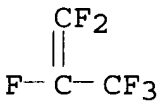
CM 1

CRN 162633-53-6
CMF C9 H14 O3



CM 2

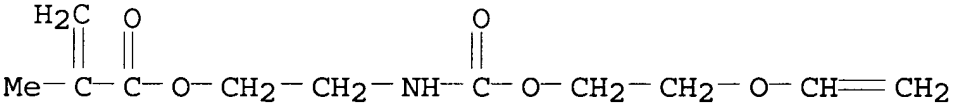
CRN 116-15-4
CMF C3 F6



RN 718616-23-0 HCA
CN 2-Propenoic acid, 2-methyl-, 2-[[[2-(ethenyloxy)ethoxy]carbonyl]amino]ethyl ester, polymer with 1,1,2,3,3,3-hexafluoro-1-propene (9CI) (CA INDEX NAME)

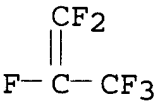
CM 1

CRN 718616-22-9
CMF C11 H17 N O5



CM 2

CRN 116-15-4
CMF C3 F6

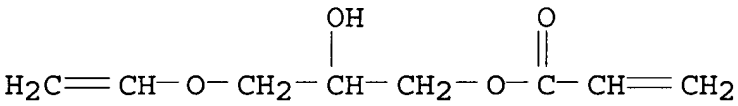


RN 718616-24-1 HCA
CN 2-Propenoic acid, 3-(ethenyloxy)-2-hydroxypropyl ester, polymer with [(ethenyloxy)methyl]oxirane and 1,1,2,3,3,3-hexafluoro-1-propene

(9CI) (CA INDEX NAME)

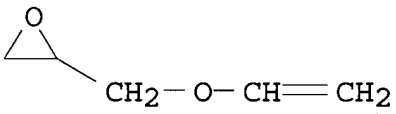
CM 1

CRN 646508-68-1
CMF C8 H12 O4



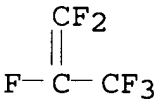
CM 2

CRN 3678-15-7
CMF C5 H8 O2



CM 3

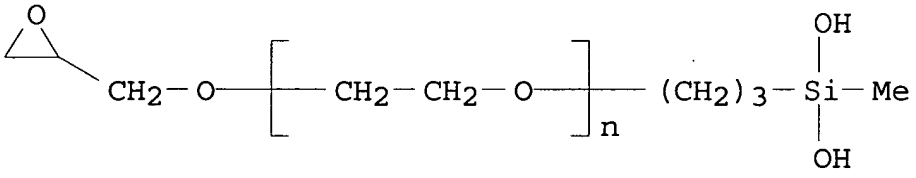
CRN 116-15-4
CMF C3 F6



IT **718616-30-9 718616-36-5**
(polysiloxane in antireflection coating)
RN 718616-30-9 HCA
CN Silanediol, dimethyl-, polymer with .alpha.-[3-(dihydroxymethylsilyl)propyl]-.omega.-(oxiranylmethoxy)poly(oxy-1,2-ethanediyl) (9CI) (CA INDEX NAME)

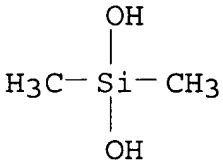
CM 1

CRN 718616-29-6
CMF (C2 H4 O)n C7 H16 O4 Si
CCI PMS



CM 2

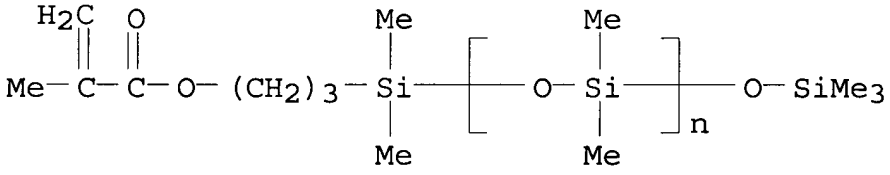
CRN 1066-42-8
CMF C2 H8 O2 Si



RN 718616-36-5 HCA
CN 2-Propenoic acid, 2-methyl-, 2-[(1-oxo-2-propenyl)oxy]ethyl ester, polymer with .alpha.-[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]-.omega.-[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)] and oxirane, block (9CI) (CA INDEX NAME)

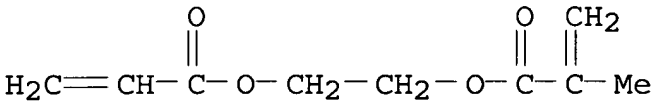
CM 1

CRN 123109-42-2
CMF (C2 H6 O Si)n C12 H26 O3 Si2
CCI PMS



CM 2

CRN 69040-48-8
CMF C9 H12 O4

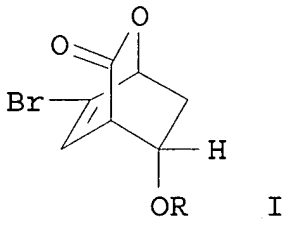


CM 3

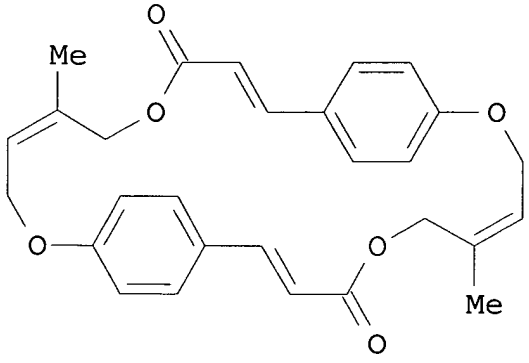
CRN 75-21-8
CMF C2 H4 O

IC ICM G02B001-11
ICS B32B007-02; B32B027-00; H05B033-02
CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 37
IT 814-68-6DP, Acrylic acid chloride, reaction product with olefinic copolymer 613687-03-9DP, Hexafluoropropylene-2-hydroxyethyl vinyl ether copolymer, reaction product with acrylic acid chloride **646508-64-7P** 655244-55-6P **718616-23-0P** **718616-24-1P**
(f-contg. copolymer in antireflection coating)
IT 165729-74-8D, trimethylsilyl- terminated 718616-25-2 718616-27-4D, trimethylsilyl- terminated 718616-28-5D, trimethylsilyl- terminated **718616-30-9** 718616-31-0 718616-33-2 718616-35-4 **718616-36-5**
(polysiloxane in antireflection coating)

L33 ANSWER 4 OF 14 HCA COPYRIGHT 2006 ACS on STN
140:339112 Synthesis of a Pondaplin Dimer and Trimer. Aromatic Interactions in Novel Macrocycles. Leonard, Michael S.; Carroll, Patrick J.; Joullie, Madeleine M. (Department of Chemistry, University of Pennsylvania, Philadelphia, PA, 19104-6323, USA). Journal of Organic Chemistry, 69(7), 2526-2531 (English) 2004. CODEN: JOCEAH. ISSN: 0022-3263. OTHER SOURCES: CASREACT 140:339112. Publisher: American Chemical Society.
GI



I

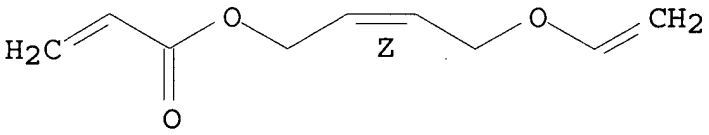


II

AB Synthetic challenges in the use of an oxabicyclo[2.2.2]octenone moiety as a masked arene for the synthesis of pondaplin are disclosed. Although the oxabicyclo[2.2.2]octenone core I (R = SiMe2CMe3, CH2CH:CHCH2OCOCH:CH2) was obtained successfully, its conversion into the desired compds. was unsuccessful. During the course of a study of the Heck reaction as a tool for macrocyclization to provide strained paracyclophanes, novel macrocycles displaying intra- and intermol. arom. interactions have been synthesized. Thus, prepn. of 4-IC6H4OCH2CH:CMeCH2OCOCH:CH2 and its exposure to Heck conditions yielded the pondaplin dimer II in 38% yield. The trimer was also be prepd. in 7% yield. The geometry of these interactions is compared to recent computational literature data.

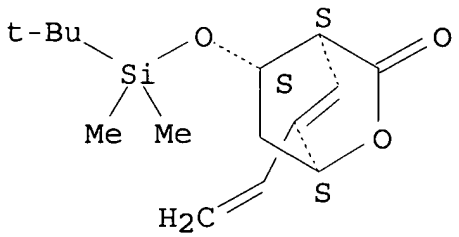
IT **681126-29-4P**
(prepn. of pondaplin dimer and trimer)
RN 681126-29-4 HCA
CN 2-Propenoic acid, (2Z)-4-(ethenyloxy)-2-butenyl ester (9CI) (CA INDEX NAME)

Double bond geometry as shown.



IT **681126-31-8P**
(prepn. of pondaplin dimer and trimer)
RN 681126-31-8 HCA
CN 2-Oxabicyclo[2.2.2]oct-5-en-3-one, 8-[[(1,1-dimethylethyl)dimethylsilyl]oxy]-6-ethenyl-, (1R,4R,8R)-rel- (9CI) (CA INDEX NAME)

Relative stereochemistry.



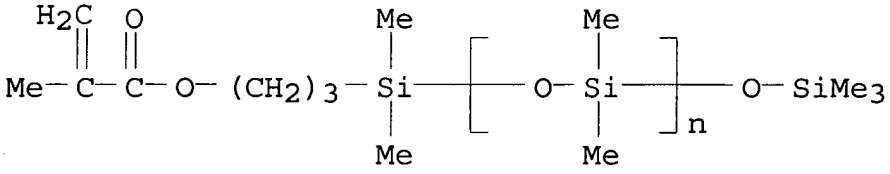
CC 26-9 (Biomolecules and Their Synthetic Analogs)
IT 69511-49-5P 74094-42-1P 114978-90-4P 183794-23-2P
681126-25-0P 681126-27-2P 681126-28-3P **681126-29-4P**
681126-32-9P 681126-33-0P 681126-34-1P
(prepn. of pondaplin dimer and trimer)
IT 681126-26-1P 681126-30-7P **681126-31-8P**
(prepn. of pondaplin dimer and trimer)

L33 ANSWER 5 OF 14 HCA COPYRIGHT 2006 ACS on STN
140:322973 Oil-based ink compositions for ink-jet printers and liquid image-developing agents for electrophotographic printing. Horie, Seiji; Sakai, Yutaka (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2004107574 A2 20040408, 47 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2002-275155 20020920.
AB Title ink compns. contain colored resin particles prepd. by dispersing surface-treated colorants in nonaq. media having 25.degree. surface tension of 15-60 mN/m and dielec. const. of 1.5-20 as seeding particles, followed by polymg. functional monomers and Si- and/or F-contg. substitute-contg. functional monomers in the presence of polymn. initiators and C:C bond-contg. end group-contg. nonaq. medium-sol. polymer dispersion stabilizers. Title image-developing agents contg. colored resin particles prepd. as described above but the nonaq. media having vol. sp. resistivity of .gtoreq.109 .OMEGA.-cm. Polymg. Me acrylate, Me methacrylate, and 2-(prefluorohexyl)ethyl methacrylate in an Isopar H dispersion contg. rosin ester-treated Microlith black C-T, lauryl methacrylate-vinyl methacrylate copolymer as dispersion stabilizer, and an azo initiator gave black pigment-encapsulated resin particles, which were used to prep. an oil-based ink showing good storage stability and giving prints with smudge and rubbing resistance.
IT **677323-08-9P 677323-10-3P**
(colorant-encapsulated by; oil-based ink-jet inks or image-developer agents contg. colorant-encapsulated F- and/or Si-contg. resin particles for storage stability)
RN 677323-08-9 HCA

CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with .alpha.-[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]-.omega.-[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)], ethenylbenzene and methyl 2-propenoate, graft (9CI) (CA INDEX NAME)

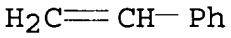
CM 1

CRN 123109-42-2
CMF (C2 H6 O Si)n C12 H26 O3 Si2
CCI PMS



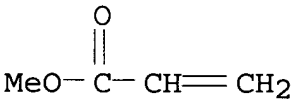
CM 2

CRN 100-42-5
CMF C8 H8



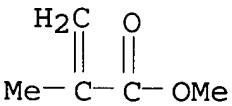
CM 3

CRN 96-33-3
CMF C4 H6 O2



CM 4

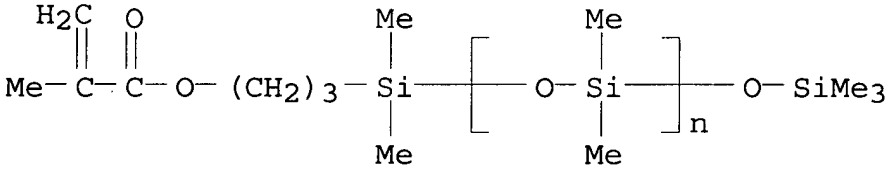
CRN 80-62-6
CMF C5 H8 O2



RN 677323-10-3 HCA
CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with .alpha.-[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]-.omega.-[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)], ethenylmethylbenzene and methyl 2-propenoate, graft (9CI) (CA INDEX NAME)

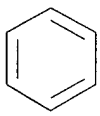
CM 1

CRN 123109-42-2
CMF (C2 H6 O Si)n C12 H26 O3 Si2
CCI PMS



CM 2

CRN 25013-15-4
CMF C9 H10
CCI IDS

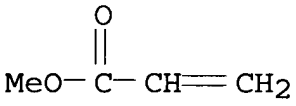


D1—Me

D1—CH═CH$_2$

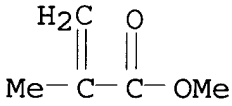
CM 3

CRN 96-33-3
CMF C4 H6 O2



CM 4

CRN 80-62-6
CMF C5 H8 O2

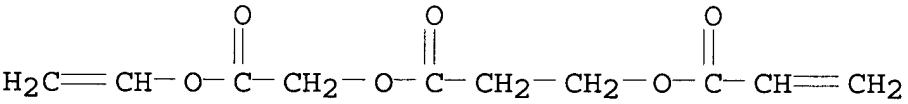


IT **100921-06-0P**, Lauryl methacrylate-vinyloxycarbonylmethyloxycarbonylethyl acrylate copolymer **113783-30-5P 677316-89-1P**
(dispersion stabilizer, in prepn. of colorant-encapsulated resin particles; oil-based ink-jet inks or image-developer agents contg. colorant-encapsulated F- and/or Si-contg. resin particles for storage stability)

RN 100921-06-0 HCA
CN 2-Propenoic acid, 2-methyl-, dodecyl ester, polymer with 3-[2-(ethenyloxy)-2-oxoethoxy]-3-oxopropyl 2-propenoate (9CI) (CA INDEX NAME)

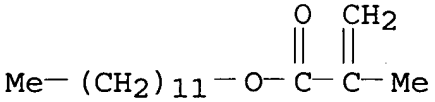
CM 1

CRN 100921-05-9
CMF C10 H12 O6



CM 2

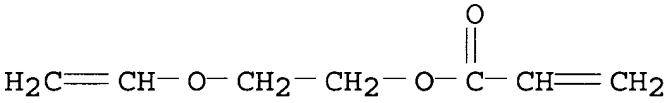
CRN 142-90-5
CMF C16 H30 O2



RN 113783-30-5 HCA
CN 2-Propenoic acid, 2-methyl-, octadecyl ester, polymer with 2-(ethenyloxy)ethyl 2-propenoate (9CI) (CA INDEX NAME)

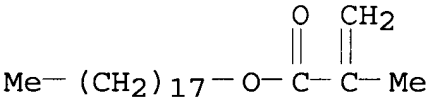
CM 1

CRN 41440-38-4
CMF C7 H10 O3



CM 2

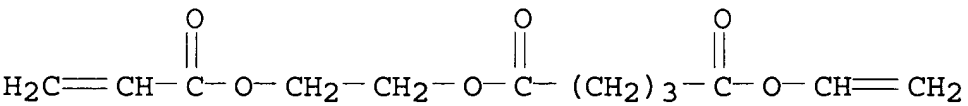
CRN 32360-05-7
CMF C22 H42 O2



RN 677316-89-1 HCA
CN Pentanedioic acid, ethenyl 2-[(1-oxo-2-propenyl)oxy]ethyl ester, polymer with tetradecyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

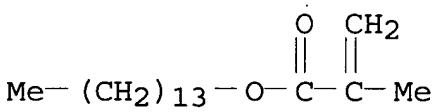
CM 1

CRN 141680-24-2
CMF C12 H16 O6



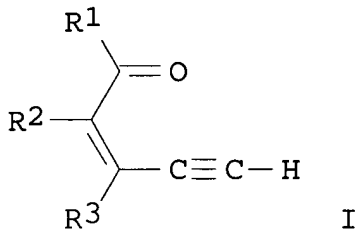
CM 2

CRN 2549-53-3
CMF C18 H34 O2

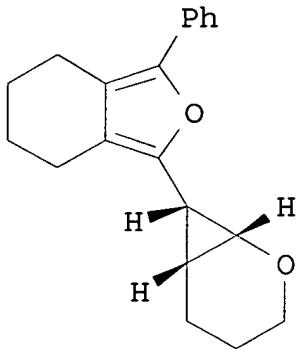


IC ICM C09D011-00
ICS B41J002-01; B41M005-00; G03G009-12; G03G009-13; C09C003-10
CC 42-12 (Coatings, Inks, and Related Products)
Section cross-reference(s): 74
IT 182558-89-0P 208054-66-4P 209454-83-1P 642067-73-0P
677322-88-2P 677322-90-6P 677322-92-8P 677322-94-0P
677322-96-2P 677322-98-4P 677323-00-1P 677323-03-4P
677323-05-6P **677323-08-9P 677323-10-3P**
677324-02-6P
(colorant-encapsulated by; oil-based ink-jet inks or image-developer agents contg. colorant-encapsulated F- and/or Si-contg. resin particles for storage stability)
IT 100921-03-7P, Lauryl methacrylate-vinyl methacrylate copolymer
100921-04-8P, Octadecyl methacrylate-vinyl methacrylate copolymer
100921-06-0P, Lauryl methacrylate-vinyloxycarbonylmethyloxycarbonylethyl acrylate copolymer
106679-74-7P 106679-75-8P 107592-14-3P,
Allyloxycarbonyldecamethylene methacrylamide-hexadecyl acrylate copolymer **113783-30-5P** 141680-17-3P 141680-21-9P
141719-09-7P 210964-44-6P 677316-84-6P 677316-87-9P
677316-89-1P 677316-91-5P 677316-95-9P 677316-97-1P
677316-99-3P
(dispersion stabilizer, in prepn. of colorant-encapsulated resin particles; oil-based ink-jet inks or image-developer agents contg. colorant-encapsulated F- and/or Si-contg. resin particles for storage stability)

L33 ANSWER 6 OF 14 HCA COPYRIGHT 2006 ACS on STN
140:287227 Catalytic cyclopropanation of alkenes via (2-furyl)carbene complexes from 1-benzoyl-cis-1-buten-3-yne with transition metal compounds. Miki, Koji; Yokoi, Tomomi; Nishino, Fumiaki; Kato, Yumiko; Washitake, Yosuke; Ohe, Kouichi; Uemura, Sakae (Department of Energy and Hydrocarbon Chemistry, Graduate School of Engineering, Kyoto University, Sakyo, Kyoto, 606-8501, Japan). Journal of Organic Chemistry, 69(5), 1557-1564 (English) 2004. CODEN: JOCEAH. ISSN: 0022-3263. Publisher: American Chemical Society.
GI



I



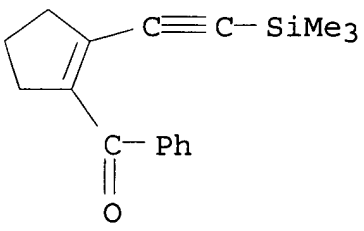
II

AB The reaction of alkenes with conjugated alkenynones I [R1 = Ph; R2 = R3 = H; R2R3 = (CH2)3, (CH2)4; R1 = Et; R2R3 = (CH2)4] in the presence of a catalytic amt. of Cr(CO)5(THF) gave 5-phenyl-2-furylcyclopropanes, e.g., II, in good yields. The key intermediate in the cyclopropanation is a (2-furyl)carbene complex. The (2-furyl)carbene complex was generated by a nucleophilic attack of carbonyl oxygen to an internal alkyne carbon in .pi.-alkyne complex or .sigma.-vinyl cationic complex. A wide range of late transition metal compds., such as [RuCl2(CO)3]2, [RhCl(cod)]2, [Rh(OAc)2]2, PdCl2, and PtCl2, also catalyzed the cyclopropanation of alkenes with alkenynones effectively. When the reactions were carried out with dienes, as carbene acceptors, the more substituted or more electron-rich alkene moiety was selectively cyclopropanated with the (2-furyl)carbenoid intermediate.

IT **675584-45-9P**
(prepn. of benzoyl(ethynyl)cyclopentene and ethynyl(propanoyl)cyclohexene via addn. of Grignard reagents to N-methoxy-N-methyl(trimethylsilylethynyl)cycloalkenecarboxamides followed by deprotection in the prepn. of cyclopropanes)

RN 675584-45-9 HCA

CN Methanone, phenyl[2-[(trimethylsilyl)ethynyl]-1-cyclopenten-1-yl]- (9CI) (CA INDEX NAME)

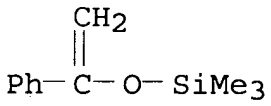


IT **13735-81-4 41440-38-4**
(stereoselective prepn. of cyclopropanes via heterocyclization of

alkenynones followed by stereoselective cyclopropanation with alkenes)

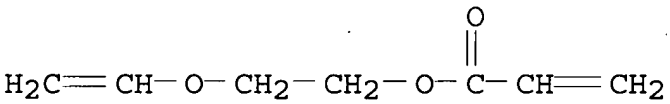
RN 13735-81-4 HCA

CN Silane, trimethyl[(1-phenylethenyl)oxy]- (9CI) (CA INDEX NAME)



RN 41440-38-4 HCA

CN 2-Propenoic acid, 2-(ethenyloxy)ethyl ester (9CI) (CA INDEX NAME)



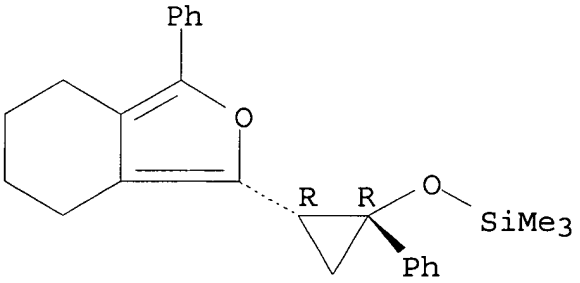
IT **436146-77-9P**

(stereoselective prepn. of cyclopropanes via heterocyclization of alkenynones followed by stereoselective cyclopropanation with alkenes)

RN 436146-77-9 HCA

CN Silane, trimethyl[[(1R,2R)-1-phenyl-2-(4,5,6,7-tetrahydro-3-phenyl-1-isobenzofuranyl)cyclopropyl]oxy]-, rel- (9CI) (CA INDEX NAME)

Relative stereochemistry.



CC 27-6 (Heterocyclic Compounds (One Hetero Atom))

Section cross-reference(s): 24, 75

IT **675584-45-9P**

(prepn. of benzoyl(ethynyl)cyclopentene and ethynyl(propanoyl)cyclohexene via addn. of Grignard reagents to N-methoxy-N-methyl(trimethylsilylethynyl)cycloalkenecarboxamides followed by deprotection in the prepn. of cyclopropanes)

IT 100-42-5, Styrene, reactions 590-18-1, cis-2-Butene 624-64-6, trans-2-Butene 926-02-3, tert-Butyl vinyl ether 5963-66-6, 2-Penten-4-ynophenone **13735-81-4 41440-38-4**

436146-73-5, (2-Ethynyl-1-cyclohexenyl)(phenyl)methanone
(stereoselective prepn. of cyclopropanes via heterocyclization of alkenynones followed by stereoselective cyclopropanation with alkenes)

IT 436146-74-6P **436146-77-9P** 436146-79-1P 436146-83-7P
436146-84-8P 675584-34-6P 675584-37-9P 675584-38-0P
675584-39-1P 675584-42-6P 675584-43-7P 675834-72-7P
866495-28-5P
(stereoselective prepn. of cyclopropanes via heterocyclization of alkenynones followed by stereoselective cyclopropanation with alkenes)

L33 ANSWER 7 OF 14 HCA COPYRIGHT 2006 ACS on STN
138:98215 Liquid electrophotographic developers with good dispersibility, fixability, and durability in printing plate making. Kato, Eiichi (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2003005455 A2 20030108, 38 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2001-187234 20010620.

AB The liq. developers comprise nonaq. solvents with elec. resistivity .gtoreq.109 .OMEGA.-cm and dielec. const. .ltoreq.3.5 and dispersed core-shell resin particles, which are manufd. by seed-polymg. (A) nonaq. solvent-sol. monofunctional monomers that become insol. by polymn. and (B) comonomers having F- and/or Si-contg. groups in the presence of seed particles with av. diam. 0.05-1.0 .mu.m and nonaq. solvent-sol. crosslinked polymer dispersants having structures of CHb1C(V0L)b2 [V0 = CO2, (CH2)rCO2, O, QX, etc.; Q = phenylene; X = linkage, O, OCO, CO2; L = C8-32-alkyl, alkenyl; b1, b2 = H, halo, cyano, C1-7-hydrocarbyl, CO2D1; D1 = H, C1-22-hydrocarbyl; r = 1-12].

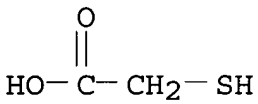
IT **215672-71-2P**, N,N-Dimethylaminoethyl methacrylate-dodecyl methacrylate-ethylene glycol methacrylate vinyl ether-thioglycolic acid telomer
(dispersion stabilizers; liq. electrophotog. developers contg. seed-polymd. graft polymer dispersants with good dispersive power)

RN 215672-71-2 HCA

CN 2-Propenoic acid, 2-methyl-, 2-(dimethylamino)ethyl ester, telomer with dodecyl 2-methyl-2-propenoate, 2-(ethenyloxy)ethyl 2-methyl-2-propenoate and mercaptoacetic acid (9CI) (CA INDEX NAME)

CM 1

CRN 68-11-1
CMF C2 H4 O2 S

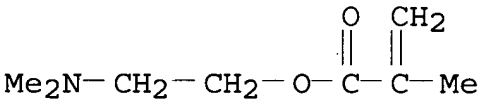


CM 2

CRN 215672-70-1
CMF (C16 H30 O2 . C8 H15 N O2 . C8 H12 O3)x
CCI PMS

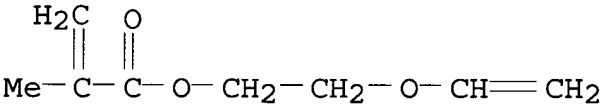
CM 3

CRN 2867-47-2
CMF C8 H15 N O2



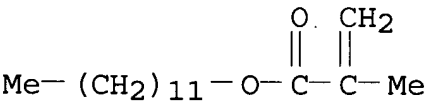
CM 4

CRN 1464-69-3
CMF C8 H12 O3



CM 5

CRN 142-90-5
CMF C16 H30 O2

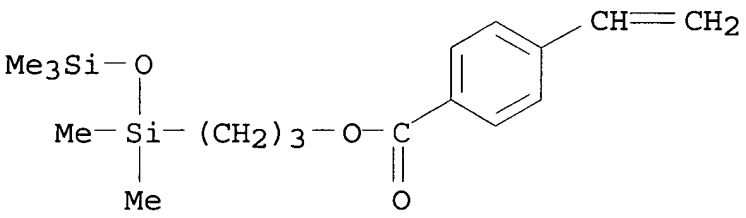


IT **477210-62-1P**
(toner particle; liq. electrophotog. developers contg. seed-polymd. graft polymer dispersants with good dispersive

power)
RN 477210-62-1 HCA
CN Benzoic acid, 4-ethenyl-, 3-(pentamethyldisiloxanyl)propyl ester, polymer with ethenyl acetate, graft (9CI) (CA INDEX NAME)

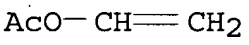
CM 1

CRN 477210-61-0
CMF C17 H28 O3 Si2



CM 2

CRN 108-05-4
CMF C4 H6 O2



IC ICM G03G009-13
ICS G03G009-12
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
IT 4693-47-4DP, 4,4'-Azobis(4-cyanopentanol), reaction products with acrylic polymers 5926-95-4DP, Glutaconic anhydride, reaction products with amino-terminated acrylic telomer 57101-68-5DP, 2,2'-Azobis(4-cyanovaleric acid), reaction products with acrylic polymers 61255-17-2P, Divinylbenzene-dodecyl methacrylate copolymer 122324-74-7P, Divinylbenzene-octadecyl methacrylate copolymer 130805-21-9P, Divinylbenzene-tridecyl methacrylate copolymer 130805-26-4DP, Divinylbenzene-hexadecyl methacrylate copolymer, 2,2'-azobis(4-cyanovaleric acid)-initiated 139703-31-4P, Divinylbenzene-octadecyl methacrylate-thioglycolic acid telomer 139703-33-6P, Divinylbenzene-tridecyl methacrylate-thioglycolic acid telomer 139720-57-3P, 2-Propenoic acid, 2-methyl-, octadecyl ester, telomer with diethenylbenzene and 3-mercaptopropanoic acid 139720-59-5P, 2-Propenoic acid, 2-methyl-, octadecyl ester, telomer with diethenylbenzene and pyridine 2-mercaptoethanesulfonate 139720-60-8P, Benzoic acid,

2-mercapto-, telomer with diethenylbenzene and octadecyl 2-methyl-2-propenoate 139720-61-9P, 2-Propenoic acid, 2-methyl-, octadecyl ester, telomer with diethenylbenzene and 2-mercaptoethyl dihydrogen phosphate 139720-62-0P, Butanoic acid, 4-[(2-mercaptoethyl)amino]-4-oxo-, telomer with diethenylbenzene and octadecyl 2-methyl-2-propenoate 139720-63-1P, .beta.-Alanine, N-(2-mercaptoethyl)-, telomer with diethenylbenzene and octadecyl 2-methyl-2-propenoate 139720-64-2DP, Divinylbenzene-2-mercaptoethylamine-octadecyl methacrylate telomer, reaction products with glutaconic anhydride 141181-86-4P, Divinylbenzene-dodecyl methacrylate-thioglycolic acid telomer 148532-67-6P, Dodecyl methacrylate-octyl methacrylate-trivinylbenzene copolymer 148532-68-7P, Butyl methacrylate-ethylene glycol dimethacrylate-octadecyl methacrylate copolymer 148532-76-7P, Butyl methacrylate-ethylene glycol dimethacrylate-octadecyl methacrylate-thioglycolic acid telomer 148532-82-5P, Divinyl adipate-hexadecyl methacrylate-thioglycolic acid telomer 159291-22-2P, Dodecyl methacrylate-octyl methacrylate-thioglycolic acid-trivinylbenzene telomer 159291-24-4P **215672-71-2P**, N,N-Dimethylaminoethyl methacrylate-dodecyl methacrylate-ethylene glycol methacrylate vinyl ether-thioglycolic acid telomer 308283-76-3DP, Docosyl methacrylate-polyethylene glycol diacrylate copolymer, 4,4'-azobis(4-cyanopentanol)-initiated 324529-94-4P, Ethylene glycol diacrylate-hexadecyl methacrylate copolymer
(dispersion stabilizers; liq. electrophotog. developers contg. seed-polymd. graft polymer dispersants with good dispersive power)

IT 477210-59-6P **477210-62-1P** 477210-92-7P 483322-42-5P
483322-45-8P 483322-46-9P 483322-47-0P 483322-50-5P
483322-52-7P 483322-54-9P 484047-04-3P 484047-05-4P
484047-07-6P 484047-08-7P 484047-09-8P 484047-11-2P
484047-12-3P 484047-13-4P 484047-14-5P 484047-15-6P
484047-16-7P 484047-18-9P 484047-19-0P 484047-20-3P
484047-21-4P 484047-22-5P 484047-23-6P
(toner particle; liq. electrophotog. developers contg. seed-polymd. graft polymer dispersants with good dispersive power)

L33 ANSWER 8 OF 14 HCA COPYRIGHT 2006 ACS on STN
138:63777 Electrophotographic liquid developer containing copolymer resin particle. Kato, Eiichi (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2002365855 A2 20021218, 39 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2001-168202 20010604.

AB The liq. developer comprises a resin particle dispersed in a nonaq. medium having an elec. resistivity .gtoreq.10^9 .OMEGA..cntdot.cm and a dielec. const. .ltoreq.3.5. The resin particle comprises .gtoreq.1 monofunctional monomer (A) which is sol. in the nonaq. solvent but becoming insol. upon the polymn., .gtoreq.1

monofunctional monomer (B) which is polymerizable with (A) and has an amino group , .gtoreq.1 monofunctional monomer (C) having .gtoreq.1 acidic group such as PO3H2, SO3H, and SO2H, .gtoreq.1 monofunctional monomer (D) which is polymerizable with (A) and contains F and/or Si, and [c1HC=Cc2(V0-L)] (V0 = COO, OCO, etc.; c1,2 = H, halo, cyano, etc.; and L = C8-32 alkyl, alkenyl). The resin particle is partially crosslinked, and is obtained by the suspension polymn. of above components.

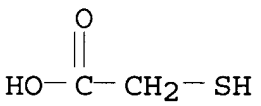
IT **215672-71-2P**, N,N-Dimethylaminoethyl methacrylate-dodecyl methacrylate-vinyl ethylene glycol methacrylate copolymer telomer with thioglycolic acid
(prepn. of resin particle contained in electrophotog. liq. developer)

RN 215672-71-2 HCA

CN 2-Propenoic acid, 2-methyl-, 2-(dimethylamino)ethyl ester, telomer with dodecyl 2-methyl-2-propenoate, 2-(ethenyloxy)ethyl 2-methyl-2-propenoate and mercaptoacetic acid (9CI) (CA INDEX NAME)

CM 1

CRN 68-11-1
CMF C2 H4 O2 S

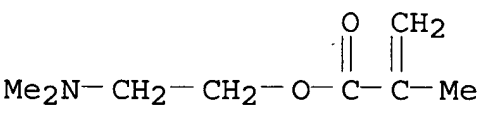


CM 2

CRN 215672-70-1
CMF (C16 H30 O2 . C8 H15 N O2 . C8 H12 O3)x
CCI PMS

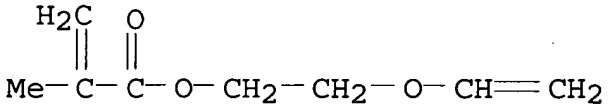
CM 3

CRN 2867-47-2
CMF C8 H15 N O2



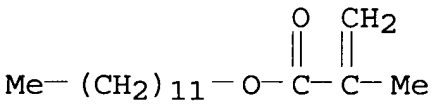
CM 4

CRN 1464-69-3
CMF C8 H12 O3



CM 5

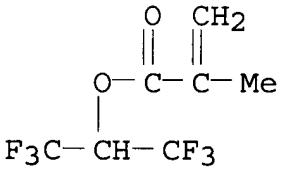
CRN 142-90-5
CMF C16 H30 O2



IT **479068-27-4P 479068-31-0P 479068-32-1P**
(prepn. of resin particle contained in electrophotog. liq. developer)
RN 479068-27-4 HCA
CN 2-Propenoic acid, 2-methyl-, 2-(dimethylamino)ethyl ester, polymer with dodecyl 2-methyl-2-propenoate, 2-(ethenyloxy)ethyl 2-methyl-2-propenoate and 2,2,2-trifluoro-1-(trifluoromethyl)ethyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

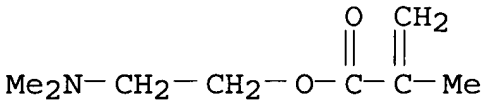
CM 1

CRN 3063-94-3
CMF C7 H6 F6 O2



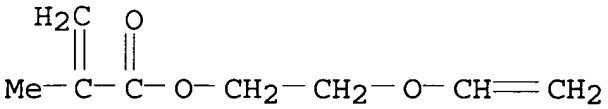
CM 2

CRN 2867-47-2
CMF C8 H15 N O2



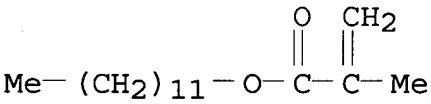
CM 3

CRN 1464-69-3
CMF C8 H12 O3



CM 4

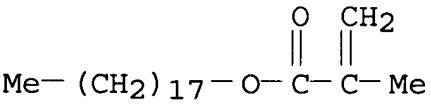
CRN 142-90-5
CMF C16 H30 O2



RN 479068-31-0 HCA
CN 2-Propenoic acid, 2-methyl-, octadecyl ester, polymer with diethenylbenzene and 3-(pentamethyldisiloxanyl)propyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

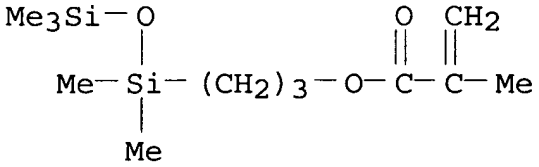
CM 1

CRN 32360-05-7
CMF C22 H42 O2



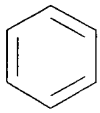
CM 2

CRN 18151-85-4
CMF C12 H26 O3 Si2



CM 3

CRN 1321-74-0
CMF C10 H10
CCI IDS

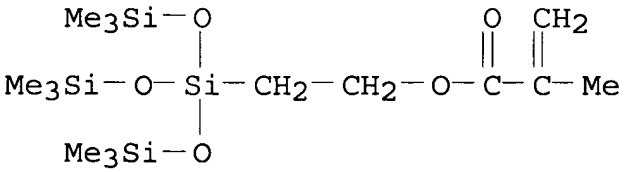


2 [D1—CH═CH2]

RN 479068-32-1 HCA
CN 2-Propenoic acid, 2-methyl-, hexadecyl ester, polymer with diethenylbenzene and 2-[3,3,3-trimethyl-1,1-bis[(trimethylsilyl)oxy]disiloxanyl]ethyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

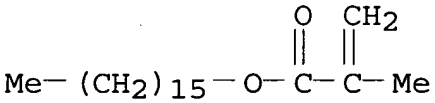
CM 1

CRN 130167-27-0
CMF C15 H36 O5 Si4



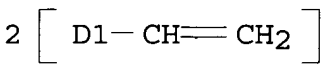
CM 2

CRN 2495-27-4
CMF C20 H38 O2



CM 3

CRN 1321-74-0
CMF C10 H10
CCI IDS



IC ICM G03G009-13
ICS G03G009-12

CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35, 38

IT 139703-31-4P, Divinylbenzene-octadecyl methacrylate copolymer telomer with thioglycolic acid 139703-33-6P, Divinylbenzene-tridecyl methacrylate copolymer telomer with thioglycolic acid 139720-57-3P 139720-59-5P 139720-60-8P 139720-61-9P 139720-62-0P 139720-63-1P 141181-86-4P, Divinylbenzene-dodecyl methacrylate copolymer telomer with thioglycolic acid 148532-76-7P, Butyl methacrylate-ethylene glycol dimethacrylate-octadecyl methacrylate copolymer telomer with thioglycolic acid 148532-82-5P, Hexadecyl methacrylate-divinyl adipate copolymer telomer with thioglycolic acid 159291-22-2P, Dodecyl methacrylate-octyl methacrylate-trivinylbenzene copolymer telomer with thioglycolic acid 159291-24-4P, 2-(Trimethoxysilyloxy)ethyl methacrylate-octadecyl methacrylate-triethylene glycol diacrylate copolymer telomer with thioglycolic acid 202459-35-6P **215672-71-2P**, N,N-Dimethylaminoethyl methacrylate-dodecyl methacrylate-vinyl ethylene glycol methacrylate copolymer telomer with thioglycolic acid
(prepn. of resin particle contained in electrophotog. liq. developer)

IT 61255-17-2P, Divinylbenzene-dodecyl methacrylate copolymer
66062-44-0P, Ethylene glycol dimethacrylate-2-hydroxyethyl methacrylate-octadecyl methacrylate copolymer 122324-74-7P, Divinylbenzene-octadecyl methacrylate copolymer 130805-21-9P, Divinylbenzene-tridecyl methacrylate copolymer 130805-26-4P, Divinylbenzene-hexadecyl methacrylate copolymer 137564-52-4P, Divinylbenzene-methacrylic acid-Octadecyl methacrylate copolymer 137564-54-6P, Octadecyl methacrylate-divinylbenzene-2-hydroxyethyl methacrylate copolymer 142302-31-6P, Acrylic acid-divinylbenzene-Octadecyl methacrylate copolymer 148532-67-6P, Dodecyl methacrylate-octyl methacrylate-trivinylbenzene copolymer 148532-68-7P, Butyl methacrylate-ethylene glycol dimethacrylate-octadecyl methacrylate copolymer 161077-96-9P, Divinylbenzene-Octadecyl methacrylate-vinyl acetate copolymer 161077-98-1P, Divinylbenzene-Octadecyl methacrylate-4-vinylbenzenecarboxylic acid copolymer 161078-01-9P 161078-02-0P 308283-76-3P, Docosyl methacrylate-polyethylene glycol diacrylate copolymer 324529-94-4P, Ethylene glycol diacrylate-hexadecylmethacrylate copolymer 324529-95-5P, Divinylbenzene-octadecyl methacrylate-glutaconic anhydride copolymer 459427-57-7P, 2-Carboxyethyl acrylate-divinylbenzene-Octadecyl methacrylate copolymer 459427-58-8P, Octadecyl methacrylate-divinylbenzene-.alpha.-chloro acrylic acid copolymer 459427-59-9P 479068-12-7P, Allyl methacrylate-dodecyl methacrylate-2-hydroxyethyl methacrylate copolymer 479068-13-8P, Allyl methacrylate-tridecyl acrylate-2-hydroxyethyl methacrylate copolymer 479068-14-9P, Dodecyl methacrylate-2-hydroxyethyl methacrylate-trivinylbenzene copolymer 479068-15-0P, Hexadecyl methacrylate-2-hydroxyethyl methacrylate-propylene glycol dimethacrylate copolymer 479068-16-1P, Butyl methacrylate-divinyl adipate-dodecyl methacrylate-2-hydroxyethyl methacrylate-propylene glycol dimethacrylate copolymer 479068-17-2P, Octadecyl methacrylate-methyl methacrylate-ethylene glycol diacrylate-2-hydroxyethyl methacrylate copolymer 479068-18-3P, Tridecyl methacrylate-2-chloroethyl methacrylate-trimethylolpropane trimethacrylate-2-hydroxyethyl methacrylate copolymer 479068-19-4P, Divinylbenzene-styrene-tetradecyl methacrylate-2-hydroxyethyl methacrylate copolymer 479068-20-7P, Octadecyl acrylate-ethylene glycol diacrylate-methacrylic acid chloride copolymer 479068-21-8P 479068-22-9P 479068-23-0P
479068-24-1P 479068-25-2P 479068-26-3P **479068-27-4P**
479068-28-5P 479068-29-6P 479068-30-9P **479068-31-0P**
479068-32-1P 479068-33-2P 479068-34-3P 479068-35-4P
479068-36-5P 479068-37-6P 479068-39-8P 479068-40-1P
479068-41-2P 479068-42-3P 479068-42-3P 479068-43-4P
479068-44-5P 479068-45-6P 479068-46-7P 479068-47-8P
479068-48-9P 479068-49-0P 479068-50-3P 479068-51-4P
479068-52-5P 479068-53-6P 479068-54-7P 479068-55-8P

479068-56-9P
(prepn. of resin particle contained in electrophotog. liq. developer)

L33 ANSWER 9 OF 14 HCA COPYRIGHT 2006 ACS on STN
138:9614 Electrophotographic liquid developer containing dispersed resin particles made by seed-polymerization. Kato, Eiichi (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2002341600 A2 20021127, 37 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2001-149621 20010518.

AB The title developer contains dispersed multi-layered core-shell resin particles in an aprotic solvent of .gtoreq.109 .OMEGA..cntdot.cm resistance and .ltoreq.3.5 dielec. const., wherein the resin particles are made of aprotic solvent-sol. monomers(A) with a mono-functional and a monomer, which form a copolymer with the monomers(A) and has F or Si-contg. substituent in the presence of the aprotic solvent-sol. dispersion-stabilizing polymer and seed particles of 0.05-1.0 .mu.m av. diam. by seed-polymn. The developer provides rapid development and the fixing process with the good dispersing characteristics and is suitable for electrophotog. printing plate-making.

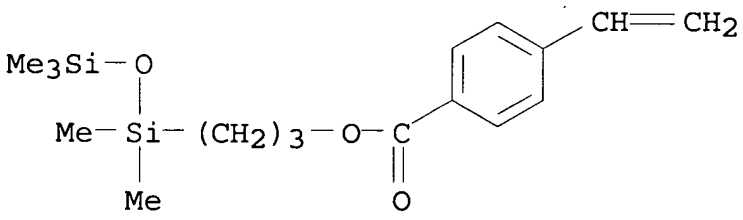
IT **477210-62-1P**
(dispersed resin particles in developer; electrophotog. liq. developer)

RN 477210-62-1 HCA

CN Benzoic acid, 4-ethenyl-, 3-(pentamethyldisiloxanyl)propyl ester, polymer with ethenyl acetate, graft (9CI) (CA INDEX NAME)

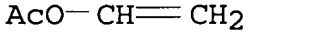
CM 1

CRN 477210-61-0
CMF C17 H28 O3 Si2



CM 2

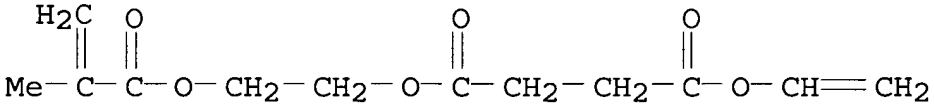
CRN 108-05-4
CMF C4 H6 O2



IT **477210-93-8**
(dispersion stabilizing polymer; electrophotog. liq. developer)
RN 477210-93-8 HCA
CN Butanedioic acid, ethenyl 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester, polymer with hexadecyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

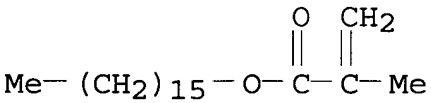
CM 1

CRN 100904-40-3
CMF C12 H16 O6



CM 2

CRN 2495-27-4
CMF C20 H38 O2



IC ICM G03G009-13
ICS C08F002-08; C08F002-44; C08F291-00
CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
IT 477210-59-6P 477210-60-9P **477210-62-1P** 477210-65-4P
477210-66-5P 477210-67-6P 477210-68-7P 477210-69-8P
477210-70-1P 477210-71-2P 477210-72-3P
(dispersed resin particles in developer; electrophotog. liq. developer)
IT 27756-15-6 34888-27-2 65291-67-0 156682-80-3
477210-93-8 477210-94-9 477210-95-0 477210-96-1
477210-97-2
(dispersion stabilizing polymer; electrophotog. liq. developer)

L33 ANSWER 10 OF 14 HCA COPYRIGHT 2006 ACS on STN
132:271645 Method for forming color image by electrophotography. Kato,

Eiichi; Nakazawa, Yusuke (Fuji Photo Film Co., Ltd., Japan). U.S. US 6045956 A 20000404, 58 pp., Cont.-in-part of U.S. Ser. No. 969,568, abandoned. (English). CODEN: USXXAM. APPLICATION: US 1999-365412 19990802. PRIORITY: JP 1994-277183 19941018; US 1995-533660 19950925; US 1997-969568 19971113.

AB A method for forming a color image comprises forming at least one color toner image on an electrophotog. photoreceptor whose surface shows a good toner image releasability, forming a peelable transfer layer on the electrophotog. photoreceptor bearing the toner image by electrodeposition using thermoplastic resin grains each contg. a resin (A) having a glass transition temp. of 10.degree.-140.degree. or a softening point of 35.degree.-180.degree. and a resin having a glass transition temp. of no more than 45.degree. or a softening point of no more than 60.degree. and its glass transition temp. or softening point is at least 2.degree. lower than that of the resin (A), transferring the toner image together with the transfer layer onto a primary receptor, and then transferring the toner image together with the transfer layer from the primary receptor onto a receiving material. The method provides a color image of high accuracy and high quality without color shear in a simple and stable manner irresp. of the kind of receiving material. The color duplicate obtained has good retouching and sealing properties and is excellent in storage stability.

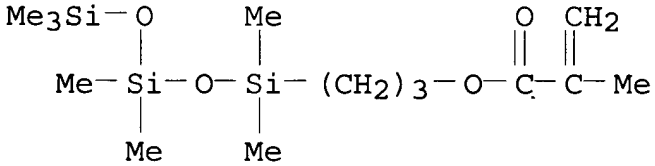
IT **263359-57-5P**
(electrophotog. photoreceptors with improved toner image transferability with surface layers contg.)

RN 263359-57-5 HCA

CN 2-Propenoic acid, 2-methyl-, 3-(heptamethyltrisiloxanyl)propyl ester, polymer with oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

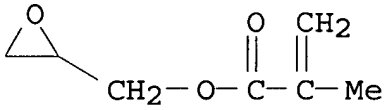
CM 1

CRN 150624-86-5
CMF C14 H32 O4 Si3



CM 2

CRN 106-91-2
CMF C7 H10 O3



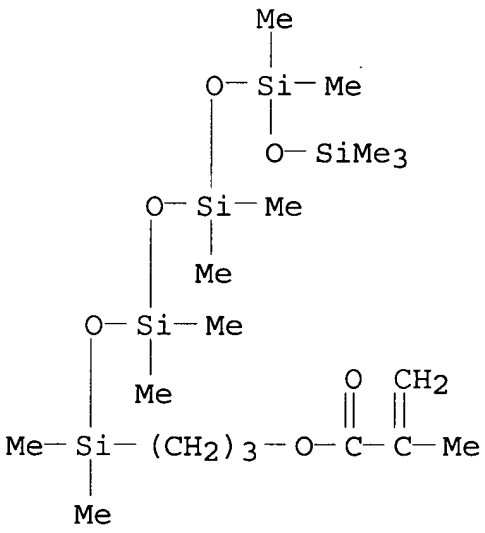
IT **150624-89-8P 176762-83-7P**
(prepn. and use in fabricating electrophotog. photoreceptors with improved toner image transferability)

RN 150624-89-8 HCA

CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with methyl 2-propenoate, oxiranylmethyl 2-methyl-2-propenoate and 3-(undecamethylpentasiloxanyl)propyl 2-methyl-2-propenoate, block (9CI) (CA INDEX NAME)

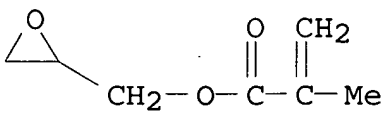
CM 1

CRN 107642-12-6
CMF C18 H44 O6 Si5



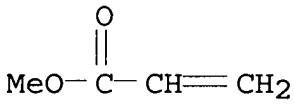
CM 2

CRN 106-91-2
CMF C7 H10 O3



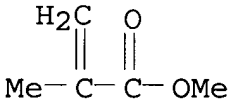
CM 3

CRN 96-33-3
CMF C4 H6 O2



CM 4

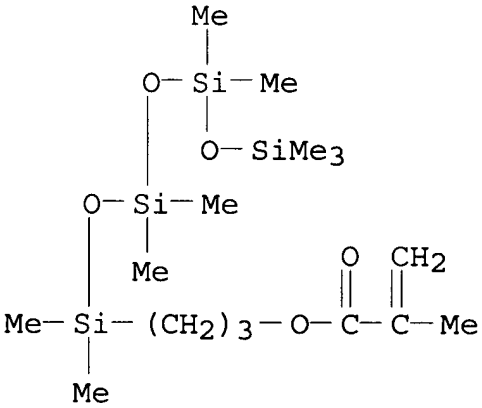
CRN 80-62-6
CMF C5 H8 O2



RN 176762-83-7 HCA
CN 2-Propenoic acid, 2-methyl-, 3-(nonamethyltetrasiloxanyl)propyl ester, polymer with oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

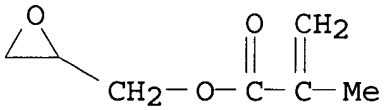
CM 1

CRN 77865-90-8
CMF C16 H38 O5 Si4



CM 2

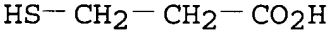
CRN 106-91-2
CMF C7 H10 O3



IT **263359-47-3P**
(prepn. and use in forming layers on electrophotog. photoreceptors with developed toner images for improved image transfer)
RN 263359-47-3 HCA
CN Butanedioic acid, ethenyl 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester, telomer with ethenyl acetate, ethenyl butanoate, 3-mercaptopropanoic acid, methyl 2-methyl-2-propenoate, 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl 5-[(2-methyl-1-oxo-2-propenyl)oxy]pentyl butanedioate, methyl 2-propenoate and octadecyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 107-96-0
CMF C3 H6 O2 S

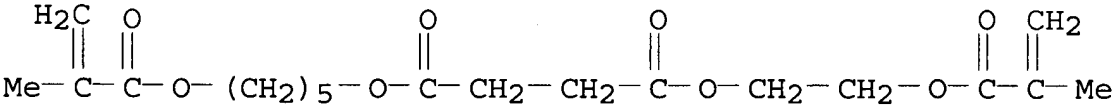


CM 2

CRN 263359-46-2
CMF (C22 H42 O2 . C19 H28 O8 . C12 H16 O6 . C6 H10 O2 . C5 H8 O2 . C4 H6 O2 . C4 H6 O2)x
CCI PMS

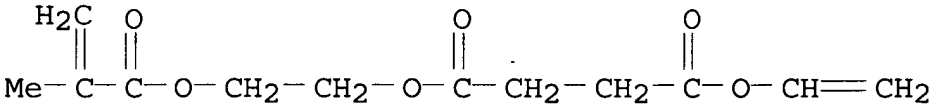
CM 3

CRN 190894-43-0
CMF C19 H28 O8



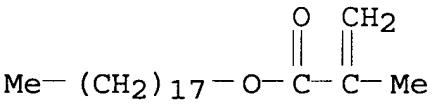
CM 4

CRN 100904-40-3
CMF C12 H16 O6



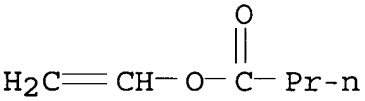
CM 5

CRN 32360-05-7
CMF C22 H42 O2



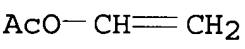
CM 6

CRN 123-20-6
CMF C6 H10 O2



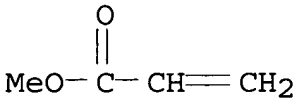
CM 7

CRN 108-05-4
CMF C4 H6 O2



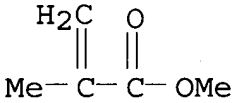
CM 8

CRN 96-33-3
CMF C4 H6 O2



CM 9

CRN 80-62-6
CMF C5 H8 O2



IC ICM G03G013-01
INCL 430047000
CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
IT **263359-57-5P**
(electrophotog. photoreceptors with improved toner image transferability with surface layers contg.)
IT 80-62-6DP, Methyl methacrylate, copolymers with dimethylsiloxanes 93705-98-7P 142199-79-9P 144541-84-4P 149643-10-7P 150551-84-1P 150551-85-2P 150551-86-3P 150551-90-9P 150551-91-0P 150551-92-1P 150624-67-2P **150624-89-8P** 150625-01-7P 150625-03-9P 150625-22-2P 150642-22-1P 150642-24-3P 155292-83-4P, Ethyl methacrylate-glycidyl methacrylate-perfluorooctylethyl methacrylate graft copolymer 155292-84-5P 155292-86-7P 155292-87-8P 155292-90-3P 155292-93-6P 155292-98-1P 155293-26-8P 156658-62-7P 161552-54-1P 161552-57-4P 169046-28-0P 169046-29-1P 169046-30-4P 169046-31-5P 169046-33-7P 169046-34-8P 169046-35-9P 176762-48-4P 176762-82-6P **176762-83-7P** 176762-84-8P 263359-29-1P 263359-31-5P 263359-32-6P 263359-33-7P 263359-34-8P 263359-35-9P 263359-37-1P 263359-39-3P 263359-40-6P 263359-42-8P 263359-43-9P 263359-44-0P 263388-81-4P 263388-83-6P 263388-86-9P
(prepn. and use in fabricating electrophotog. photoreceptors with improved toner image transferability)
IT 9010-88-2P, Methyl methacrylate-ethyl acrylate copolymer 24937-78-8P, Evaflex 45X 26616-87-5P, Styrene-butadiene-vinyl acetate copolymer 26715-83-3P, Vinyl acetate-vinyl propionate copolymer 31799-28-7P, Methyl acrylate-methyl methacrylate-vinyl acetate copolymer 39534-65-1P, Methyl methacrylate-dodecyl methacrylate-ethyl acrylate copolymer 176762-85-9P 188951-09-9P, 1,10-Decanediol-terephthalic acid-1,5-pentanediol-carbonic acid

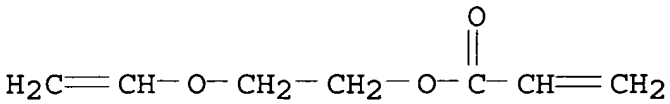
copolymer **263359-47-3P** 263359-48-4P 263359-49-5P, Phenethyl methacrylate-2-butoxyethyl methacrylate-methyl methacrylate-2-(2-butoxyethoxy)ethyl methacrylate copolymer 263359-50-8P, Vinyl acetate-vinyl valerate-methyl methacrylate-methyl acrylate copolymer 263359-51-9P, Methyl methacrylate-2,3-dibutyroyloxypropyl methacrylate-3-phenylpropyl methacrylate-3-propoxypropyl methacrylate copolymer 263359-52-0P, Methyl methacrylate-2-phenoxyethyl methacrylate-2-butoxycarbonylethyl methacrylate copolymer 263359-53-1P, Methyl methacrylate-methyl acrylate-hexyl acrylate copolymer 263359-54-2P, Styrene-methylstyrene-vinyl acetate-vinyl propionate copolymer 263359-55-3P, Vinyl acetate-crotonic acid-vinyl butyrate-methyl methacrylate-butyl acrylate copolymer 263388-89-2P 263388-91-6P, Methyl methacrylate-butyl acrylate-Kemit R 185 copolymer
(prepn. and use in forming layers on electrophotog. photoreceptors with developed toner images for improved image transfer)

L33 ANSWER 11 OF 14 HCA COPYRIGHT 2006 ACS on STN
129:148807 Reactions of complex ligands. Part 81. Chromium complex-catalyzed synthesis of spirocyclopropanes from diaryl diazo compounds. Direct NMR-spectroscopic observation of a carbene complex intermediate. Pfeiffer, Juergen; Nieger, Martin; Doetz, Karl Heinz (Kekule-Institut Organische Chemie Biochemie, Rheinische Friedrich-Wilhelms-Universitaet, Bonn, D-53121, Germany). European Journal of Organic Chemistry (6), 1011-1022 (English) 1998. CODEN: EJOCFK. ISSN: 1434-193X. OTHER SOURCES: CASREACT 129:148807. Publisher: Wiley-VCH Verlag GmbH.

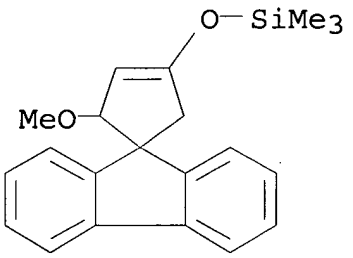
AB The [2+1] cycloaddn. of electron-rich alkenes such as enol ethers with 9-diazo-9H-fluorene is efficiently catalyzed by pentacarbonyl(.eta.2-cis-cyclooctene)chromium(0). This cyclopropanation reaction shows a pronounced preference for electron-rich C:C bonds, as demonstrated by the regioselective reactions of CH2:CH2OCH:CH2 and CH2:CHCO2(CH2)2OCH:CH2. The [2+1] cycloaddn. proceeds via the carbene complex intermediate pentacarbonyl(9H-fluoren-9-ylidene)chromium, which was detected by 13C NMR in the course of the reaction. (Z)-MeCH:CHOCH2Ph yields a spirocyclopropane with retention of the configuration of the former olefinic double bond. Whereas 1-diazo-1H-indene and 9-diazo-9,10-dihydro-10,10-dimethylanthracene react with EtOCH:CH2 to give low yields of cyclopropanes, 5-diazo-5H-dibenzo[a,d]cycloheptene and 4-MeOC6H4PhCN2 afford moderate yields of olefin metathesis products. The competition between cyclopropanation and olefin metathesis reflects the propensity of the carbene complex intermediates to undergo decarbonylation.

IT **41440-38-4**, 2-Vinyloxyethyl acrylate
(prepn. of spirocyclopropanes from diaryl diazo compds. with

catalysis of chromium complexes)
RN 41440-38-4 HCA
CN 2-Propenoic acid, 2-(ethenyloxy)ethyl ester (9CI) (CA INDEX NAME)



IT **210886-66-1P**
(prepn. of spirocyclopropanes from diaryl diazo compds. with catalysis of chromium complexes)
RN 210886-66-1 HCA
CN Silane, [(5-methoxyspiro[3-cyclopentene-1,9'-[9H]fluoren]-3-yl)oxy]trimethyl- (9CI) (CA INDEX NAME)



CC 25-26 (Benzene, Its Derivatives, and Condensed Benzenoid Compounds)
Section cross-reference(s): 22
IT 100-42-5, reactions 109-92-2 110-87-2 116-11-0 832-80-4 1191-99-7, 2,3-Dihydrofuran 3917-15-5, Allyl vinyl ether 6141-56-6 20359-74-4 22618-03-7 32426-80-5 35847-40-6 **41440-38-4**, 2-Vinyloxyethyl acrylate 54125-02-9 85199-64-0 133634-82-9
(prepn. of spirocyclopropanes from diaryl diazo compds. with catalysis of chromium complexes)
IT 746-47-4P, 9,9'-Bifluorenylidene 2071-44-5P 2975-79-3P 4333-75-9P 10423-18-4P 21328-27-8P 71350-88-4P 109218-00-0P 202334-20-1P 202334-21-2P 208332-32-5P 210886-65-0P **210886-66-1P** 210886-67-2P 210886-68-3P 210886-69-4P 210886-70-7P 210886-73-0P 210886-74-1P 210886-75-2P
(prepn. of spirocyclopropanes from diaryl diazo compds. with catalysis of chromium complexes)

L33 ANSWER 12 OF 14 HCA COPYRIGHT 2006 ACS on STN
127:57972 Electrophotographic image formation. Kato, Eiichi (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 09106202 A2 19970422 Heisei, 42 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 1996-208632 19960807. PRIORITY: JP 1995-222778 19950809.

AB The title image formation uses a photoreceptor having 2 laminated peelable transfer layers to form an electrophotog. toner image and then to thermally transfer the toner image to a recording material, wherein the 1st transfer layer is formed by electro-depositing thermoplastic resin particles contg. 2 kinds of specified resins with different softening point and glass transition point in 1 particle, and the 2nd transfer layer contains a different resin.

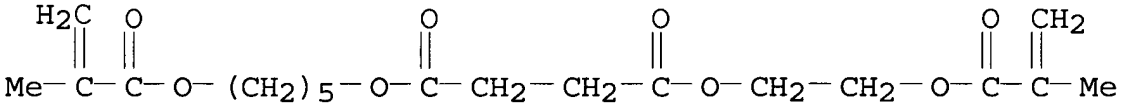
IT **190894-44-1P 190894-45-2P 190894-46-3P**
190894-47-4P 190894-48-5P 190894-49-6P
190894-50-9P 190894-51-0P 190894-52-1DP,
reaction products with thiacetic acid and hydroxyethyl methacrylate
190894-53-2DP, reaction products with thiopropanoic acid and hydroxyethyl acrylate **190894-54-3DP**, reaction products with thioethyl methacrylate **190894-56-5P**
190903-33-4DP, reaction products with thiopropanoic acid and hydroxyethyl acrylate
(prepd. as thermoplastic resin particle for transfer layer of electrophotog. photoreceptor for image formation)

RN 190894-44-1 HCA

CN Butanedioic acid, ethenyl 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester, polymer with ethenyl acetate, ethenyl butanoate, methyl 2-methyl-2-propenoate, 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl 5-[(2-methyl-1-oxo-2-propenyl)oxy]pentyl butanedioate, methyl 2-propenoate and octadecyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

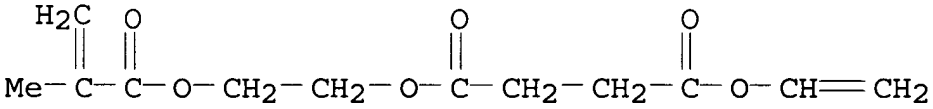
CM 1

CRN 190894-43-0
CMF C19 H28 O8



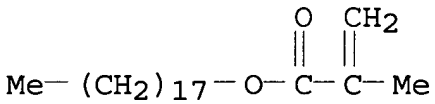
CM 2

CRN 100904-40-3
CMF C12 H16 O6



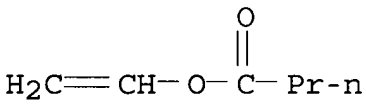
CM 3

CRN 32360-05-7
CMF C22 H42 O2



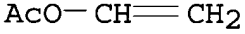
CM 4

CRN 123-20-6
CMF C6 H10 O2



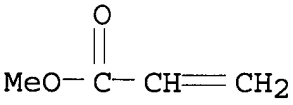
CM 5

CRN 108-05-4
CMF C4 H6 O2



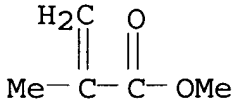
CM 6

CRN 96-33-3
CMF C4 H6 O2



CM 7

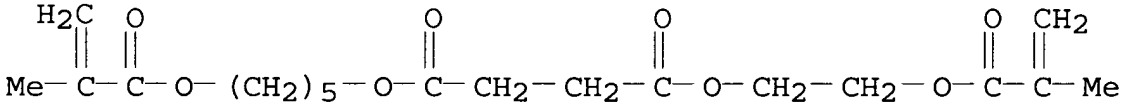
CRN 80-62-6
CMF C5 H8 O2



RN 190894-45-2 HCA
CN Butanedioic acid, ethenyl 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester, polymer with butyl 2-propenoate, methyl 2-methyl-2-propenoate, 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl 5-[(2-methyl-1-oxo-2-propenyl)oxy]pentyl butanedioate, octadecyl 2-methyl-2-propenoate and 2-propoxyethyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

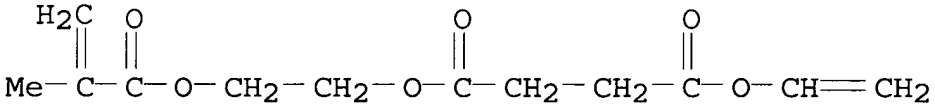
CM 1

CRN 190894-43-0
CMF C19 H28 O8



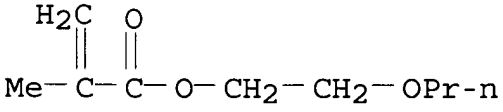
CM 2

CRN 100904-40-3
CMF C12 H16 O6



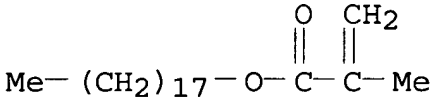
CM 3

CRN 45023-48-1
CMF C9 H16 O3



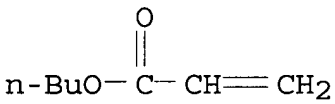
CM 4

CRN 32360-05-7
CMF C22 H42 O2



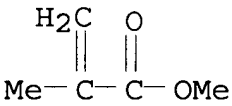
CM 5

CRN 141-32-2
CMF C7 H12 O2



CM 6

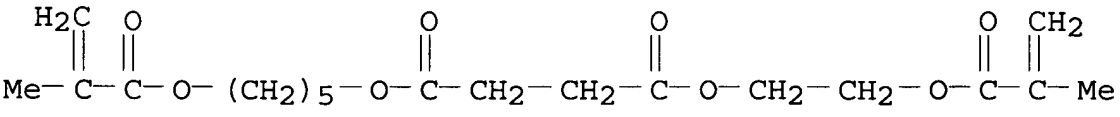
CRN 80-62-6
CMF C5 H8 O2



RN 190894-46-3 HCA
CN Butanedioic acid, ethenyl 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester, polymer with ethenyl acetate, 2-(hexyloxy)ethyl 2-methyl-2-propenoate, methyl 2-methyl-2-propenoate, 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl 5-[(2-methyl-1-oxo-2-propenyl)oxy]pentyl butanedioate and octadecyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

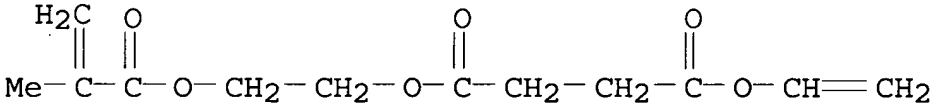
CM 1

CRN 190894-43-0
CMF C19 H28 O8



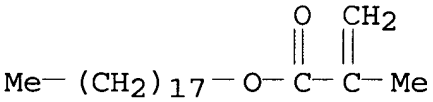
CM 2

CRN 100904-40-3
CMF C12 H16 O6



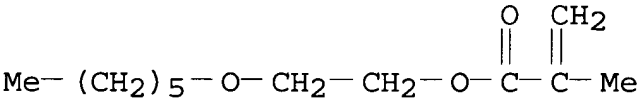
CM 3

CRN 32360-05-7
CMF C22 H42 O2



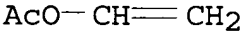
CM 4

CRN 24260-60-4
CMF C12 H22 O3



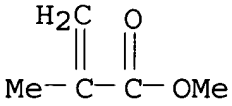
CM 5

CRN 108-05-4
CMF C4 H6 O2



CM 6

CRN 80-62-6
CMF C5 H8 O2

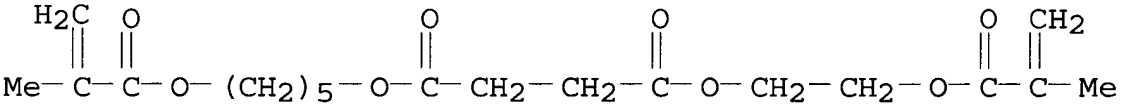


RN 190894-47-4 HCA

CN Butanedioic acid, ethenyl 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester, polymer with 2-(2-butoxyethoxy)ethyl 2-methyl-2-propenoate, 2-butoxyethyl 2-methyl-2-propenoate, methyl 2-methyl-2-propenoate, 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl 5-[(2-methyl-1-oxo-2-propenyl)oxy]pentyl butanedioate, octadecyl 2-methyl-2-propenoate and 2-phenylethyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

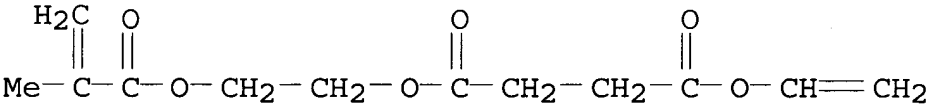
CM 1

CRN 190894-43-0
CMF C19 H28 O8



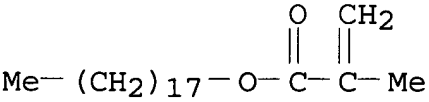
CM 2

CRN 100904-40-3
CMF C12 H16 O6



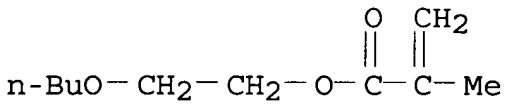
CM 3

CRN 32360-05-7
CMF C22 H42 O2



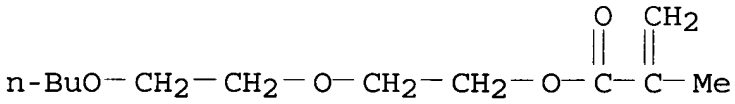
CM 4

CRN 13532-94-0
CMF C10 H18 O3



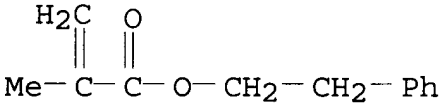
CM 5

CRN 7328-22-5
CMF C12 H22 O4



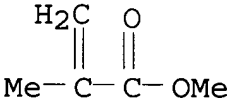
CM 6

CRN 3683-12-3
CMF C12 H14 O2



CM 7

CRN 80-62-6
CMF C5 H8 O2

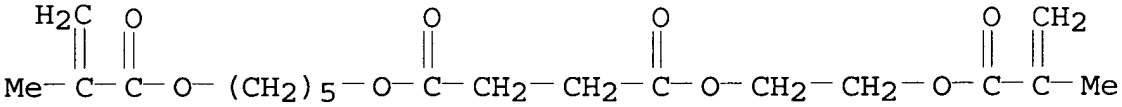


RN 190894-48-5 HCA
CN Butanedioic acid, ethenyl 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester, polymer with 2-(2-butoxyethoxy)ethyl 2-methyl-2-propenoate, ethenyl acetate, ethenyl pentanoate, methyl 2-methyl-2-propenoate, 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl 5-[(2-methyl-1-oxo-2-

propenyl)oxy]pentyl butanedioate and octadecyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

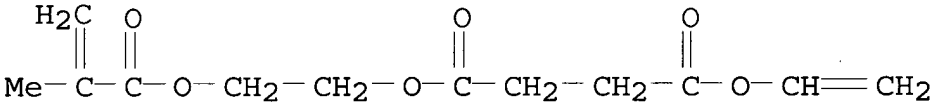
CM 1

CRN 190894-43-0
CMF C19 H28 O8



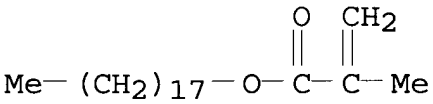
CM 2

CRN 100904-40-3
CMF C12 H16 O6



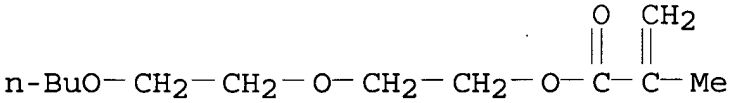
CM 3

CRN 32360-05-7
CMF C22 H42 O2



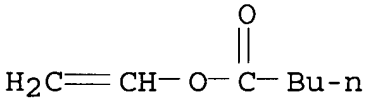
CM 4

CRN 7328-22-5
CMF C12 H22 O4



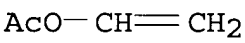
CM 5

CRN 5873-43-8
CMF C7 H12 O2



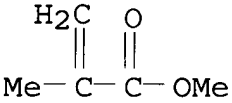
CM 6

CRN 108-05-4
CMF C4 H6 O2



CM 7

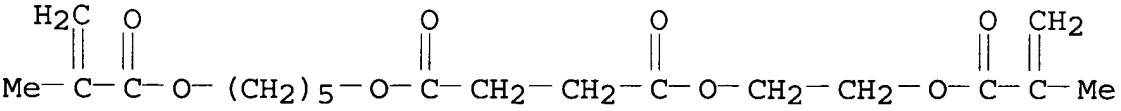
CRN 80-62-6
CMF C5 H8 O2



RN 190894-49-6 HCA
CN Butanedioic acid, ethenyl 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester, polymer with 2,3-dibutoxypropyl 2-methyl-2-propenoate, methyl 2-methyl-2-propenoate, 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl 5-[(2-methyl-1-oxo-2-propenyl)oxy]pentyl butanedioate, octadecyl 2-methyl-2-propenoate, 3-phenylpropyl 2-methyl-2-propenoate and 3-propoxypropyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

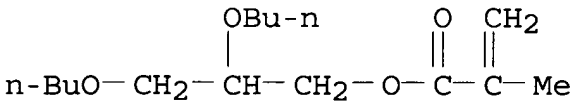
CM 1

CRN 190894-43-0
CMF C19 H28 O8



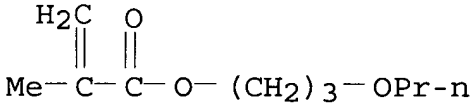
CM 2

CRN 188950-87-0
CMF C15 H28 O4



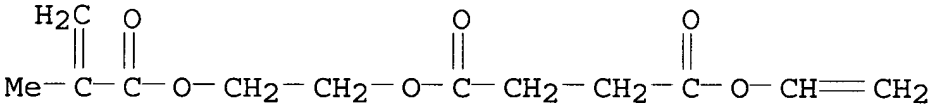
CM 3

CRN 187836-63-1
CMF C10 H18 O3



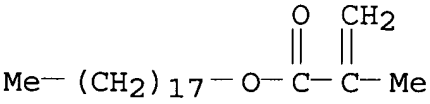
CM 4

CRN 100904-40-3
CMF C12 H16 O6



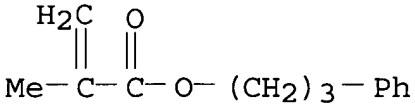
CM 5

CRN 32360-05-7
CMF C22 H42 O2



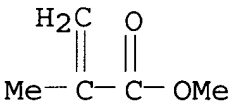
CM 6

CRN 3683-14-5
CMF C13 H16 O2



CM 7

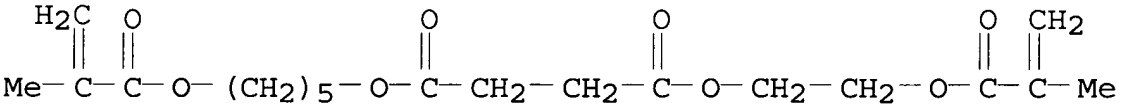
CRN 80-62-6
CMF C5 H8 O2



RN 190894-50-9 HCA
CN Butanedioic acid, ethenyl 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester, polymer with 3-butoxy-3-oxopropyl 2-methyl-2-propenoate, 2,3-dibutoxypropyl 2-methyl-2-propenoate, methyl 2-methyl-2-propenoate, 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl 5-[(2-methyl-1-oxo-2-propenyl)oxy]pentyl butanedioate and octadecyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

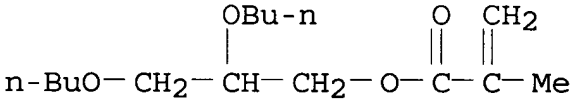
CM 1

CRN 190894-43-0
CMF C19 H28 O8



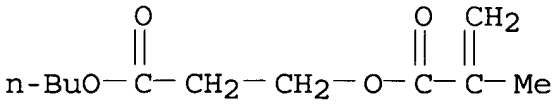
CM 2

CRN 188950-87-0
CMF C15 H28 O4



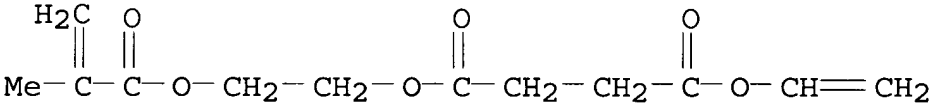
CM 3

CRN 117231-54-6
CMF C11 H18 O4



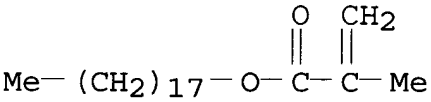
CM 4

CRN 100904-40-3
CMF C12 H16 O6



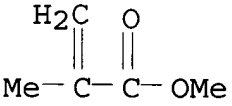
CM 5

CRN 32360-05-7
CMF C22 H42 O2



CM 6

CRN 80-62-6
CMF C5 H8 O2

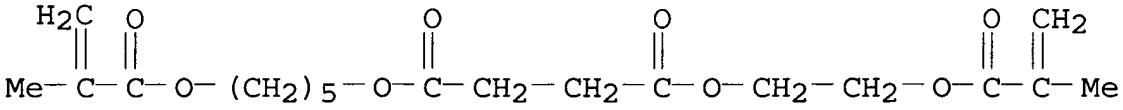


RN 190894-51-0 HCA
CN Butanedioic acid, ethenyl 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester, polymer with decyl 2-methyl-2-propenoate, ethyl 2-methyl-2-propenoate, 2-methoxyethyl 2-methyl-2-propenoate, methyl 2-methyl-2-propenoate, 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl 5-[(2-methyl-1-oxo-2-propenyl)oxy]pentyl butanedioate and octadecyl

2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

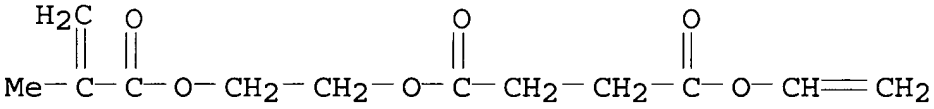
CM 1

CRN 190894-43-0
CMF C19 H28 O8



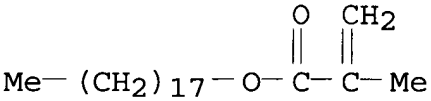
CM 2

CRN 100904-40-3
CMF C12 H16 O6



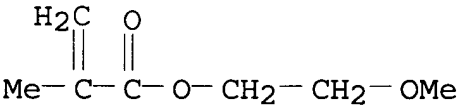
CM 3

CRN 32360-05-7
CMF C22 H42 O2



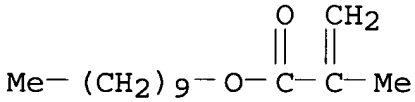
CM 4

CRN 6976-93-8
CMF C7 H12 O3



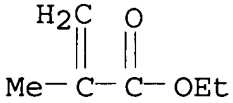
CM 5

CRN 3179-47-3
CMF C14 H26 O2



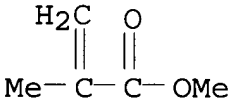
CM 6

CRN 97-63-2
CMF C6 H10 O2



CM 7

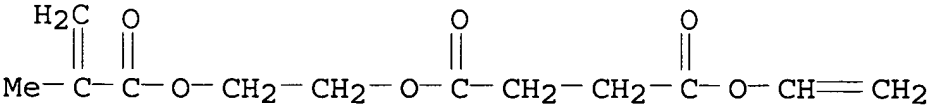
CRN 80-62-6
CMF C5 H8 O2



RN 190894-52-1 HCA
CN Butanedioic acid, ethenyl 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester, polymer with dodecyl 2-methyl-2-propenoate, ethenyl acetate, ethenyl pentanoate, 2-ethylhexyl 2-propenoate, octadecyl 2-methyl-2-propenoate, phenylmethyl 2-methyl-2-propenoate and 2,2,3,3-tetrafluoropropyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

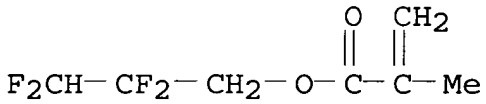
CM 1

CRN 100904-40-3
CMF C12 H16 O6



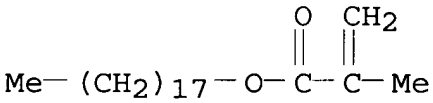
CM 2

CRN 45102-52-1
CMF C7 H8 F4 O2



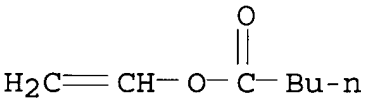
CM 3

CRN 32360-05-7
CMF C22 H42 O2



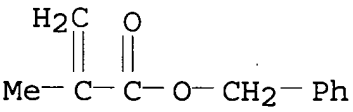
CM 4

CRN 5873-43-8
CMF C7 H12 O2



CM 5

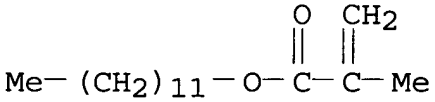
CRN 2495-37-6
CMF C11 H12 O2



CM 6

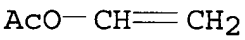
CRN 142-90-5

CMF C16 H30 O2



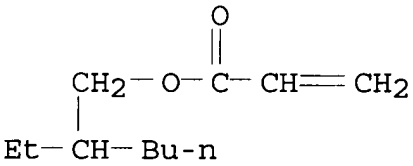
CM 7

CRN 108-05-4
CMF C4 H6 O2



CM 8

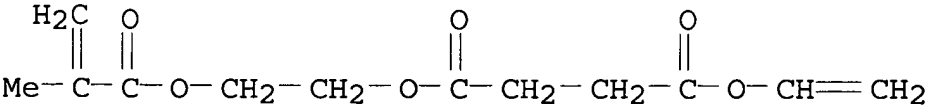
CRN 103-11-7
CMF C11 H20 O2



RN 190894-53-2 HCA
CN Butanedioic acid, ethenyl 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester, polymer with dodecyl 2-methyl-2-propenoate, ethenyl acetate, ethenyl pentanoate, 2-ethylhexyl 2-propenoate, octadecyl 2-methyl-2-propenoate, phenylmethyl 2-methyl-2-propenoate and 3-[1,3,3,3-tetramethyl-1-[(trimethylsilyl)oxy]disiloxanyl]propyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

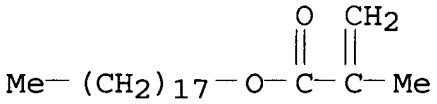
CM 1

CRN 100904-40-3
CMF C12 H16 O6



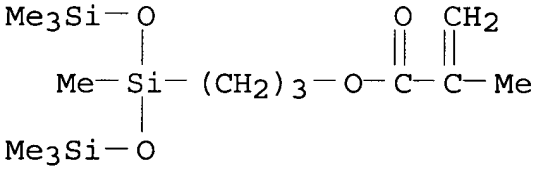
CM 2

CRN 32360-05-7
CMF C22 H42 O2



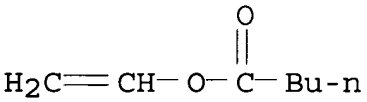
CM 3

CRN 19309-90-1
CMF C14 H32 O4 Si3



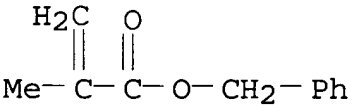
CM 4

CRN 5873-43-8
CMF C7 H12 O2



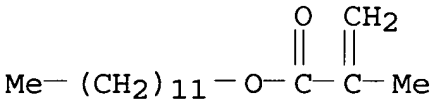
CM 5

CRN 2495-37-6
CMF C11 H12 O2



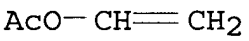
CM 6

CRN 142-90-5
CMF C16 H30 O2



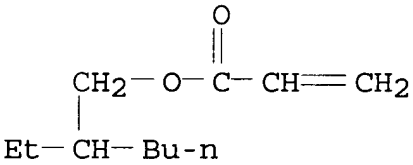
CM 7

CRN 108-05-4
CMF C4 H6 O2



CM 8

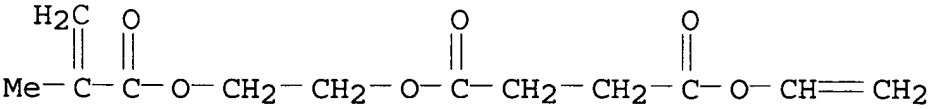
CRN 103-11-7
CMF C11 H20 O2



RN 190894-54-3 HCA
CN Butanedioic acid, ethenyl 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester, polymer with dodecyl 2-methyl-2-propenoate, ethenyl acetate, ethenyl pentanoate, 2-ethylhexyl 2-propenoate, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-methyl-2-propenoate, octadecyl 2-methyl-2-propenoate and phenylmethyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

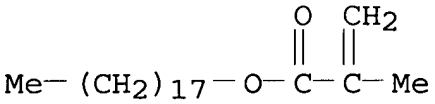
CM 1

CRN 100904-40-3
CMF C12 H16 O6



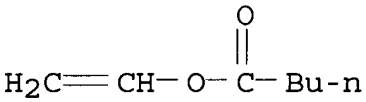
CM 2

CRN 32360-05-7
CMF C22 H42 O2



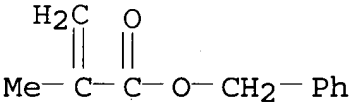
CM 3

CRN 5873-43-8
CMF C7 H12 O2



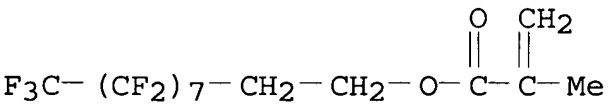
CM 4

CRN 2495-37-6
CMF C11 H12 O2



CM 5

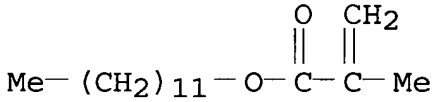
CRN 1996-88-9
CMF C14 H9 F17 O2



CM 6

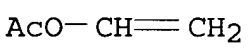
CRN 142-90-5

CMF C16 H30 O2



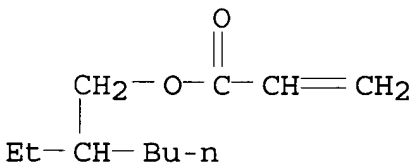
CM 7

CRN 108-05-4
CMF C4 H6 O2



CM 8

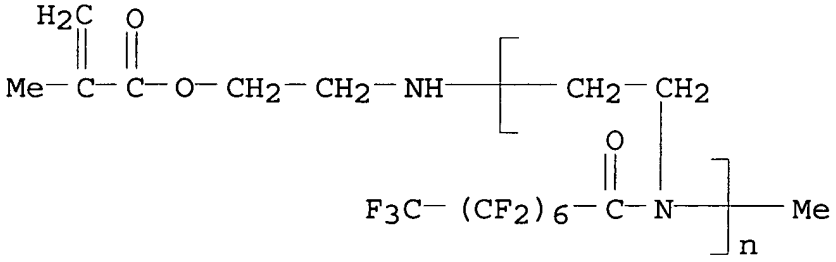
CRN 103-11-7
CMF C11 H20 O2



RN 190894-56-5 HCA
CN Butanedioic acid, ethenyl 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester, polymer with ethenyl acetate, ethenyl pentanoate, 2-ethylhexyl 2-propenoate, .alpha.-methyl-.omega.-[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]amino]poly[[(2,2,3,3,4,4,5,5,6,6,7,7,8,8,8-pentadecafluoro-1-oxooctyl)imino]-1,2-ethanediyl], methyl 2-methyl-2-propenoate, octadecyl 2-methyl-2-propenoate and phenylmethyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

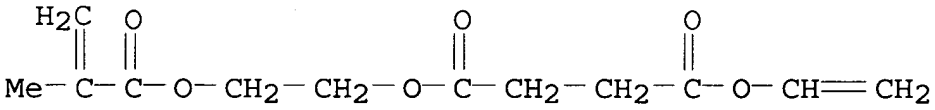
CM 1

CRN 188950-78-9
CMF (C10 H4 F15 N O)n C7 H13 N O2
CCI PMS



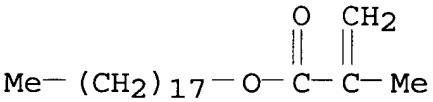
CM 2

CRN 100904-40-3
CMF C12 H16 O6



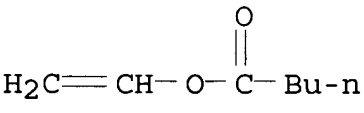
CM 3

CRN 32360-05-7
CMF C22 H42 O2



CM 4

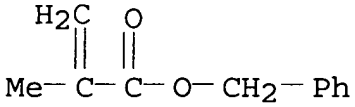
CRN 5873-43-8
CMF C7 H12 O2



CM 5

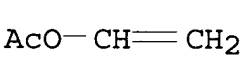
CRN 2495-37-6

CMF C11 H12 O2



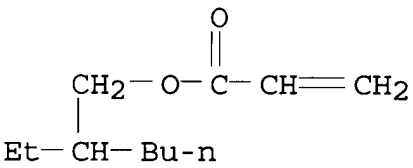
CM 6

CRN 108-05-4
CMF C4 H6 O2



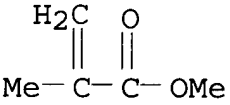
CM 7

CRN 103-11-7
CMF C11 H20 O2



CM 8

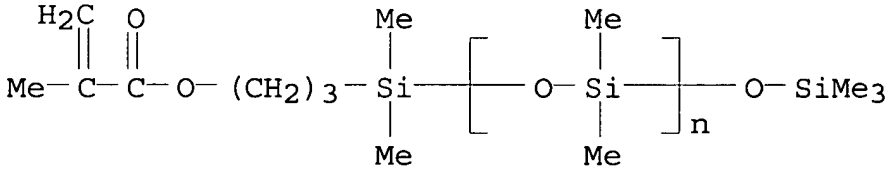
CRN 80-62-6
CMF C5 H8 O2



RN 190903-33-4 HCA
CN Butanedioic acid, ethenyl 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester, polymer with .alpha.-[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]-.omega.-[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)], dodecyl 2-methyl-2-propenoate, ethenyl acetate, ethenyl pentanoate, 2-ethylhexyl 2-propenoate, octadecyl 2-methyl-2-propenoate and phenylmethyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

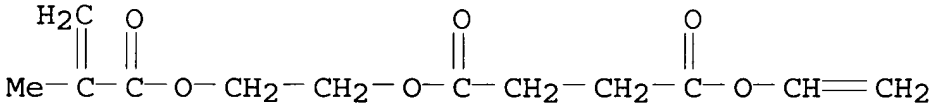
CM 1

CRN 123109-42-2
CMF (C2 H6 O Si)n C12 H26 O3 Si2
CCI PMS



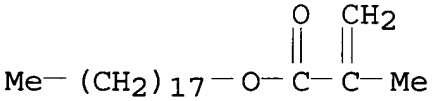
CM 2

CRN 100904-40-3
CMF C12 H16 O6



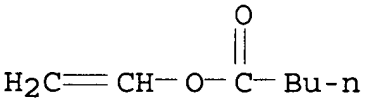
CM 3

CRN 32360-05-7
CMF C22 H42 O2



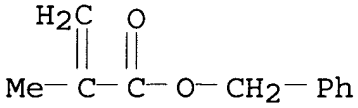
CM 4

CRN 5873-43-8
CMF C7 H12 O2



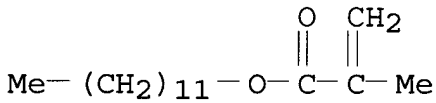
CM 5

CRN 2495-37-6
CMF C11 H12 O2



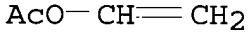
CM 6

CRN 142-90-5
CMF C16 H30 O2



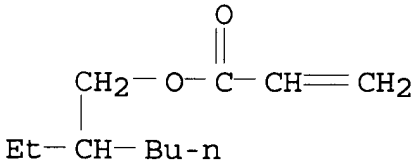
CM 7

CRN 108-05-4
CMF C4 H6 O2



CM 8

CRN 103-11-7
CMF C11 H20 O2

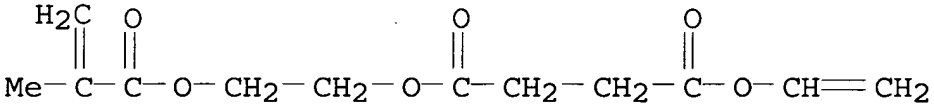


IT **190894-57-6P**
(prepd. for forming transfer layer of electrophotog. photoreceptor for image formation)
RN 190894-57-6 HCA
CN Butanedioic acid, ethenyl 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl

ester, polymer with ethenyl acetate, ethenyl propanoate and octadecyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

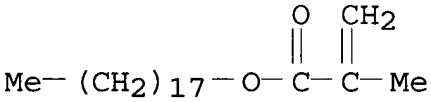
CM 1

CRN 100904-40-3
CMF C12 H16 O6



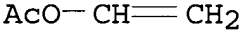
CM 2

CRN 32360-05-7
CMF C22 H42 O2



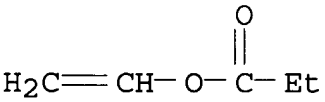
CM 3

CRN 108-05-4
CMF C4 H6 O2



CM 4

CRN 105-38-4
CMF C5 H8 O2

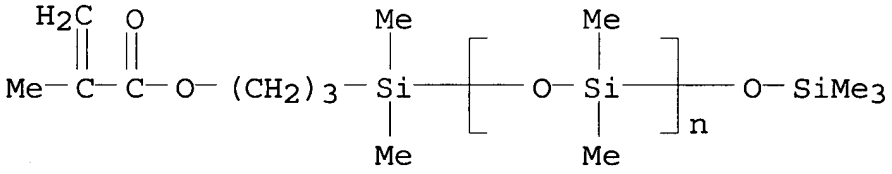


IT **190894-75-8 190894-78-1**
(used for increasing peeling ability of transfer layer for electrophotog. photoreceptor for image formation)
RN 190894-75-8 HCA

CN 2-Propenoic acid, 2-methyl-, ethyl ester, polymer with .alpha.-[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]-.omega.-[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)] and oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

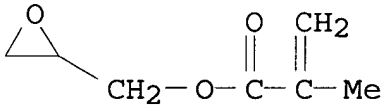
CM 1

CRN 123109-42-2
CMF (C2 H6 O Si)n C12 H26 O3 Si2
CCI PMS



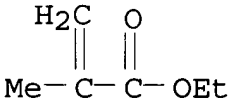
CM 2

CRN 106-91-2
CMF C7 H10 O3



CM 3

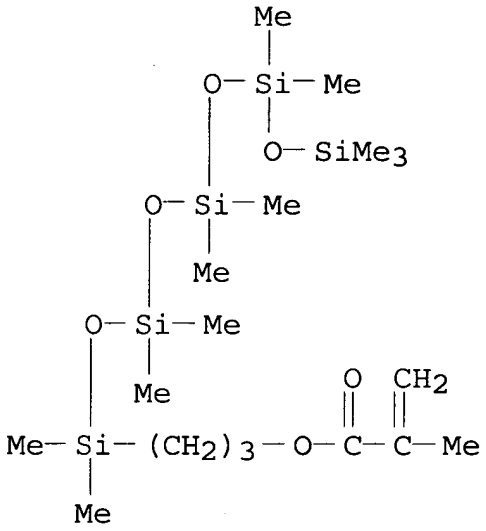
CRN 97-63-2
CMF C6 H10 O2



RN 190894-78-1 HCA
CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with methyl 2-propenoate, oxiranylmethyl 2-propenoate and 3-(undecamethylpentasiloxanyl)propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

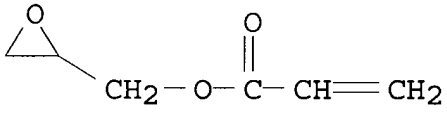
CM 1

CRN 107642-12-6
CMF C18 H44 O6 Si5



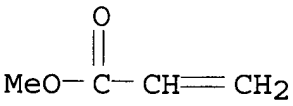
CM 2

CRN 106-90-1
CMF C6 H8 O3



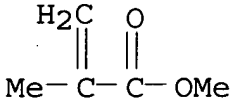
CM 3

CRN 96-33-3
CMF C4 H6 O2



CM 4

CRN 80-62-6
CMF C5 H8 O2



IC ICM G03G015-16
ICS G03G007-00; G03G015-01
CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
IT **190894-44-1P 190894-45-2P 190894-46-3P 190894-47-4P 190894-48-5P 190894-49-6P 190894-50-9P 190894-51-0P 190894-52-1DP**, reaction products with thiacetic acid and hydroxyethyl methacrylate **190894-53-2DP**, reaction products with thiopropanoic acid and hydroxyethyl acrylate **190894-54-3DP**, reaction products with thioethyl methacrylate 190894-55-4DP, reaction products with thiopropanoic acid and aminoethyl methacrylate **190894-56-5P 190903-33-4DP**, reaction products with thiopropanoic acid and hydroxyethyl acrylate
(prepd. as thermoplastic resin particle for transfer layer of electrophotog. photoreceptor for image formation)
IT **190894-57-6P** 190894-59-8P 190894-60-1P 190894-61-2P 190894-62-3P 190894-63-4P 190894-64-5P 190894-66-7P 190894-67-8P 190894-68-9P 190894-69-0P 190894-70-3P 190894-71-4P
(prepd. for forming transfer layer of electrophotog. photoreceptor for image formation)
IT 58258-12-1 162127-42-6 166594-75-8 **190894-75-8** 190894-76-9 190894-77-0D, reaction products with thioethyl methacrylate **190894-78-1** 190894-79-2 190894-81-6
(used for increasing peeling ability of transfer layer for electrophotog. photoreceptor for image formation)

L33 ANSWER 13 OF 14 HCA COPYRIGHT 2006 ACS on STN
126:349707 Preparing printing plates by electrophotography. Kato, Eiichi; Nakazawa, Yusuke; Ishii, Kazuo (Fuji Photo Film Co., Ltd., Japan). Brit. UK Pat. Appl. GB 2302063 A1 19970108, 248 pp. (English). CODEN: BAXXDU. APPLICATION: GB 1996-12258 19960612. PRIORITY: JP 1995-144885 19950612.
AB Printing plates are prepd. by forming a toner image on a peelable transfer layer contg. a resin, capable of being removed by chem. reaction, on an electrophotog. light-sensitive element, providing an adhesive layer contg. a thermoplastic resin only on the toner image, transferring the toner image together with the transfer layer and the adhesive layer from the element to a temporary receptor, transferring the toner image with the layers to a receiving material

with a hydrophilic surface, and partially removing the transfer layer by chem. reaction. Printing plates which produce good prints can be obtained for a long period of time even when the thickness of the transfer layer is reduced or the transfer is conducted under low temp., low pressure, and high speed.

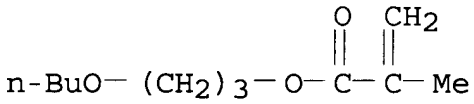
IT **188950-75-6 188950-80-3**, Crotonic acid;ethenyl 2-[(1-oxo-2-propenyl)oxy]ethyl butanedioate;tridecyl methacrylate;vinyl acetate;vinyl valerate graft copolymer **188950-89-2 188950-91-6 188951-10-2**
(prepn. and use in prepg. transfer layers for electrophotog. photoreceptors for manuf. of printing plates)

RN 188950-75-6 HCA

CN 2-Propenoic acid, 2-methyl-, 3-butoxypropyl ester, polymer with hexadecyl 2-methyl-2-propenoate, 2-phenylethyl 2-methyl-2-propenoate, 2-propenoic acid and 3-[1,3,3,3-tetramethyl-1-[(trimethylsilyl)oxy]disiloxanyl]propyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

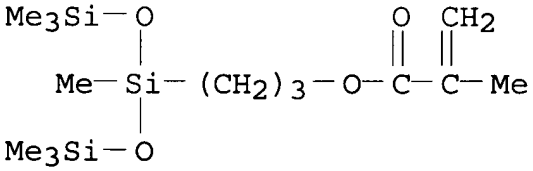
CM 1

CRN 188950-64-3
CMF C11 H20 O3



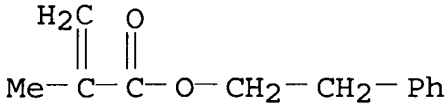
CM 2

CRN 19309-90-1
CMF C14 H32 O4 Si3



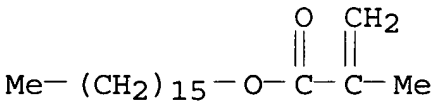
CM 3

CRN 3683-12-3
CMF C12 H14 O2



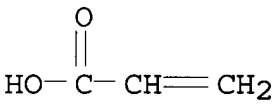
CM 4

CRN 2495-27-4
CMF C20 H38 O2



CM 5

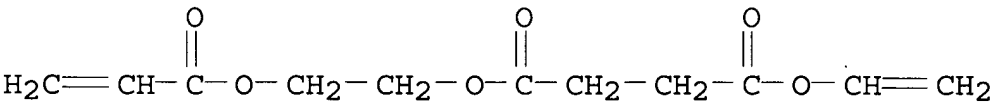
CRN 79-10-7
CMF C3 H4 O2



RN 188950-80-3 HCA
CN Butanedioic acid, ethenyl 2-[(1-oxo-2-propenyl)oxy]ethyl ester, polymer with 2-butenoic acid, ethenyl acetate, ethenyl pentanoate and tridecyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

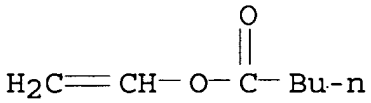
CM 1

CRN 120516-07-6
CMF C11 H14 O6



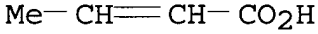
CM 2

CRN 5873-43-8
CMF C7 H12 O2



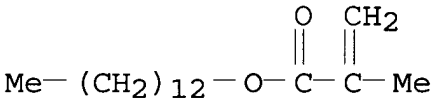
CM 3

CRN 3724-65-0
CMF C4 H6 O2



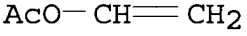
CM 4

CRN 2495-25-2
CMF C17 H32 O2



CM 5

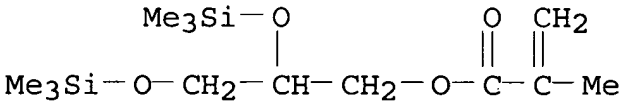
CRN 108-05-4
CMF C4 H6 O2



RN 188950-89-2 HCA
CN 2-Propenoic acid, 2-methyl-, 2,3-bis[(trimethylsilyl)oxy]propyl ester, polymer with 2-ethoxyethyl 2-propenoate, 2-methylphenyl 2-methyl-2-propenoate, octadecyl 2-methyl-2-propenoate and 2-propenal, graft (9CI) (CA INDEX NAME)

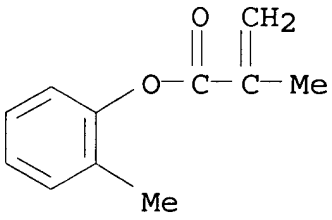
CM 1

CRN 143987-99-9
CMF C13 H28 O4 Si2



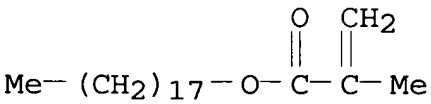
CM 2

CRN 74937-80-7
CMF C11 H12 O2



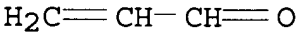
CM 3

CRN 32360-05-7
CMF C22 H42 O2



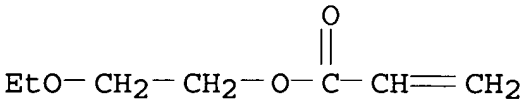
CM 4

CRN 107-02-8
CMF C3 H4 O



CM 5

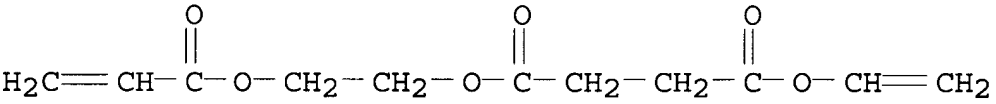
CRN 106-74-1
CMF C7 H12 O3



RN 188950-91-6 HCA
CN Butanedioic acid, bis[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 2-butenoic acid, 2-butoxyethyl 2-methyl-2-propenoate, ethenyl acetate, ethenyl 2-[(1-oxo-2-propenyl)oxy]ethyl butanedioate, ethenyl pentanoate, octadecyl 2-methyl-2-propenoate, phenylmethyl 2-methyl-2-propenoate, 2-propenoic acid and tridecyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

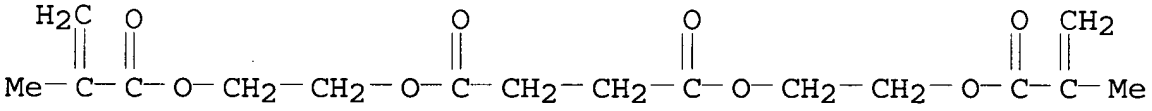
CM 1

CRN 120516-07-6
CMF C11 H14 O6



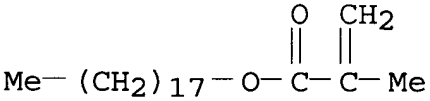
CM 2

CRN 48075-85-0
CMF C16 H22 O8



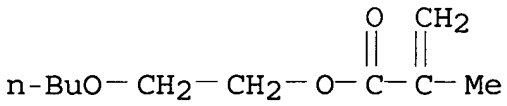
CM 3

CRN 32360-05-7
CMF C22 H42 O2



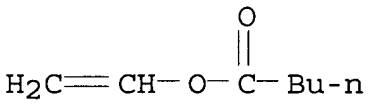
CM 4

CRN 13532-94-0
CMF C10 H18 O3



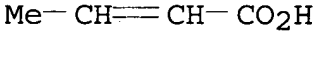
CM 5

CRN 5873-43-8
CMF C7 H12 O2



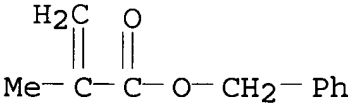
CM 6

CRN 3724-65-0
CMF C4 H6 O2



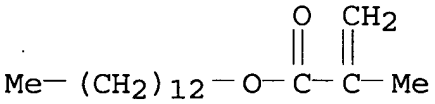
CM 7

CRN 2495-37-6
CMF C11 H12 O2



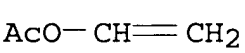
CM 8

CRN 2495-25-2
CMF C17 H32 O2



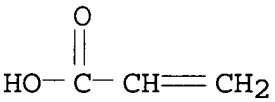
CM 9

CRN 108-05-4
CMF C4 H6 O2



CM 10

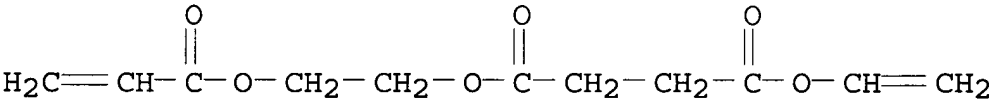
CRN 79-10-7
CMF C3 H4 O2



RN 188951-10-2 HCA
CN Butanedioic acid, ethenyl 2-[(1-oxo-2-propenyl)oxy]ethyl ester, polymer with ethenyl acetate, ethenyl propanoate and tridecyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

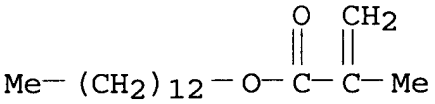
CM 1

CRN 120516-07-6
CMF C11 H14 O6



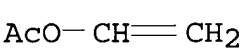
CM 2

CRN 2495-25-2
CMF C17 H32 O2



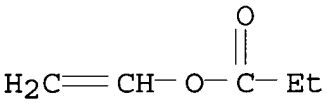
CM 3

CRN 108-05-4
CMF C4 H6 O2



CM 4

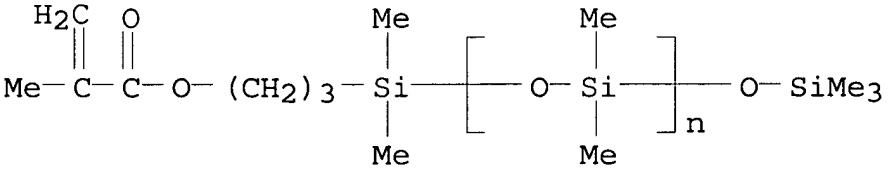
CRN 105-38-4
CMF C5 H8 O2



IT **186094-52-0**
(printing plate prepn. by electrophotog. toner image transfer process using primary receptors contg.)
RN 186094-52-0 HCA
CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with .alpha.-[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]-.omega.-[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)] and oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

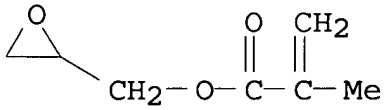
CM 1

CRN 123109-42-2
CMF (C2 H6 O Si)n C12 H26 O3 Si2
CCI PMS



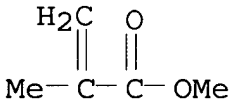
CM 2

CRN 106-91-2
CMF C7 H10 O3



CM 3

CRN 80-62-6
CMF C5 H8 O2



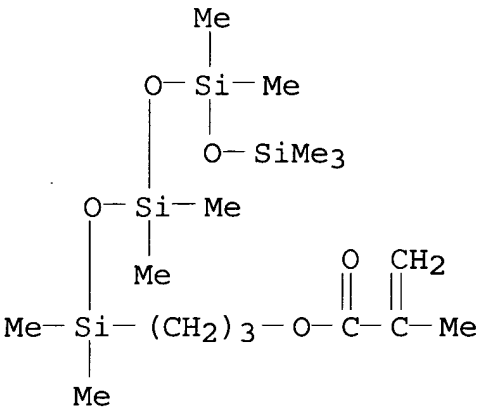
IT **176762-83-7 188951-15-7 188951-26-0,**
Methyl methacrylate-4-methylstyrene-3-(trimethoxysilyl)propyl methacrylate copolymer
(printing plate prepn. by toner image transfer process using electrophotog. photoreceptors contg.)

RN 176762-83-7 HCA

CN 2-Propenoic acid, 2-methyl-, 3-(nonamethyltetrasiloxanyl)propyl ester, polymer with oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

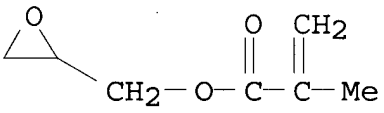
CM 1

CRN 77865-90-8
CMF C16 H38 O5 Si4



CM 2

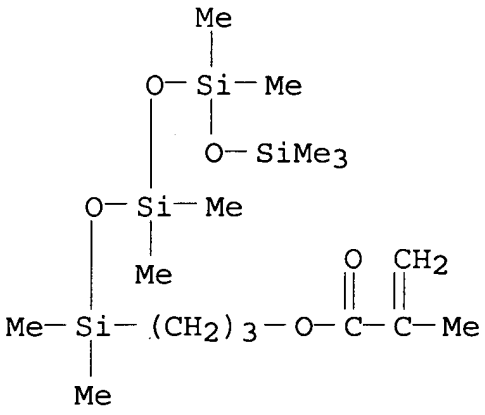
CRN 106-91-2
CMF C7 H10 O3



RN 188951-15-7 HCA
CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with 3-(nonamethyltetrasiloxanyl)propyl 2-methyl-2-propenoate and oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

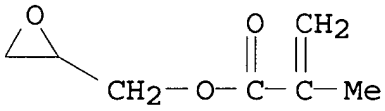
CM 1

CRN 77865-90-8
CMF C16 H38 O5 Si4



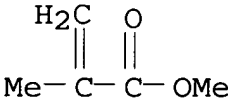
CM 2

CRN 106-91-2
CMF C7 H10 O3



CM 3

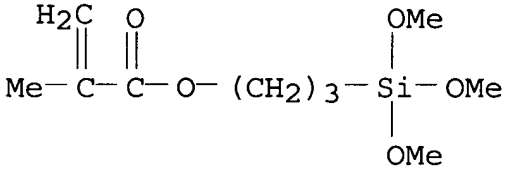
CRN 80-62-6
CMF C5 H8 O2



RN 188951-26-0 HCA
CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with 1-ethenyl-4-methylbenzene and 3-(trimethoxysilyl)propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

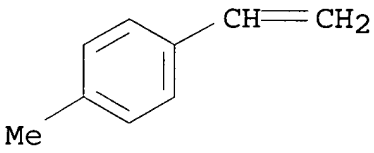
CM 1

CRN 2530-85-0
CMF C10 H20 O5 Si



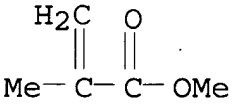
CM 2

CRN 622-97-9
CMF C9 H10



CM 3

CRN 80-62-6
CMF C5 H8 O2



IC ICM G03G013-28
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
IT 26616-87-5, 1,3-Butadiene-styrene-vinyl acetate copolymer 188950-63-2, Acrylic acid;benzyl methacrylate;bis(methacryoxyethyl) butandioate;2-butoxyethyl methacrylate;octadecyl methacrylate graft copolymer 188950-65-4, Acrylic acid;3-butoxypropyl methacrylate;hexadecyl methacrylate;octadecyl methacrylate;2-phenylethyl methacrylate graft copolymer 188950-67-6, 2-Carboxyethyl acrylate;2,3-diethoxypropyl methacrylate;dodecyl methacrylate;methyl methacrylate;5-[3-[(2-methyl-1-oxo-2-propenyl)oxy]-1-oxopropoxy]pentyl methacrylate graft copolymer 188950-68-7 188950-69-8 188950-70-1 188950-71-2 188950-73-4 188950-74-5 **188950-75-6** 188950-76-7 188950-77-8 188950-79-0 **188950-80-3**, Crotonic acid;ethenyl 2-[(1-oxo-2-propenyl)oxy]ethyl butanedioate;tridecyl

methacrylate;vinyl acetate;vinyl valerate graft copolymer
188950-82-5, Benzyl methacrylate;dodecyl methacrylate;2-[2-(hexyloxy)ethoxy]ethyl methacrylate;2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl 11-[(2-methyl-1-oxo-2-propenyl)amino]undecanoate; 2-sulfoethyl methacrylate graft copolymer 188950-83-6
188950-85-8 188950-86-9 188950-88-1 **188950-89-2**
188950-90-5 **188950-91-6** 188950-92-7 188950-93-8
188950-94-9 188950-95-0 188950-96-1 188950-97-2 188950-99-4
188951-00-0 188951-01-1 188951-02-2 188951-03-3 188951-04-4
188951-05-5 188951-06-6 188951-07-7 188951-08-8 188951-09-9
188951-10-2 189120-14-7 189890-33-3
(prepn. and use in prepg. transfer layers for electrophotog. photoreceptors for manuf. of printing plates)

IT 53192-53-3, Glycidyl methacrylate-methyl acrylate-methyl methacrylate copolymer **186094-52-0**
(printing plate prepn. by electrophotog. toner image transfer process using primary receptors contg.)

IT 85-44-9, Phthalic anhydride 574-93-6, Phthalocyanine 1314-13-2, Zinc oxide, uses 15008-36-3 17501-44-9, Zirconium acetylacetonate 28630-43-5, Glycidyl methacrylate-methacrylic acid-methyl methacrylate copolymer 30525-33-8, Acrylic acid-dodecyl methacrylate-methyl methacrylate copolymer 36034-82-9
113374-95-1 173783-73-8 **176762-83-7** 182559-23-5
188951-11-3 188951-14-6 **188951-15-7** 188951-17-9
188951-26-0, Methyl methacrylate-4-methylstyrene-3-(trimethoxysilyl)propyl methacrylate copolymer 188951-28-2
188951-30-6 188951-31-7 188951-32-8
(printing plate prepn. by toner image transfer process using electrophotog. photoreceptors contg.)

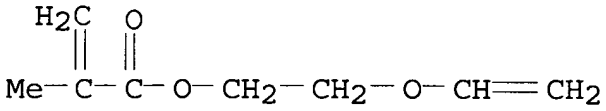
L33 ANSWER 14 OF 14 HCA COPYRIGHT 2006 ACS on STN
112:36564 Synthesis of some tailor-made poly(benzo-19-crown-6s) via cyclopolymerization of divinyl ether with hydrogen iodide/iodine initiator. Kakuchi, Toyoji; Kobayashi, Osamu; Nakaya, Daigo; Yokota, Kazuaki (Fac. Eng., Hokkaido Univ., Sapporo, 060, Japan). Polymer Journal (Tokyo, Japan), 21(8), 649-53 (English) 1989. CODEN: POLJB8. ISSN: 0032-3896.

AB Cationic cyclopolymn. of 1,2-bis[2-(2-vinyloxyethoxy)ethoxy]benzene (I) via a long-lived intermediate was achieved by the HI/iodine initiating system to give a polymer contg. benzo-19-crown-6 units. The mol. wt. distribution of the polymer was relatively narrow as Mw/Mn .ltoreq. 1.4 when prepd. in CH2Cl2 at -60 and -72.degree.. The d.p. agreed with the predicted value for [I]/[HI] ratios <10. A poly(crown ether) with a reactive end group could be prepd. through the polymn. of I initiated with iodine and the hydroiodinated adduct of a monovinyl ether, i.e., a dimethylmethoxysilyl-capped polymer from dimethylmethoxy[4-(2-vinyloxyethoxy)phenyl]silane and a macromonomer from 2-(vinyloxy)ethyl methacrylate.

IT **1464-69-3DP**, 2-Vinyloxyethyl methacrylate, reaction products with bis[(vinyloxyethoxy)ethoxy]benzene homopolymer **124761-96-2DP**, reaction products with bis[(vinyloxyethoxy)ethoxy]benzene homopolymer
(prepn. of, catalysts for)

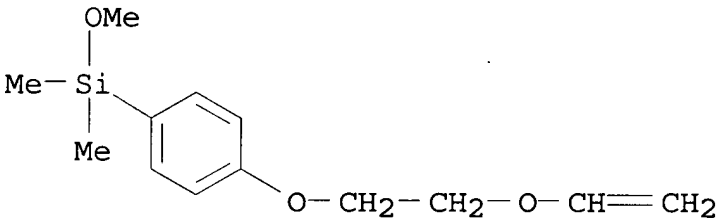
RN 1464-69-3 HCA

CN 2-Propenoic acid, 2-methyl-, 2-(ethenyloxy)ethyl ester (9CI) (CA INDEX NAME)



RN 124761-96-2 HCA

CN Silane, [4-[2-(ethenyloxy)ethoxy]phenyl]methoxydimethyl- (9CI) (CA INDEX NAME)



CC 35-4 (Chemistry of Synthetic High Polymers)

IT **1464-69-3DP**, 2-Vinyloxyethyl methacrylate, reaction products with bis[(vinyloxyethoxy)ethoxy]benzene homopolymer 124701-16-2DP, reaction products with vinyloxyethyl compds. **124761-96-2DP**, reaction products with bis[(vinyloxyethoxy)ethoxy]benzene homopolymer
(prepn. of, catalysts for)